

<https://indico.in2p3.fr/event/24931/>

SIMDET 2021

4th school on silicon detectors simulation



SIMDET 2021, 29 November – 1 December 2021, LPNHE Paris



Introduction to Silicon Detectors

with focus on applications at Hadron Colliders

Michael Moll, CERN EP-DT, Geneva, Switzerland

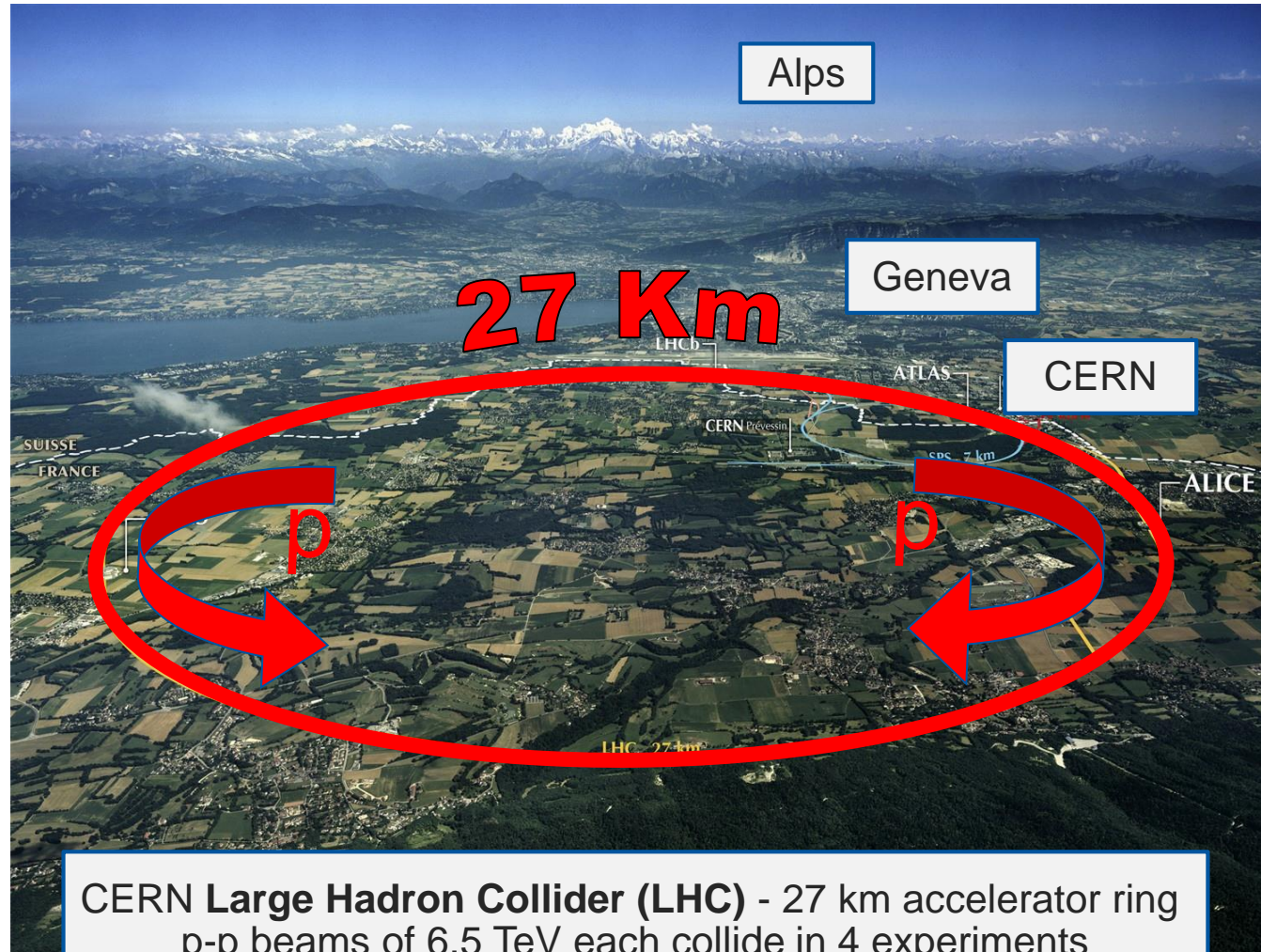
OUTLINE



- **The Large Hadron Collider (LHC) at CERN**
 - Where are the silicon detectors?
- **Silicon Detectors for High Energy Physics Applications**
 - The basic concept of Semiconductor Detectors: A reverse biased pn-junction
 - Strip and Pixel Detectors at the Large Hadron Collider (LHC) at CERN
 - Recent developments in Silicon Detectors
 - MAPS sensors and sensors with intrinsic gain for fast timing applications
- **Radiation Damage to Silicon Detectors**
 - Upgrade of the Large Hadron Collider (HL-LHC)
 - Radiation damage mechanisms
 - Microscopic defects and macroscopic damage
 - Mitigation techniques: What can we do against radiation damage?
 - Examples of radhard devices for the HL-LHC: p-type strip sensors and 3D sensors
- **Why do we need (TCAD) device simulations (introduction)?**
- **Summary & Further reading**

Details in following presentations:
Magdalena Munker; Marco Bomben;
Matteo C.Vignali, David Flores, Alex Bähr

CERN & LHC - Large Hadron Collider



CERN Large Hadron Collider (LHC) - 27 km accelerator ring
p-p beams of 6.5 TeV each collide in 4 experiments

Also a program with Pb beams at 6.5 Z TeV

• CERN:

- 23 member states
- ~14000 scientists (Users)
- ~ 2600 personnel
- Budget ~1200 MCHF

• LHC: 27 km tunnel

- ≈ 4000 MCHF (machine+experiments)
- 1232 dipoles $B=8.3T$
- Design: pp $\sqrt{s} = 14$ TeV
 $L_{\text{design}} = 10^{34} \text{ cm}^{-2} \text{ s}^{-1}$
Heavy ions (e.g. Pb-Pb; 5TeV)

• Circulating beams:

2008: first beam

2012: Run 1 at 2 x 4 TeV

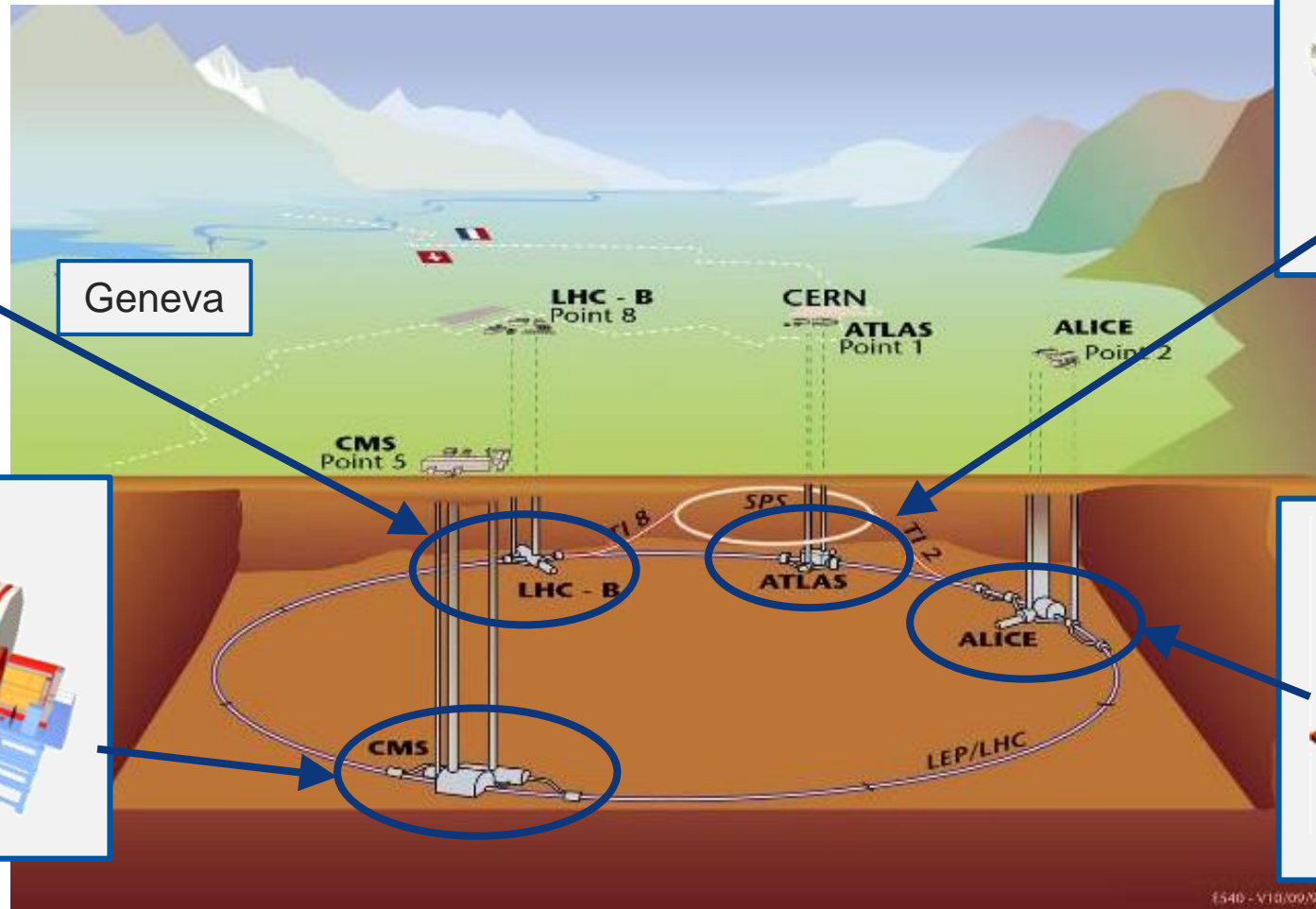
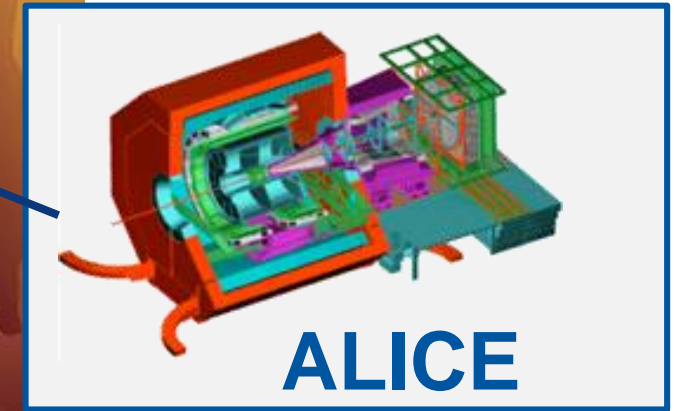
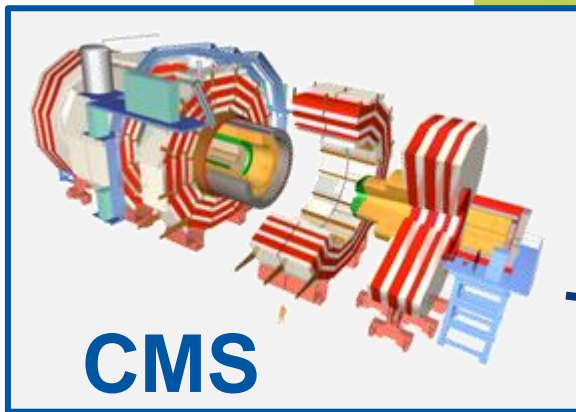
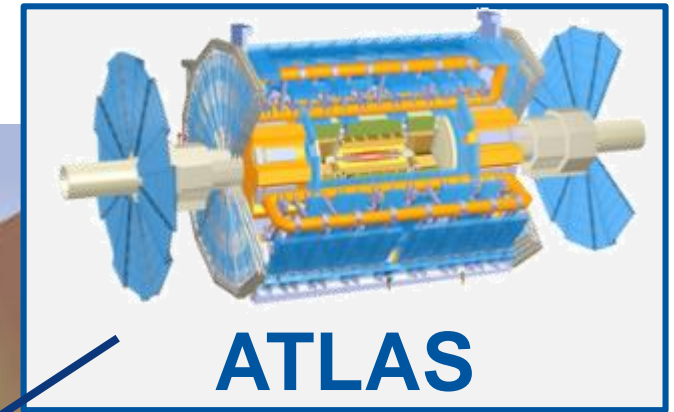
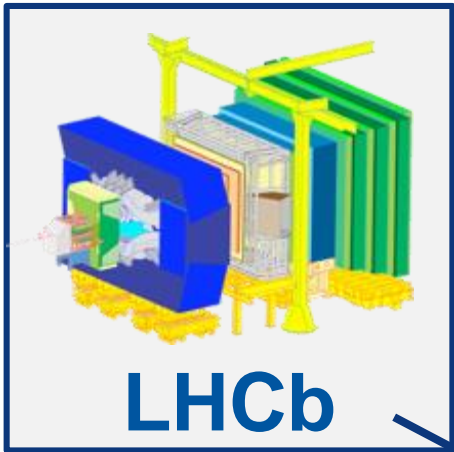
2015: Run 2 at 2 x 6.5 TeV

2016: Reaching $10^{34} \text{ cm}^{-2} \text{ s}^{-1}$

2018: LS2; 2022: Run 3

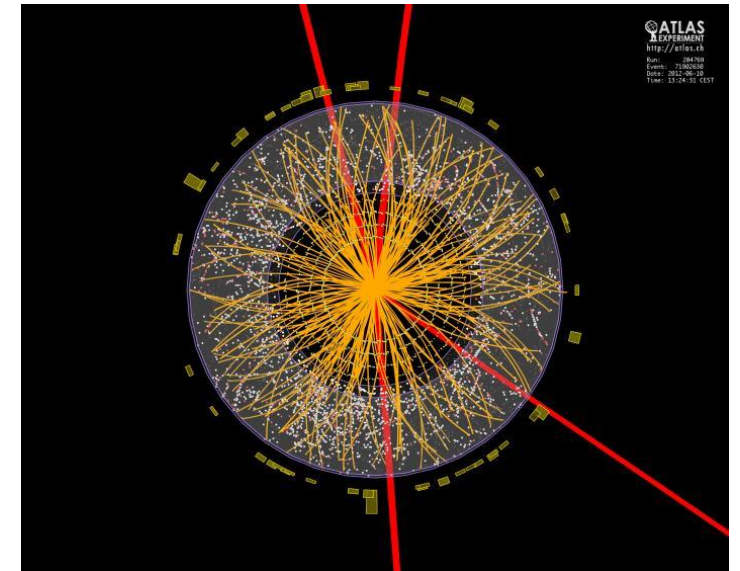
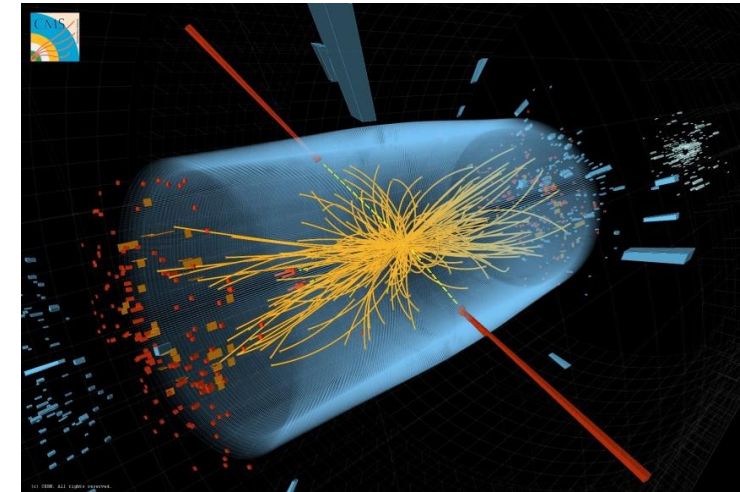
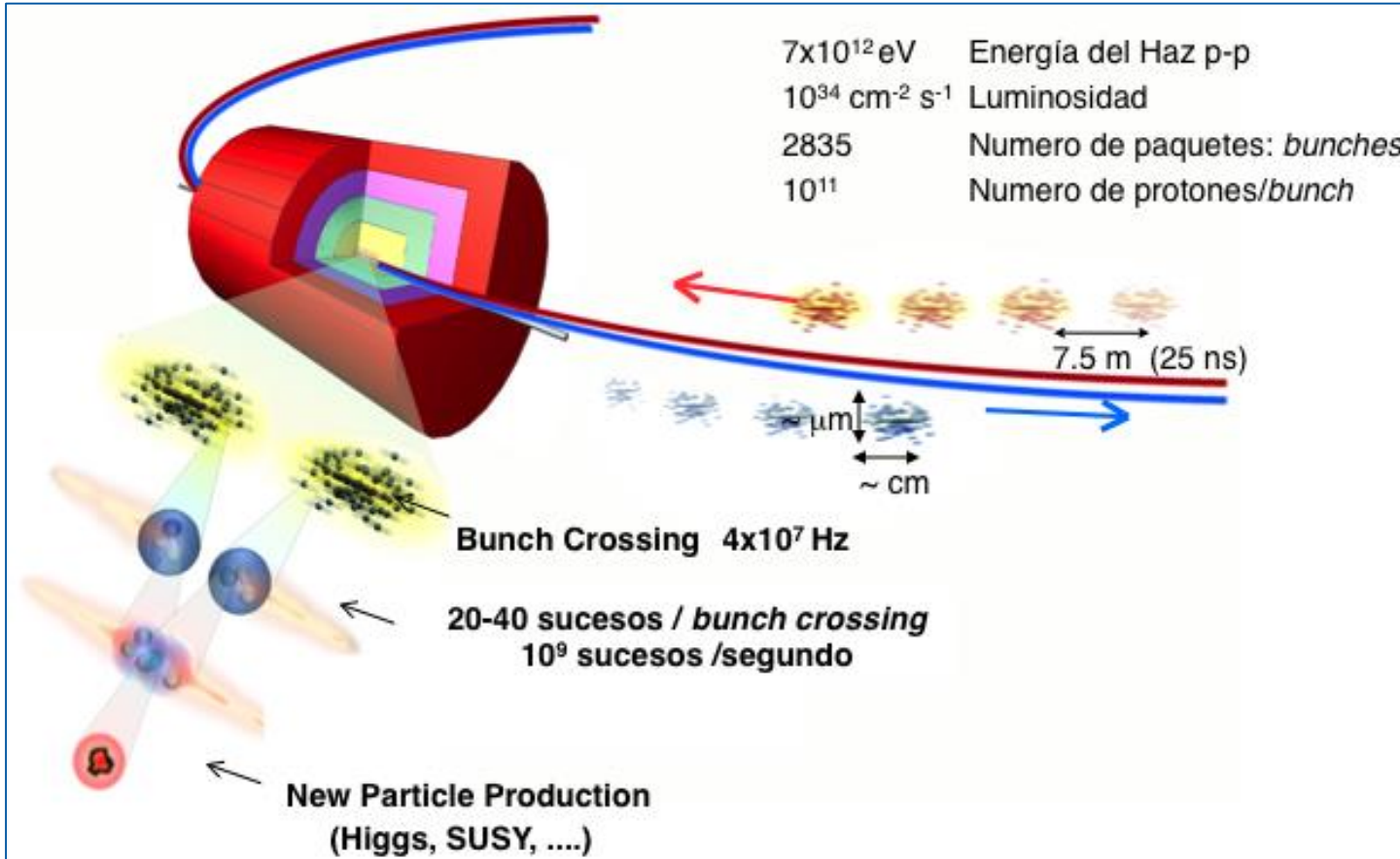
2025: LS3; **2027: HL-LHC**

The LHC Experiments



E540 - V18/09/97

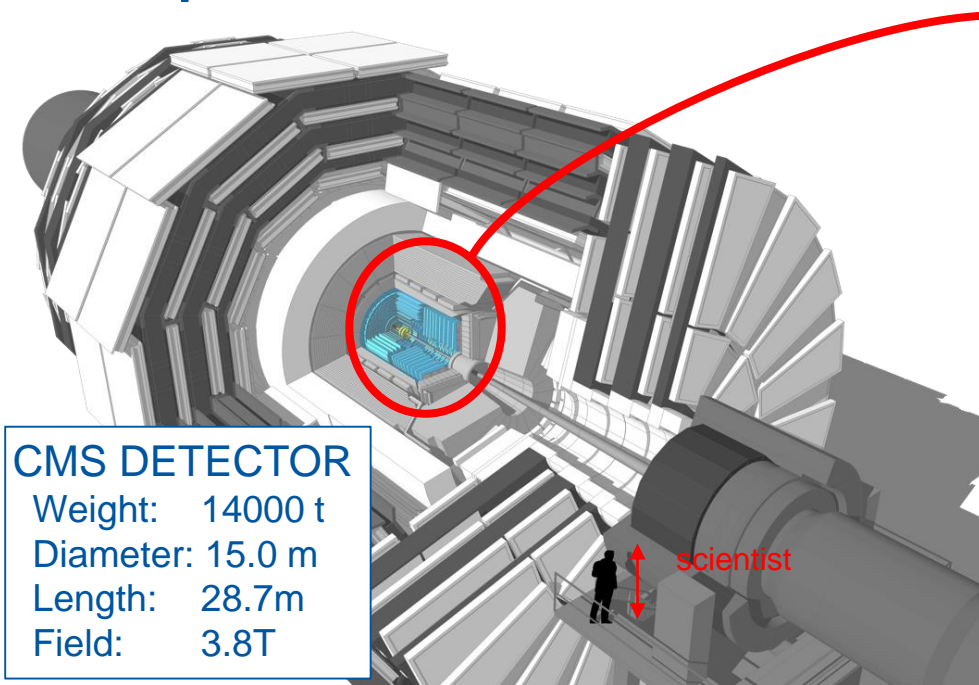
Collisions in the LHC



Silicon Tracking Detector



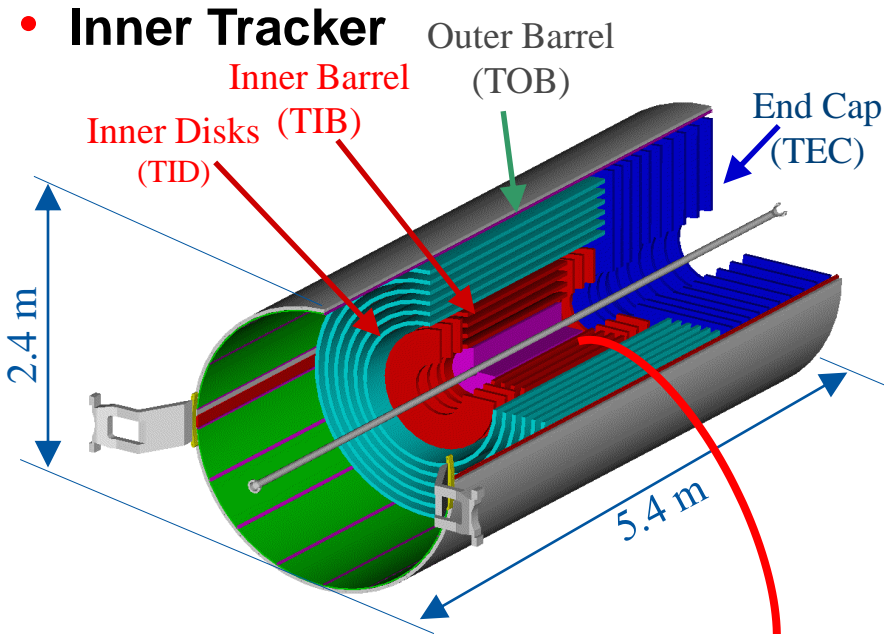
- LHC example: The CMS DETECTOR



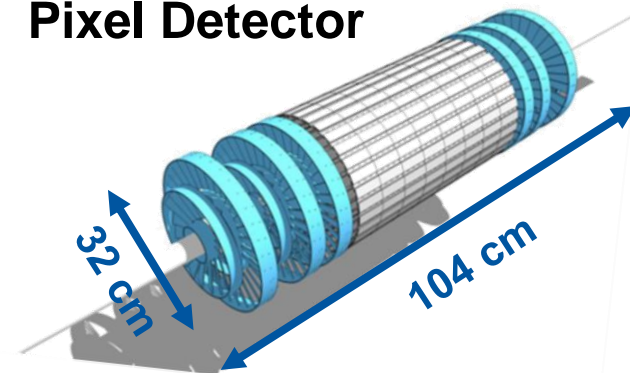
CMS DETECTOR
Weight: 14000 t
Diameter: 15.0 m
Length: 28.7m
Field: 3.8T

- CMS – Inner Tracker & Pixel Detector

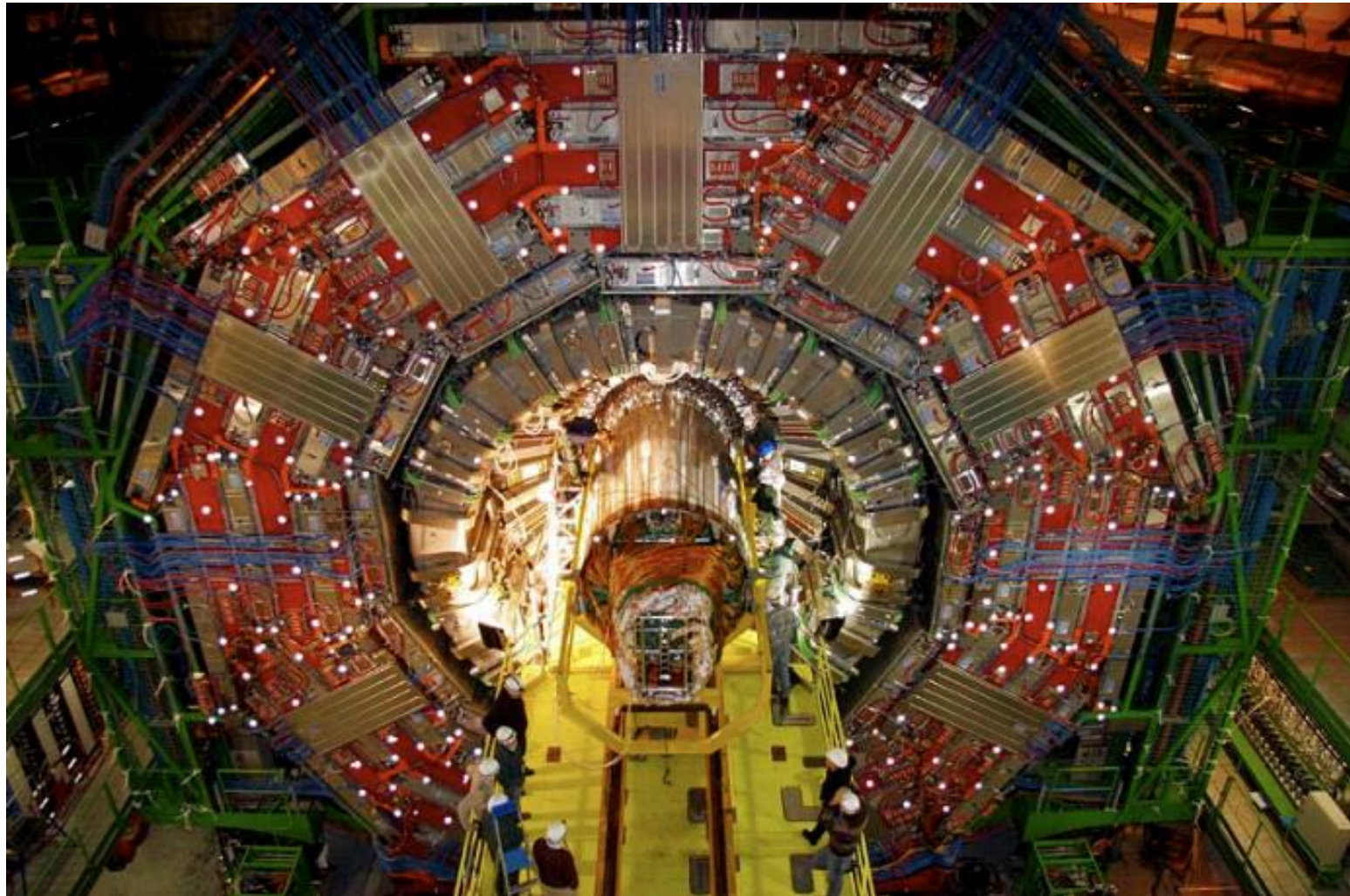
- **Micro Strip:**
 - ~ 214 m² of silicon strip sensors, 11.4 million strips
- **Pixel:**
 - 4 layers & 2 x 3 disks: silicon pixels (~ 1m²)
 - 124 million pixels (100x150μm²)
 - Resolution: $\sigma(r\phi) \sim 10 \mu\text{m}$, $\sigma(z) \sim 25\mu\text{m}$



- Pixel Detector



Present LHC Tracking Sensors



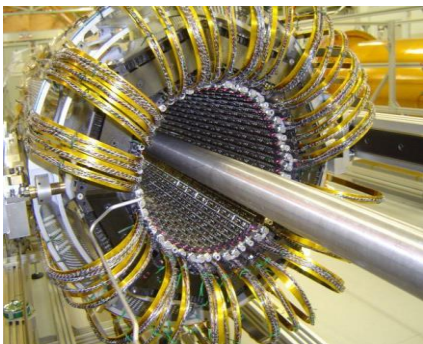
CMS Tracker insertion

December 2007

Silicon Tracking Detectors



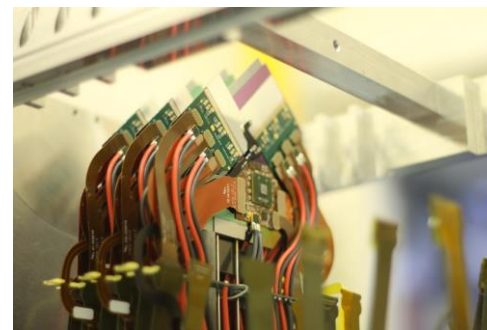
Silicon tracking detectors are used in almost all HEP experiments:
Different sensor technologies, designs, operating conditions,....



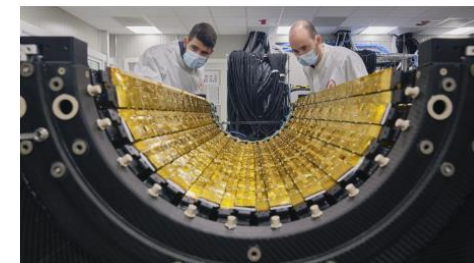
ATLAS Pixel Detector



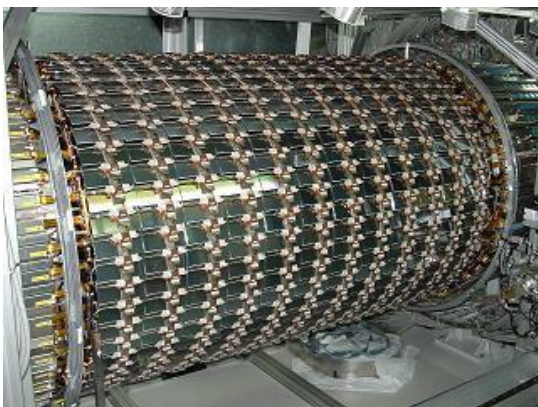
CMS Pixel Detector



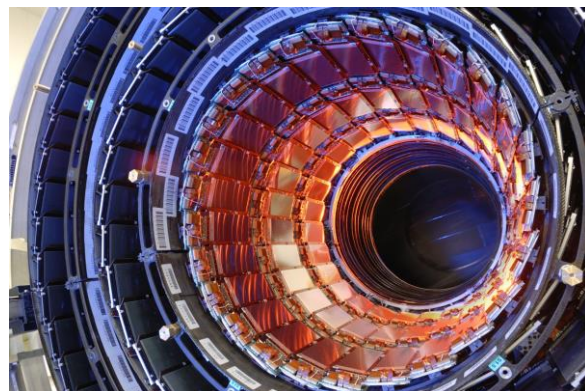
LHCb VELO (New Velo for Run3:2022)



ALICE ITS Barrel
New ITS for Run3:2022)



ATLAS SCT Barrel



CMS Strip Tracker IB



LHCb VELO (New Velo for Run3:2022)



ALICE ITS Outer Barrel
(Insertion Test 2021)

Silicon Sensors

Solid State Detectors – Why Silicon?



• Some characteristics of Silicon crystals

- **Small band gap** $E_g = 1.12 \text{ eV} \Rightarrow E(\text{e-h pair}) = 3.6 \text{ eV}$ ($\approx 30 \text{ eV}$ for gas detectors)
- **High specific density** 2.33 g/cm^3 ; dE/dx (M.I.P.) $\approx 3.8 \text{ MeV/cm} \approx 106 \text{ e-h}/\mu\text{m}$ (average)
- **High carrier mobility** $\mu_e = 1450 \text{ cm}^2/\text{Vs}$, $\mu_h = 450 \text{ cm}^2/\text{Vs}$ \Rightarrow fast charge collection ($< 10 \text{ ns}$)
- **Very pure** $< 1 \text{ ppm}$ impurities and $< 0.1 \text{ ppb}$ electrical active impurities
- **Rigidity** of silicon allows thin self supporting structures
- **Detector production by microelectronic techniques**
 \Rightarrow well known industrial technology, relatively low price, small structures easily possible

• Alternative semiconductors

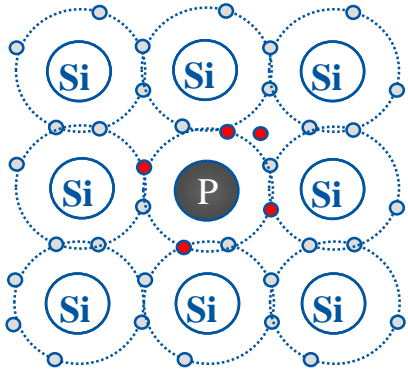
- **Diamond**
- Gallium arsenide (GaAs)
- Gallium nitride (GaN)
- **Silicon Carbide (SiC)**
- Germanium (Ge)

	Diamond	SiC (4H)	GaAs	Si	Ge
Atomic number Z	6	14/6	31/33	14	32
Bandgap E_g [eV]	5.5	3.3	1.42	1.12	0.66
$E(\text{e-h pair})$ [eV]	13	7.6-8.4	4.3	3.6	2.9
density [g/cm^3]	3.52	3.22	5.32	2.33	5.32
e-mobility μ_e [cm^2/Vs]	1800	800	8500	1450	3900
h-mobility μ_h [cm^2/Vs]	1200	115	400	450	1900

Doping, resistivity and p-n junction



e.g. Phosphorus



- resistivity ρ**

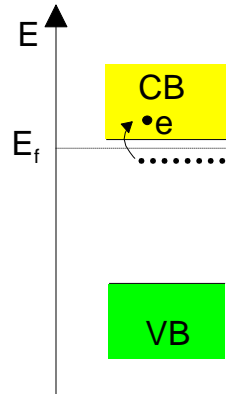
- carrier concentration n, p
- carrier mobility μ_n, μ_p

$$\rho = \frac{1}{q_0(\mu_n n + \mu_p p)}$$

	detector grade	electronics grade
doping	$\approx 10^{12} \text{ cm}^{-3}$	$\approx 10^{17} \text{ cm}^{-3}$
resistivity ρ	$\approx 5 \text{ k}\Omega\cdot\text{cm}$	$\approx 1 \text{ }\Omega\cdot\text{cm}$

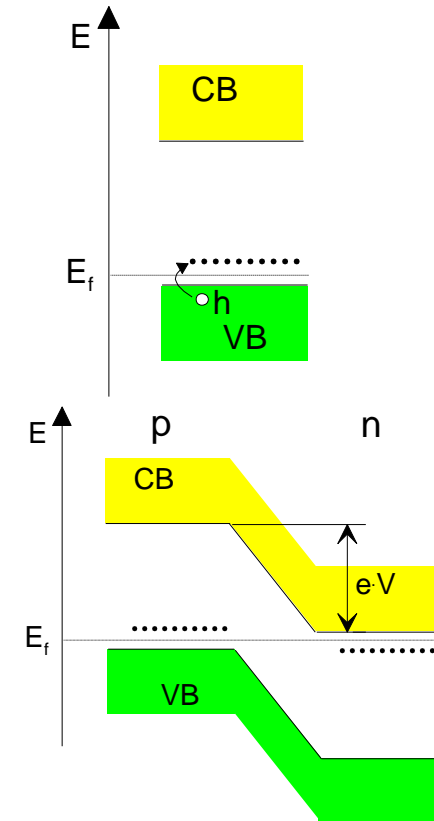
- Doping: n-type silicon**

- add elements from Vth group \Rightarrow **donors** (P, As,..)
- electrons are majority carriers



- Doping: p-type silicon**

- add elements from IIIrd group \Rightarrow **acceptors** (B,..)
- holes are majority carriers



- p-n junction**

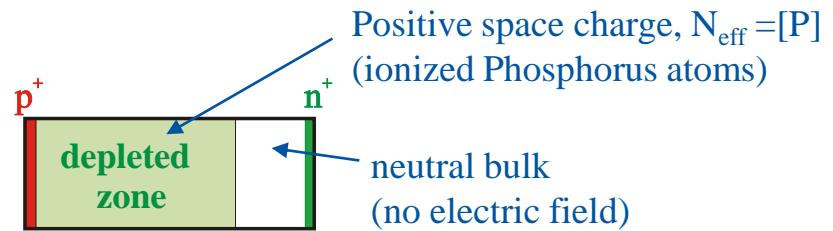
There must be a single Fermi level!

- \Rightarrow band structure deformation
- \Rightarrow potential difference
- \Rightarrow depleted zone

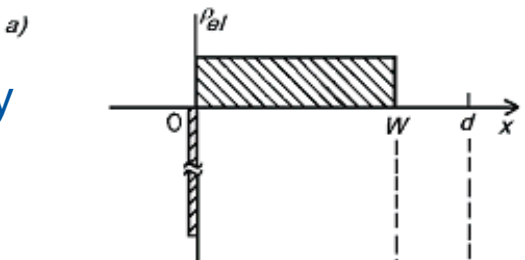
Reverse biased p-n junction

Poisson's equation

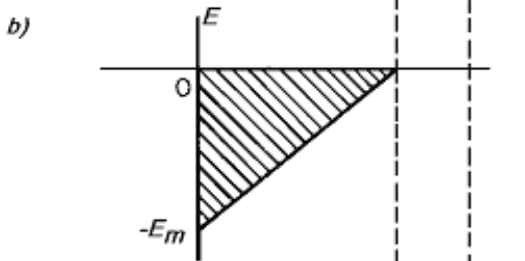
$$-\frac{d^2}{dx^2} \phi(x) = \frac{q_0}{\epsilon\epsilon_0} \cdot N_{eff}$$



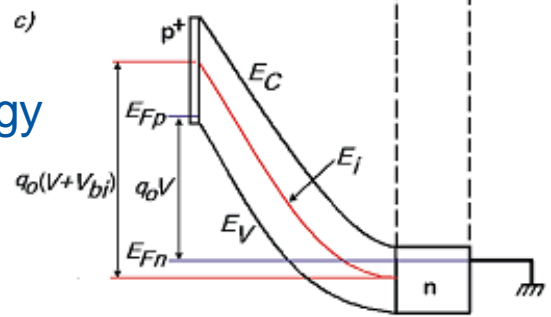
Electrical charge density



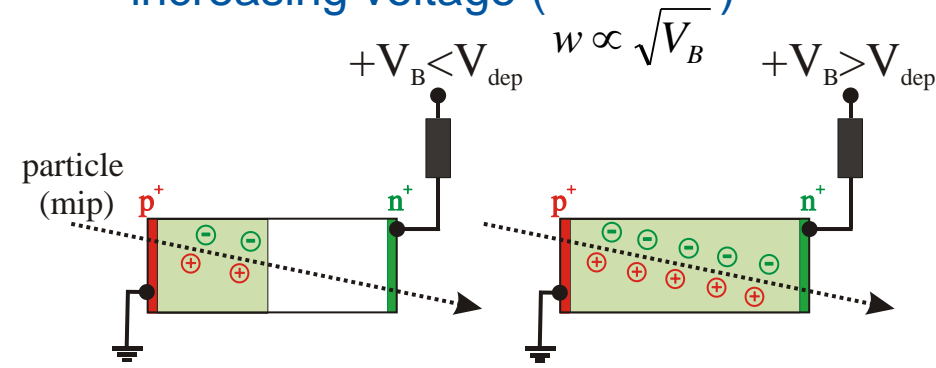
Electrical field strength



Electron potential energy



- Depleted zone growth with increasing voltage ($W \propto \sqrt{V_B}$)



- Full charge collection only for fully depleted detector ($V_B > V_{dep}$)

depletion voltage V_{dep}

detector thickness d

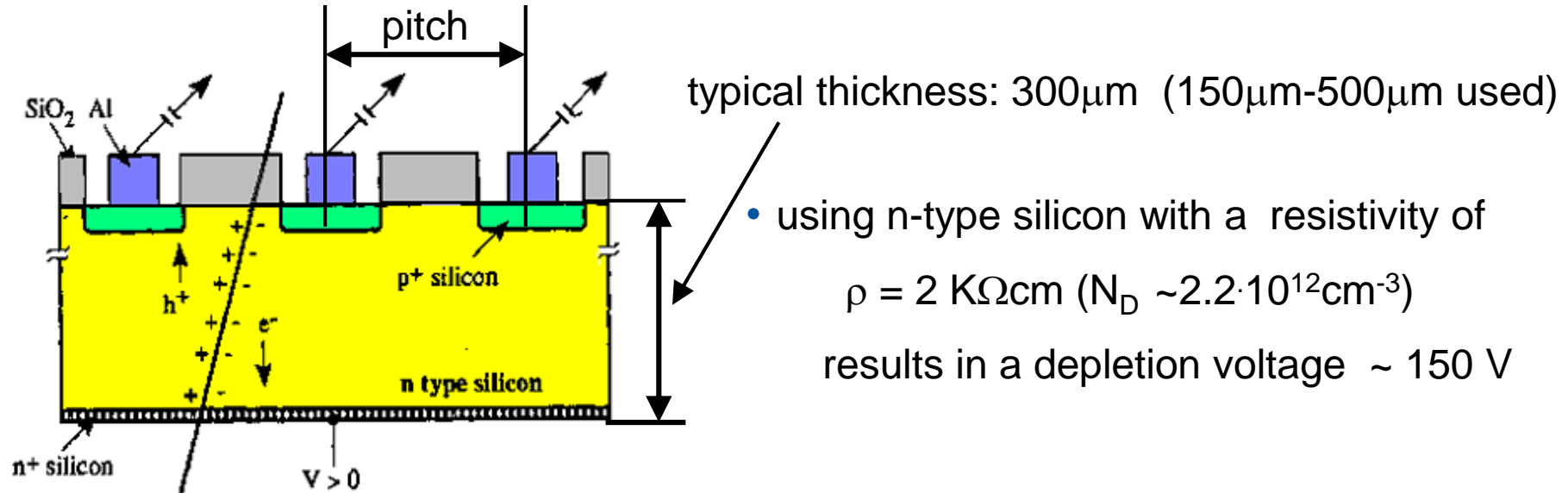
$$V_{dep} = \frac{q_0}{\epsilon\epsilon_0} \cdot |N_{eff}| \cdot d^2$$

effective space charge density N_{eff}

Single Sided Strip Detector



- Segmentation of the p⁺ layer into strips (Diode Strip Detector) and connection of strips to individual read-out channels gives spatial information



- using n-type silicon with a resistivity of $\rho = 2 \text{ K}\Omega\text{cm}$ ($N_D \sim 2.2 \cdot 10^{12} \text{cm}^{-3}$) results in a depletion voltage $\sim 150 \text{ V}$

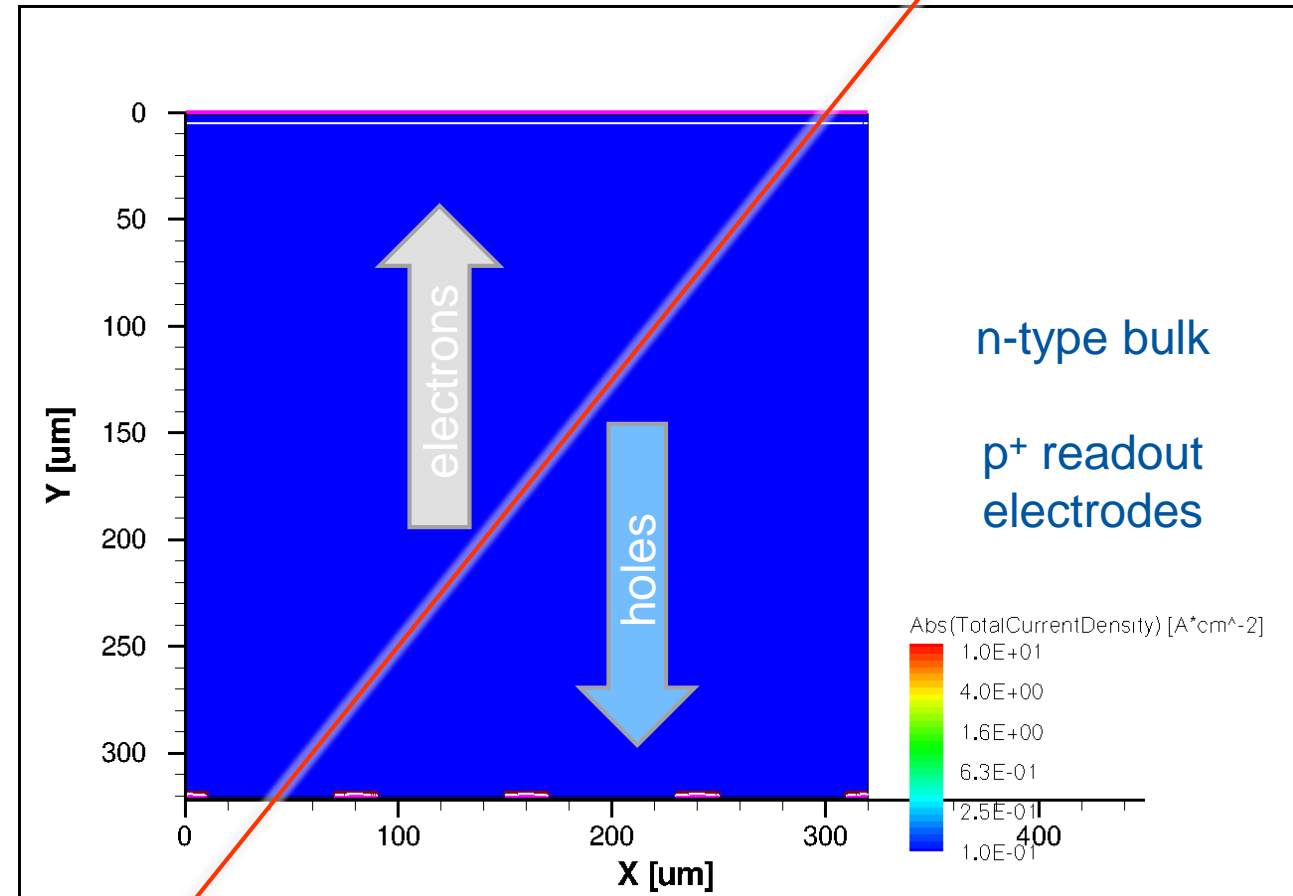
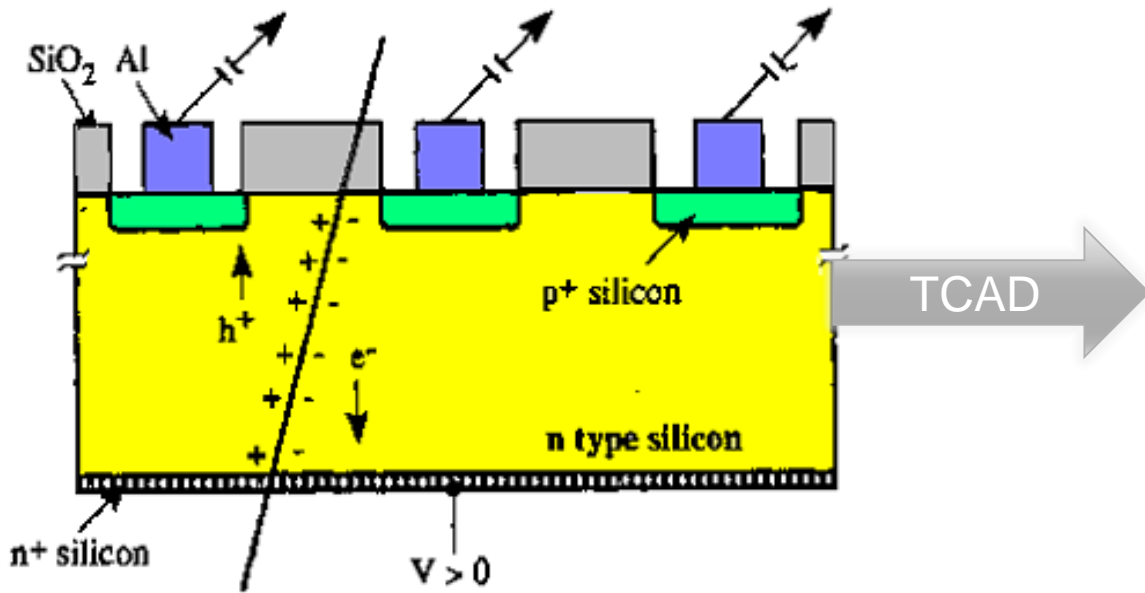
- Resolution σ depends on the pitch p (distance from strip to strip)
 - e.g. detection of charge in binary way (threshold discrimination) and using center of strip as measured coordinate results in

$$\sigma = \frac{p}{\sqrt{12}}$$

typical pitch values are 20 μm– 150 μm \Rightarrow 50 μm pitch results in 14.4 μm resolution

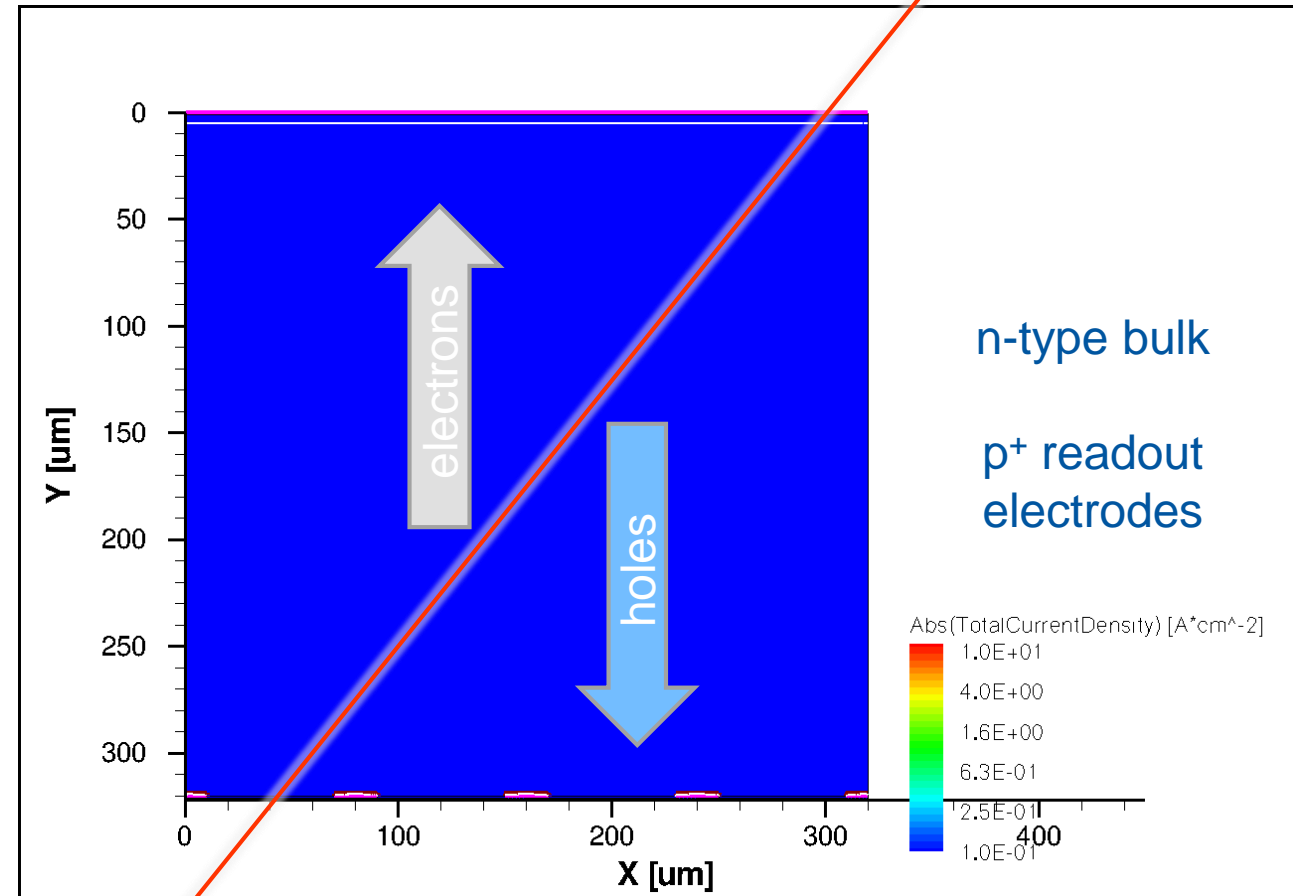
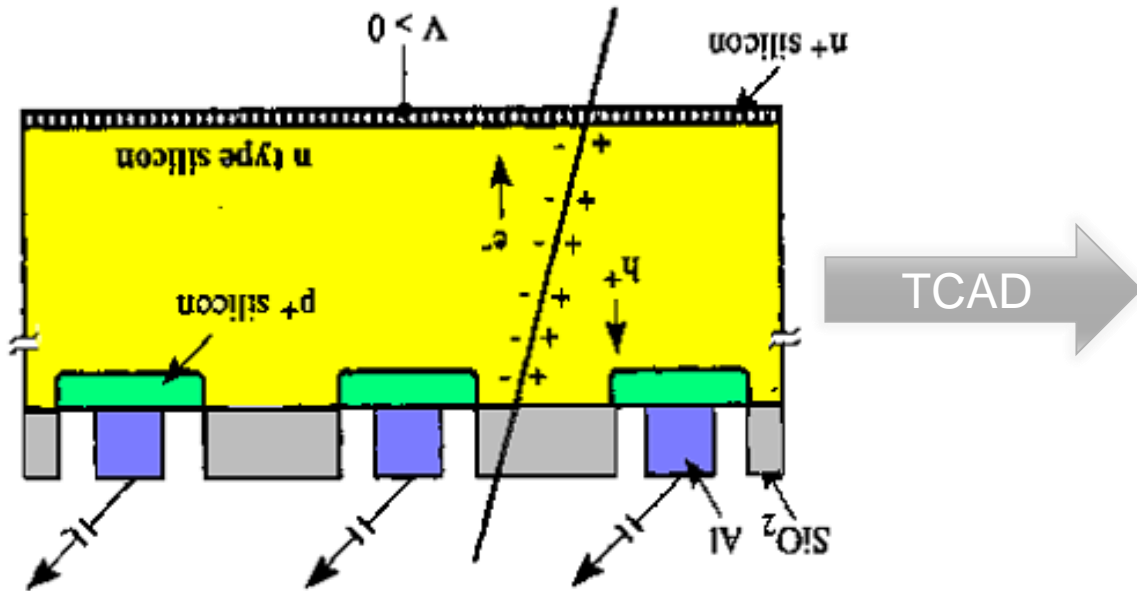
Signal Formation in a strip sensor

- TCAD simulation: minimum ionizing particle traversing the sensor
 - with typical dimensions for presently operating large LHC trackers (p-in-n devices)



Signal Formation in a strip sensor

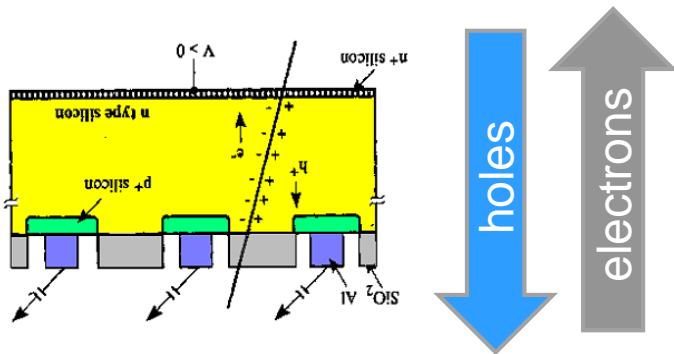
- TCAD simulation: minimum ionizing particle traversing the sensor
 - with typical dimensions for presently operating large LHC trackers (p-in-n devices)



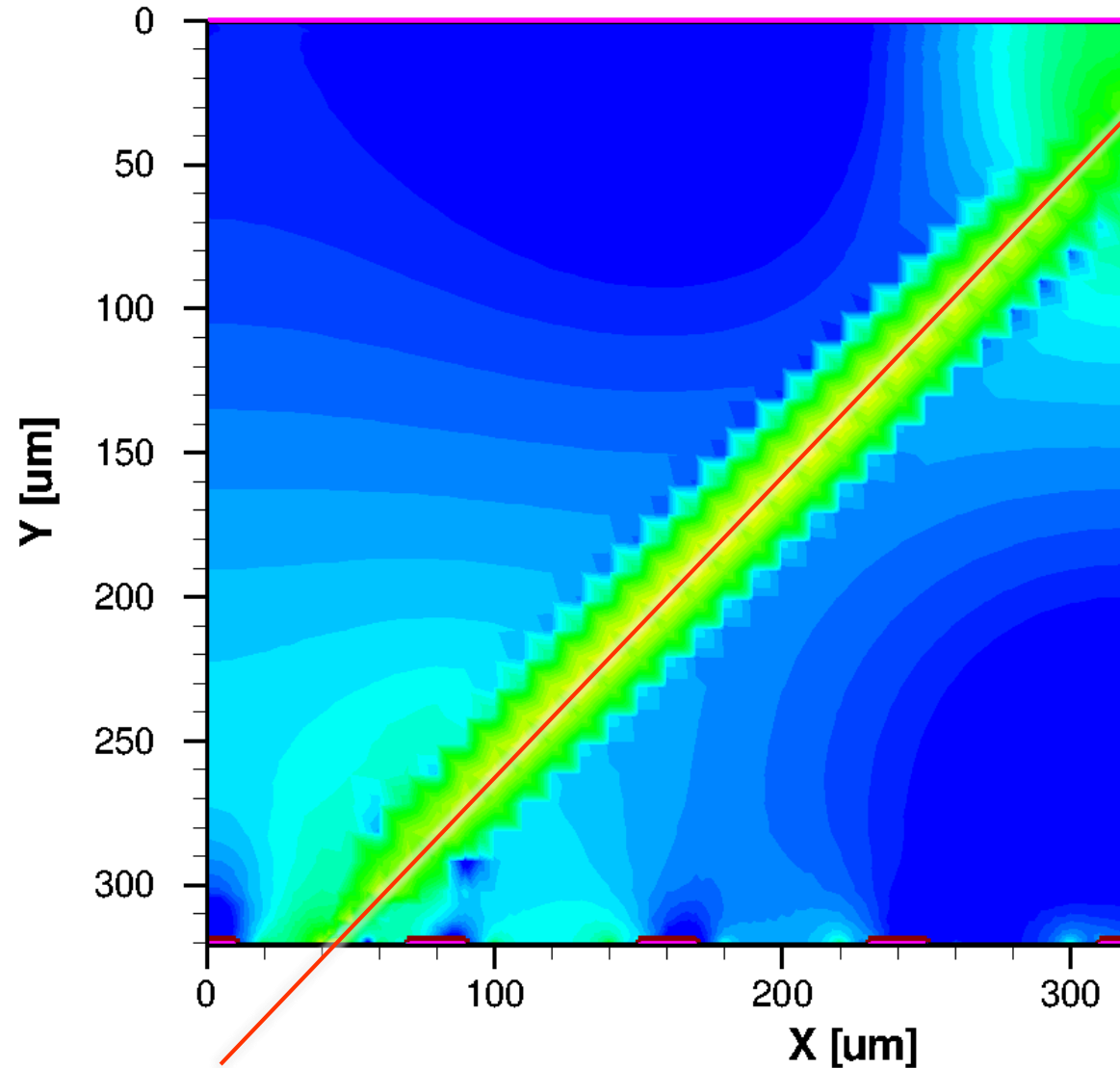
Signal formation in a strip sensor



- Simulation:
 - Current density
 - mip, 45° angle

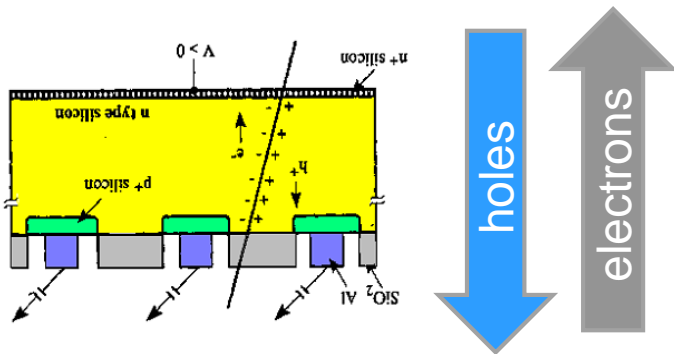


t = 1 ns

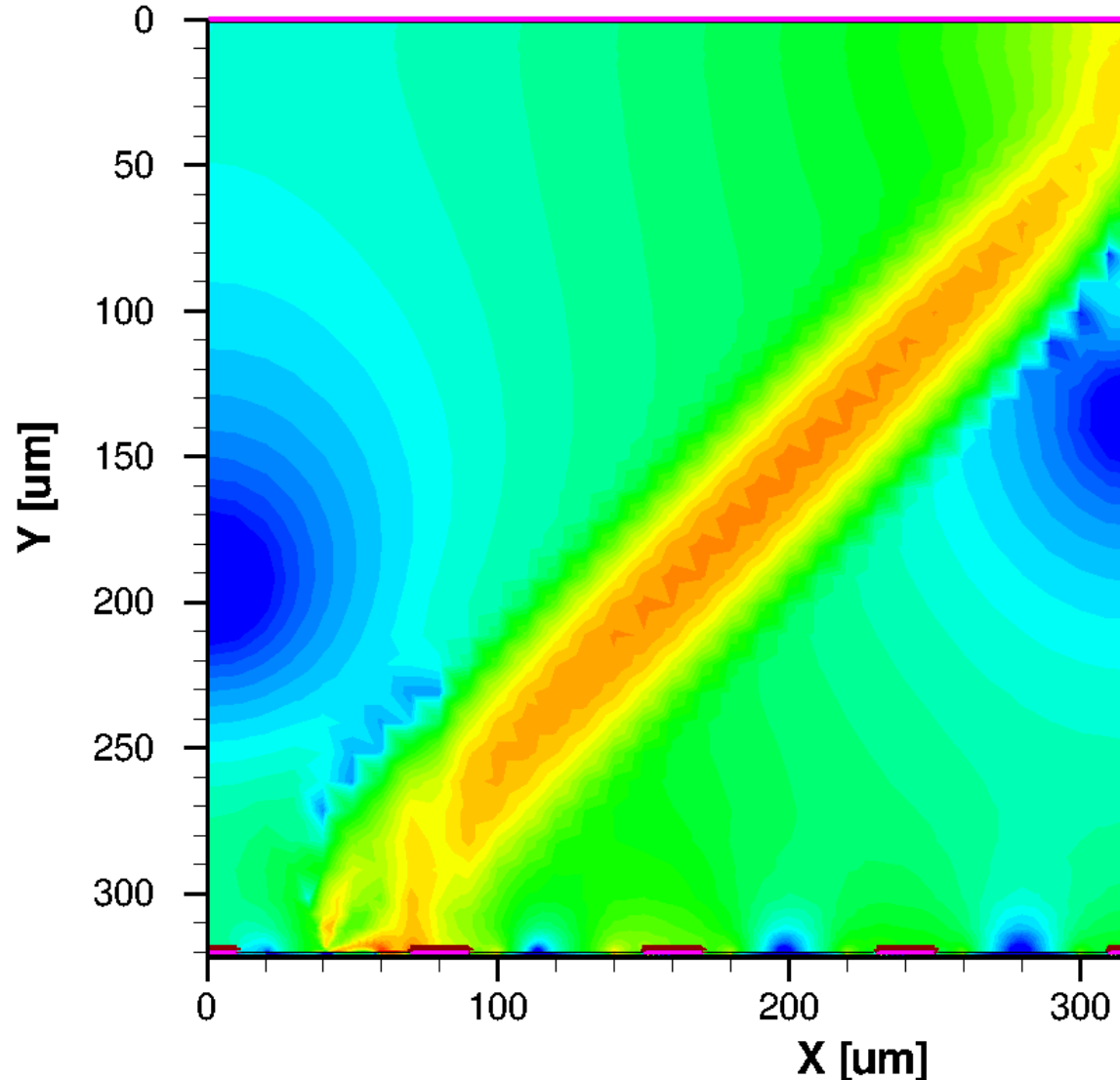


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

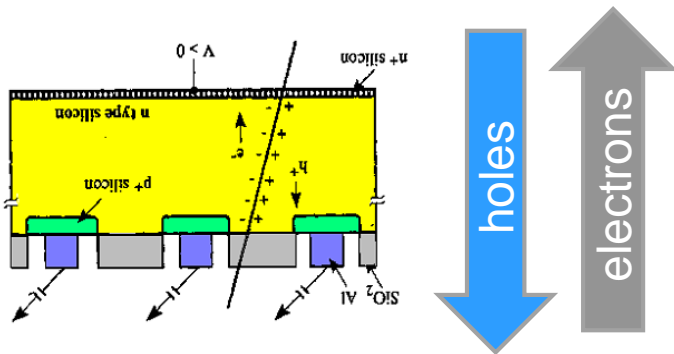


t = 1.2 ns

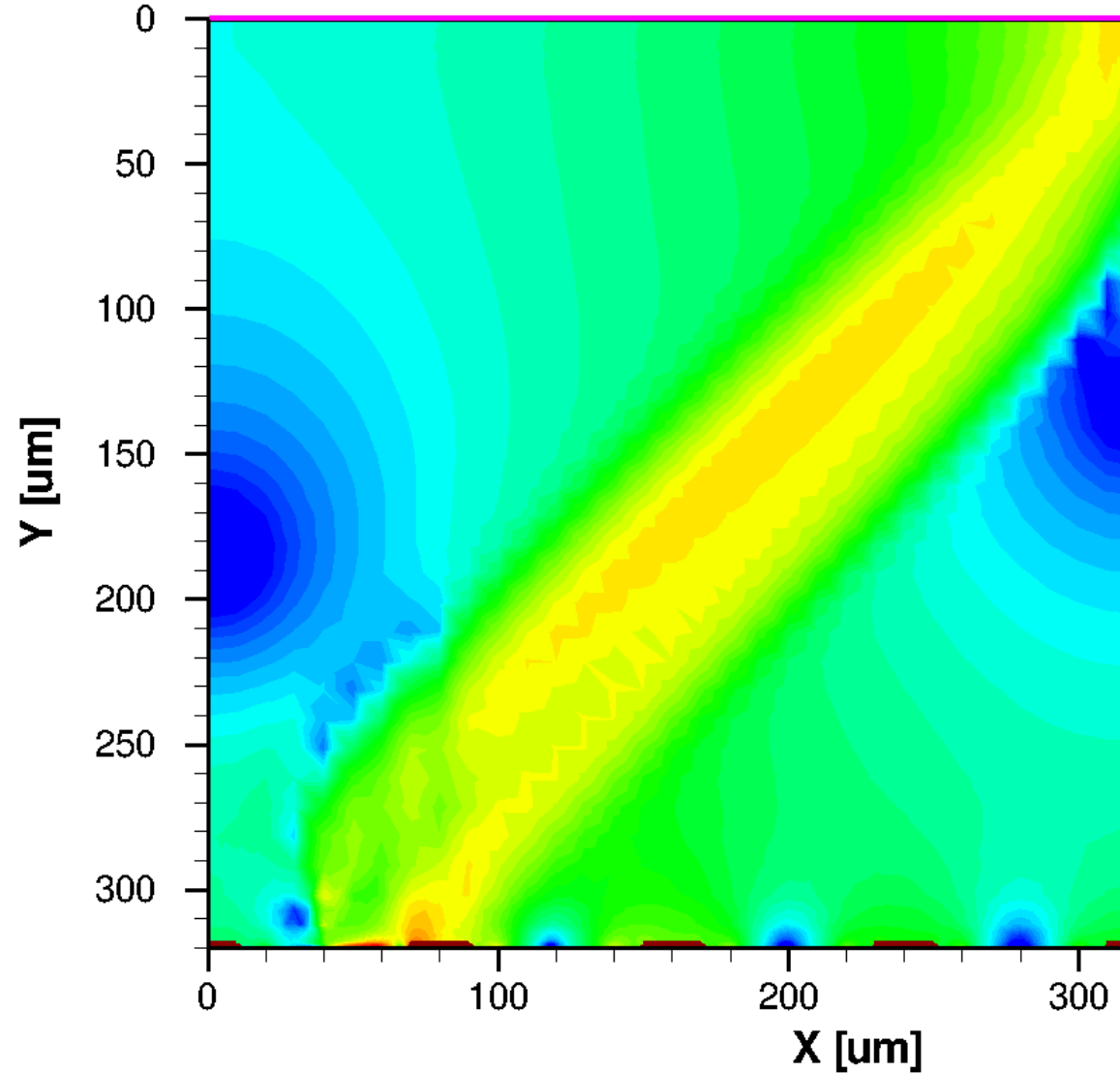


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

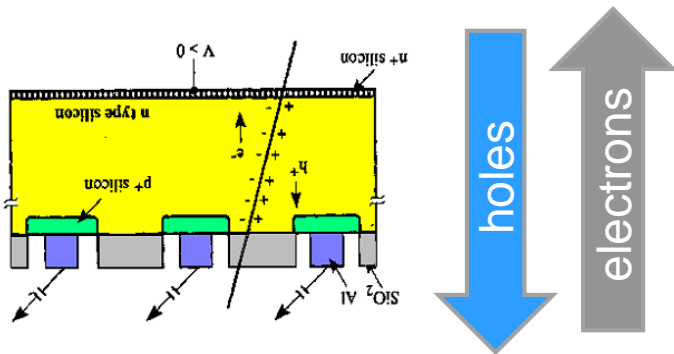


t = 1.4 ns

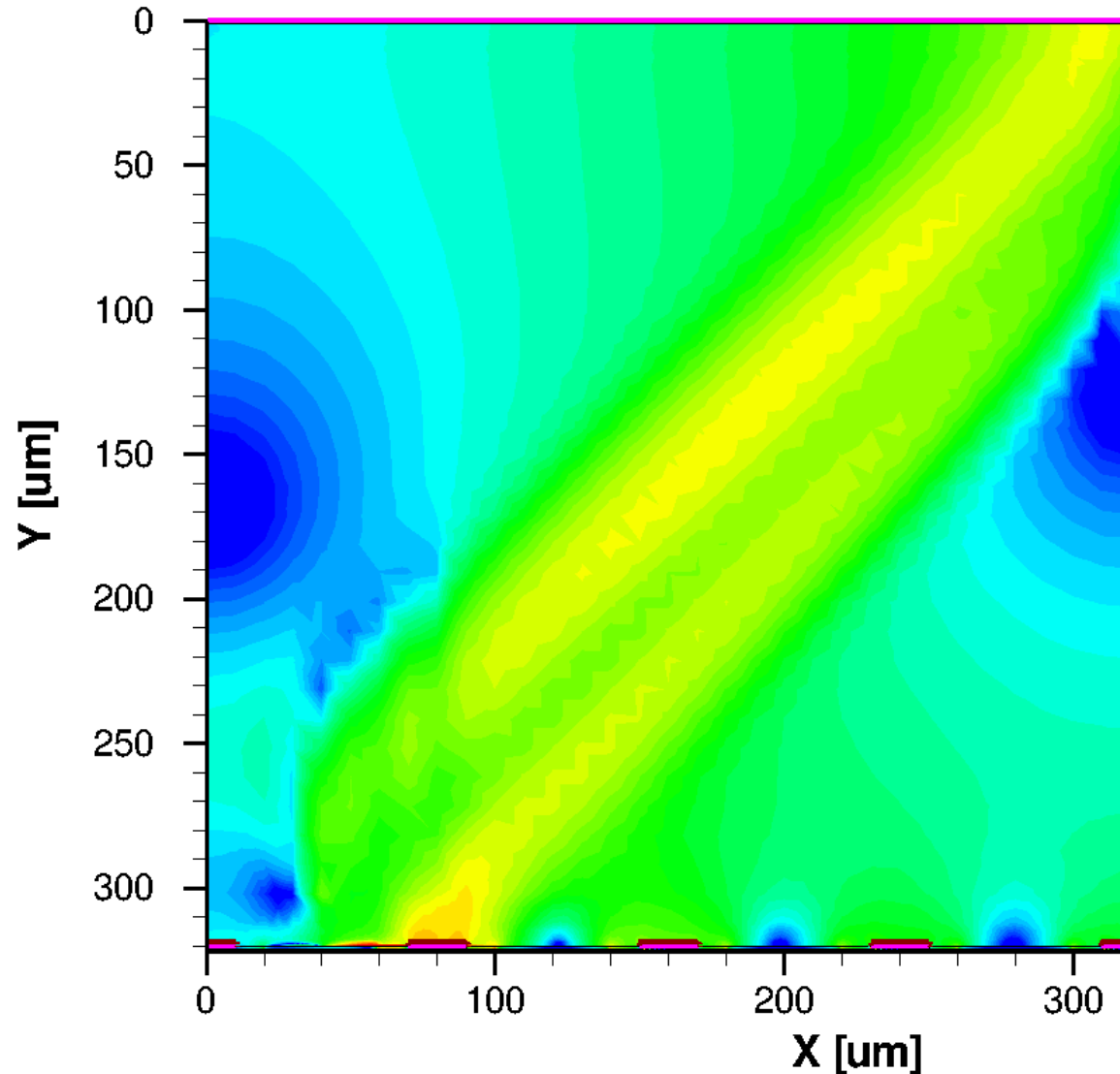


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

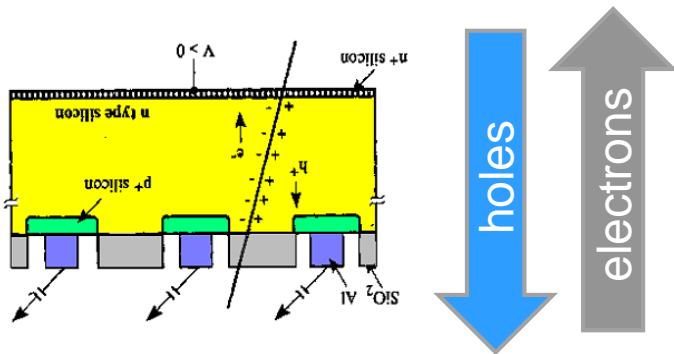


t = 1.6 ns

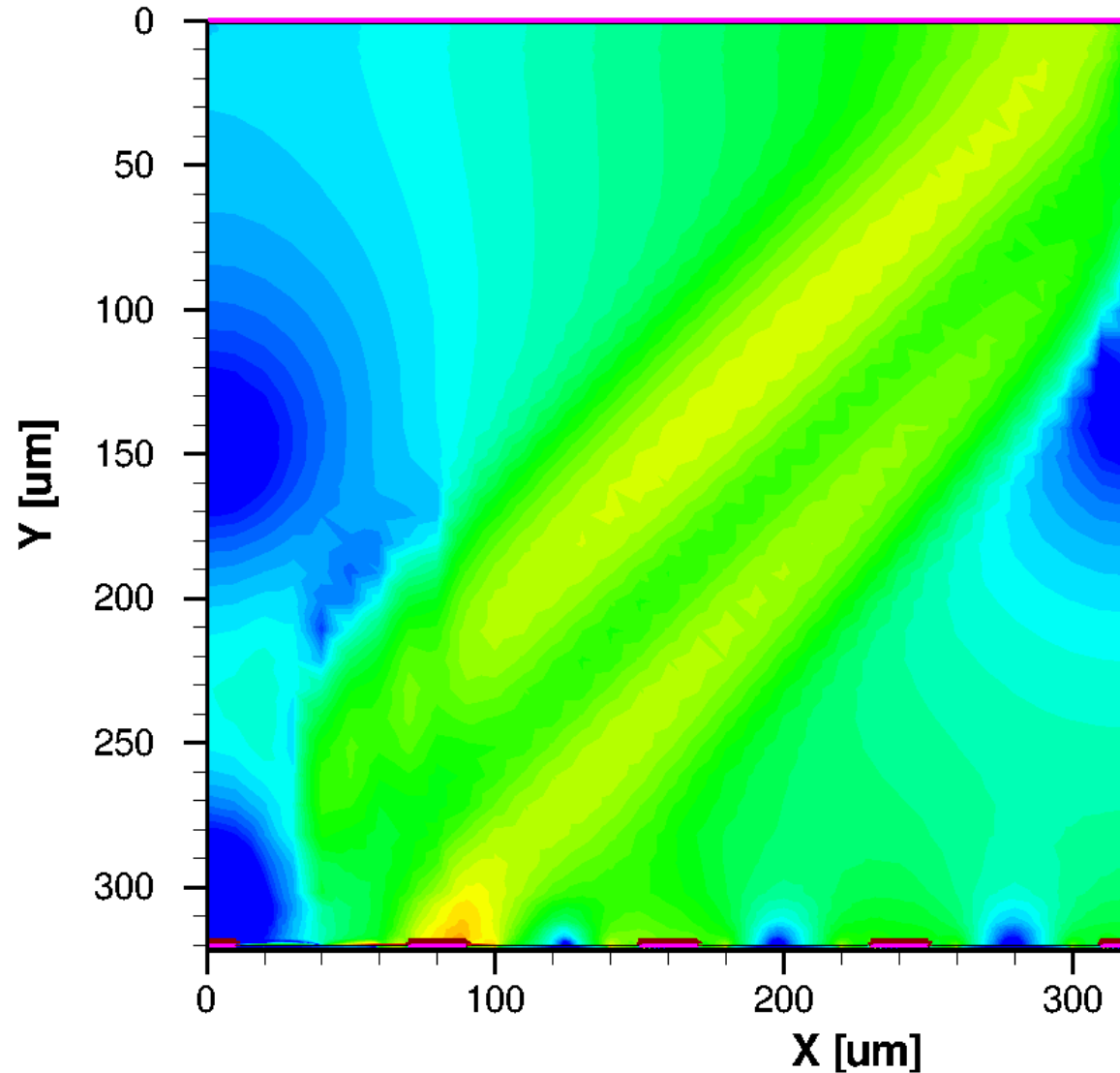


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

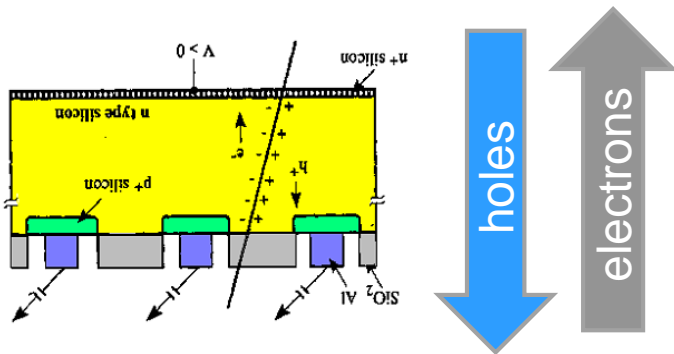


t = 1.8 ns

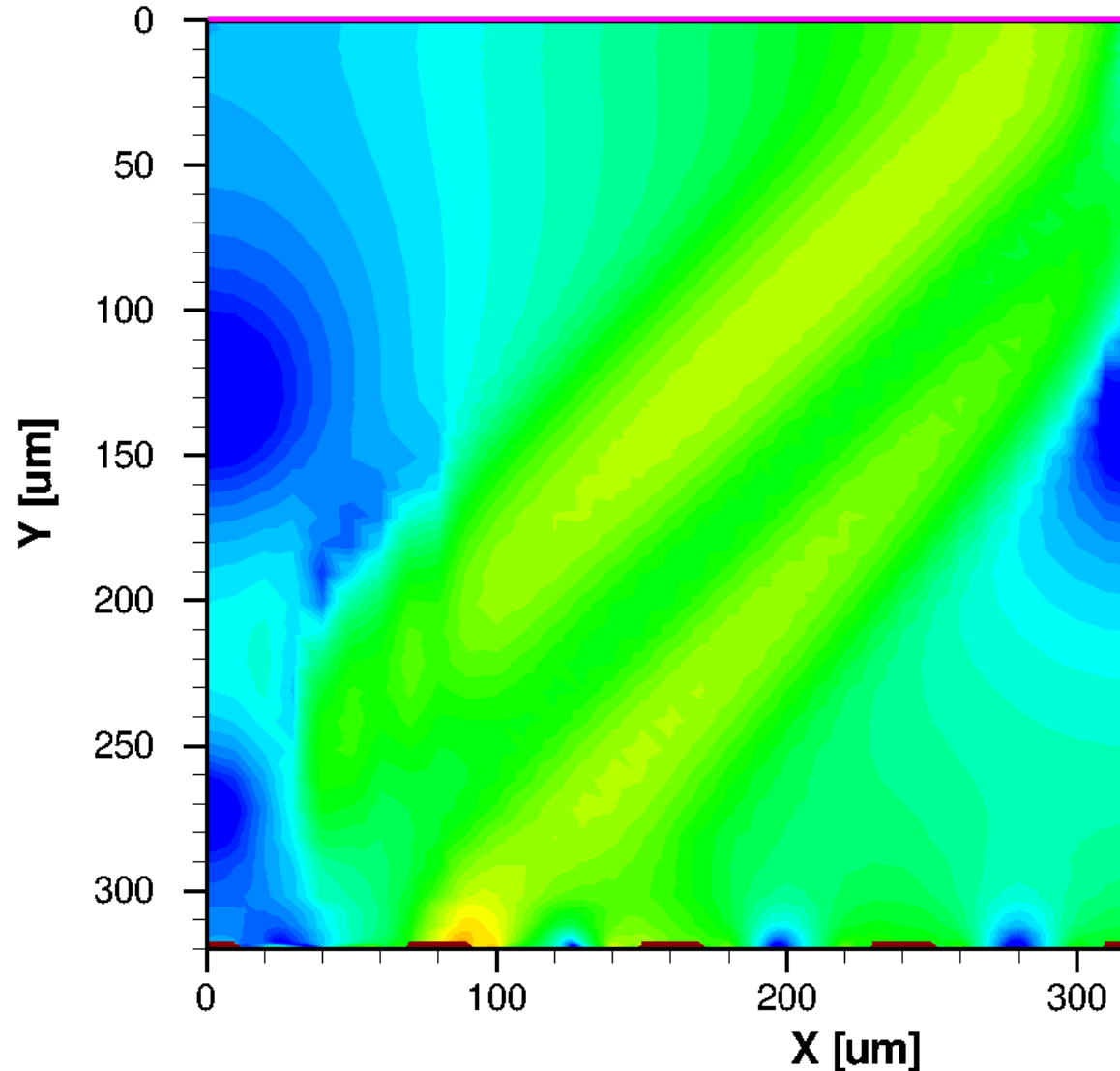


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

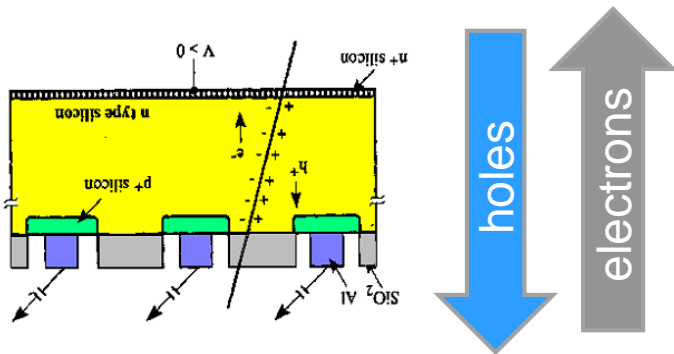


t = 2.0 ns

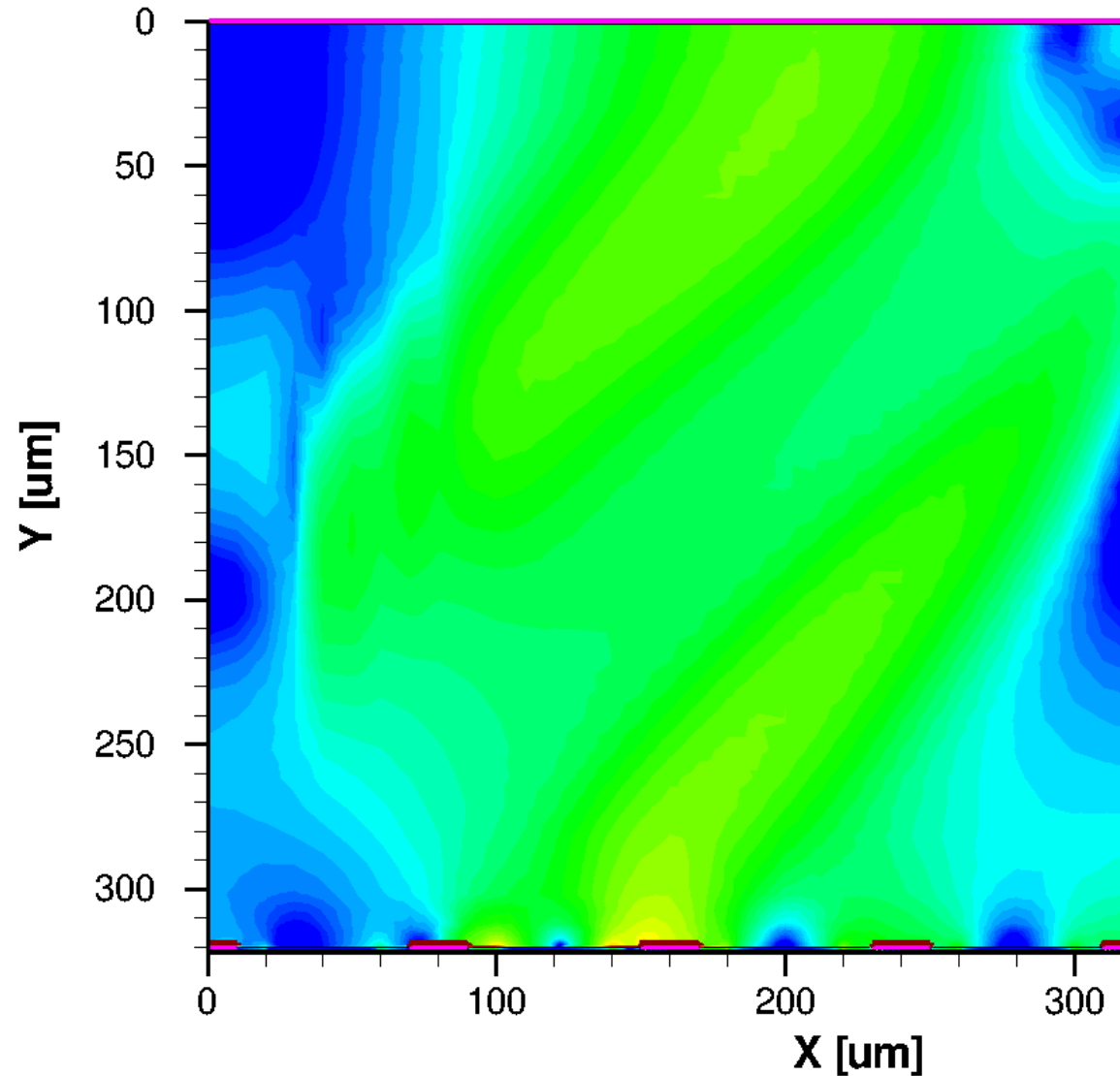


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

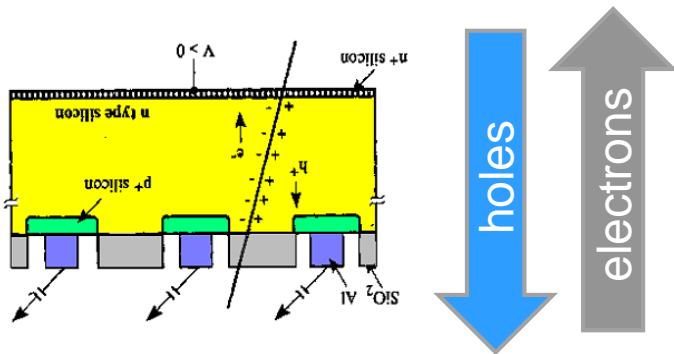


t = 3.0 ns

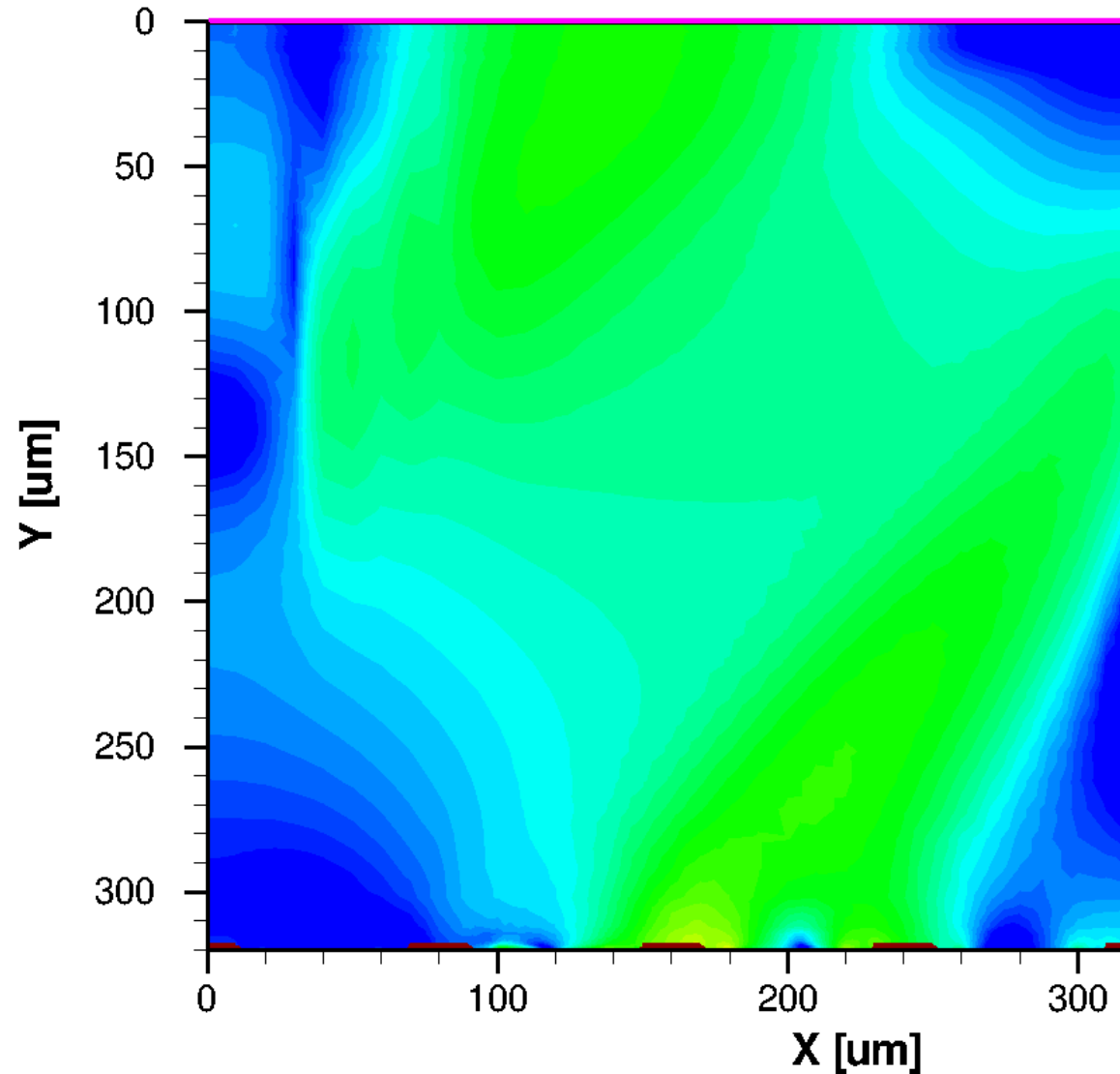


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

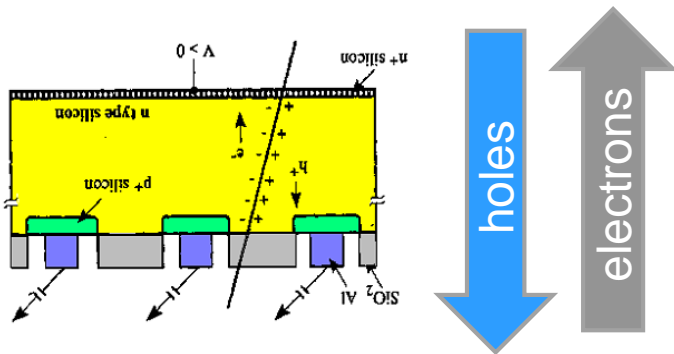


t = 4.0 ns

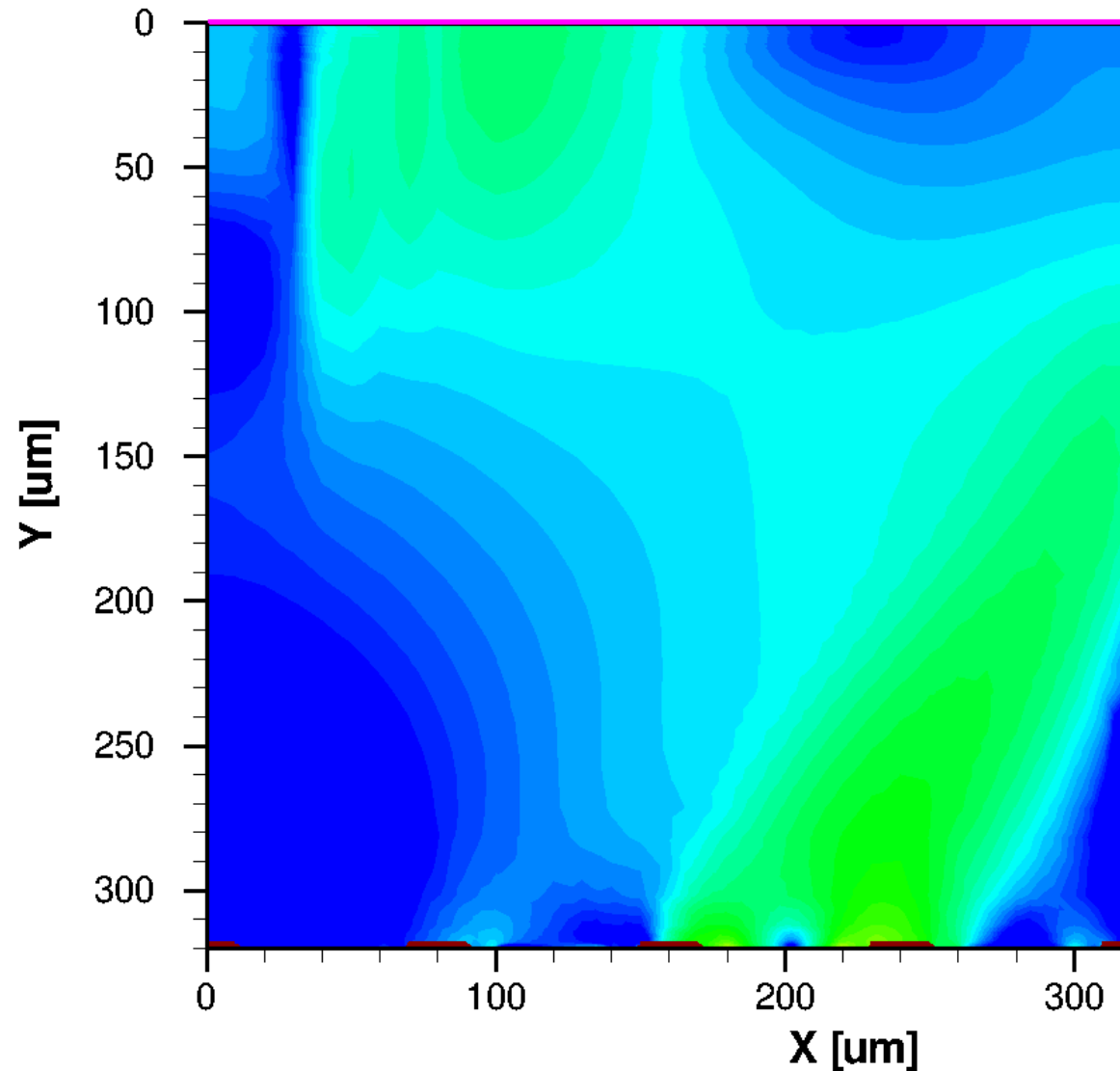


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

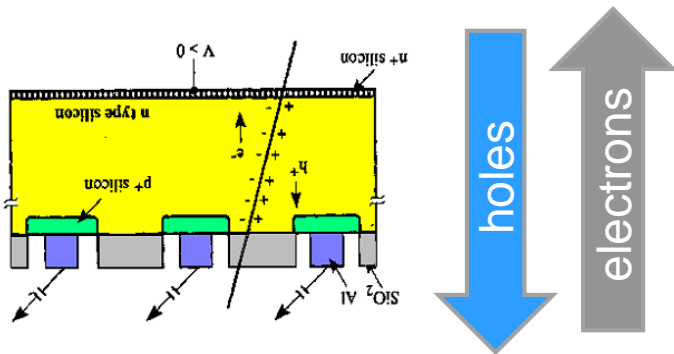


t = 5.0 ns

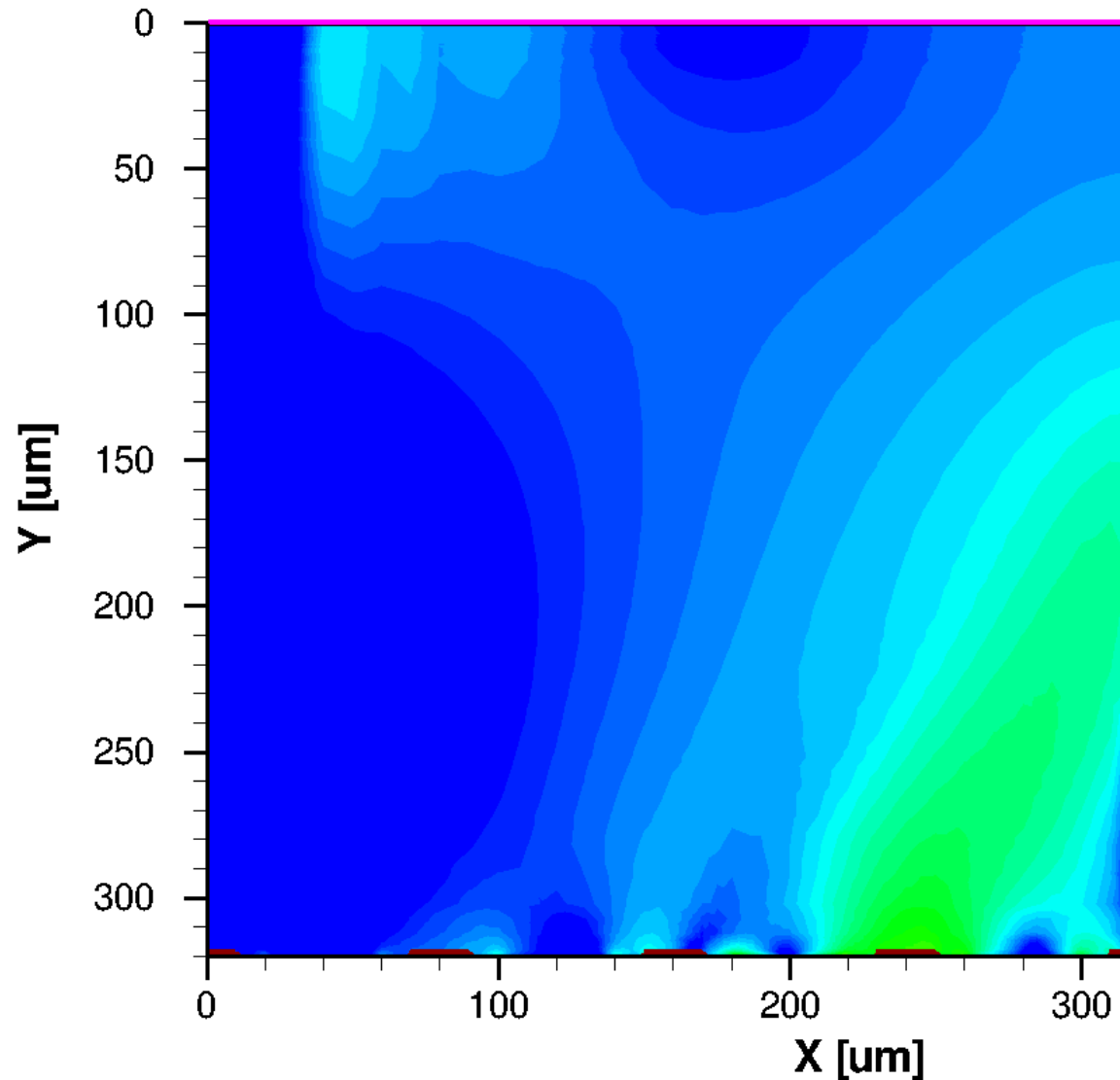


Signal formation in a strip sensor

- Simulation:
 - Current density
 - mip, 45° angle

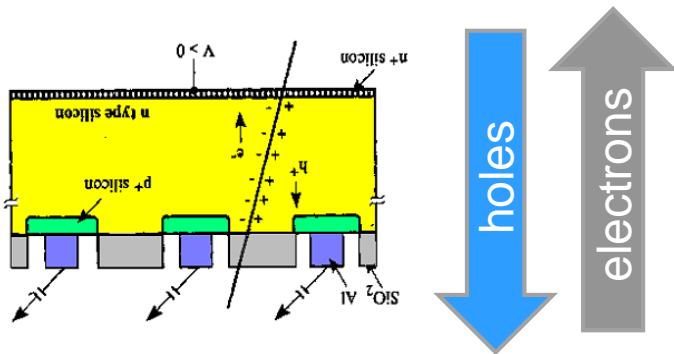


t = 6.0 ns

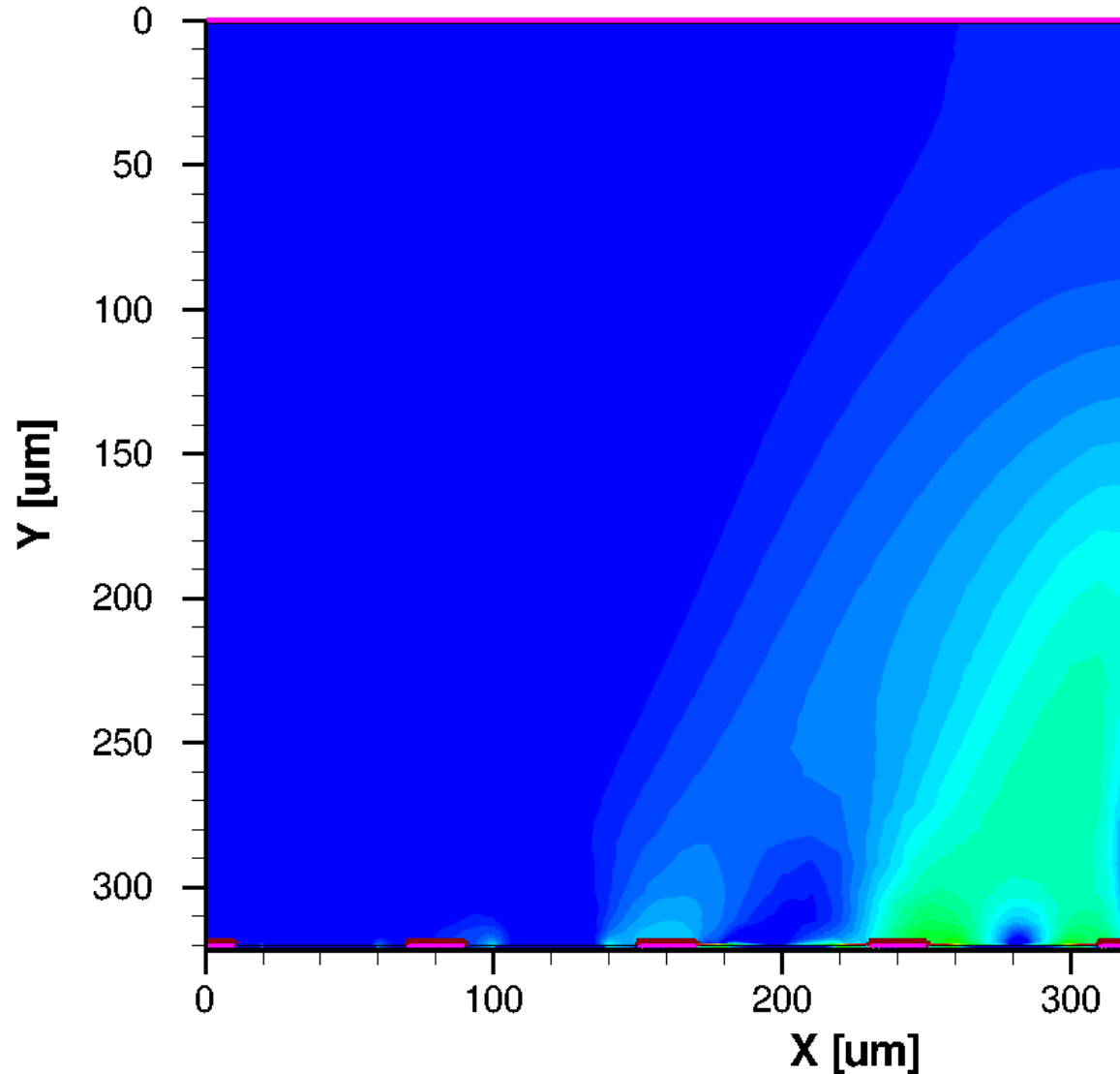


Signal formation in a strip sensor

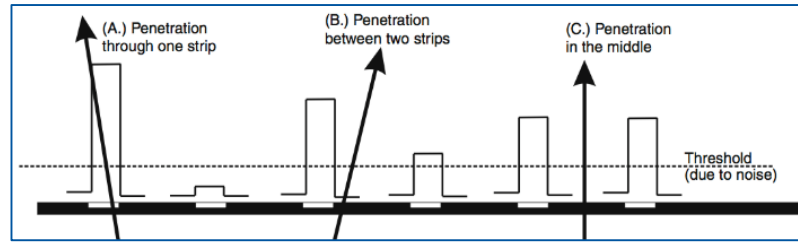
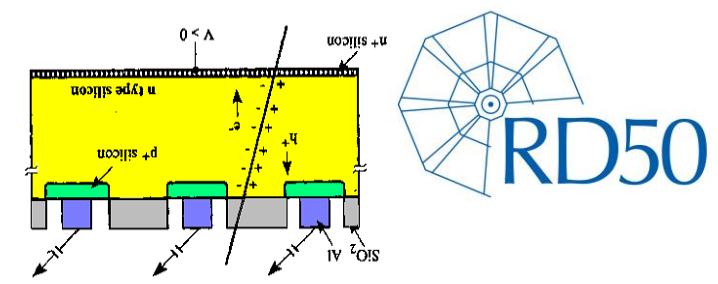
- Simulation:
 - Current density
 - mip, 45° angle



t = 7.0 ns



Signal formation in a strip sensor

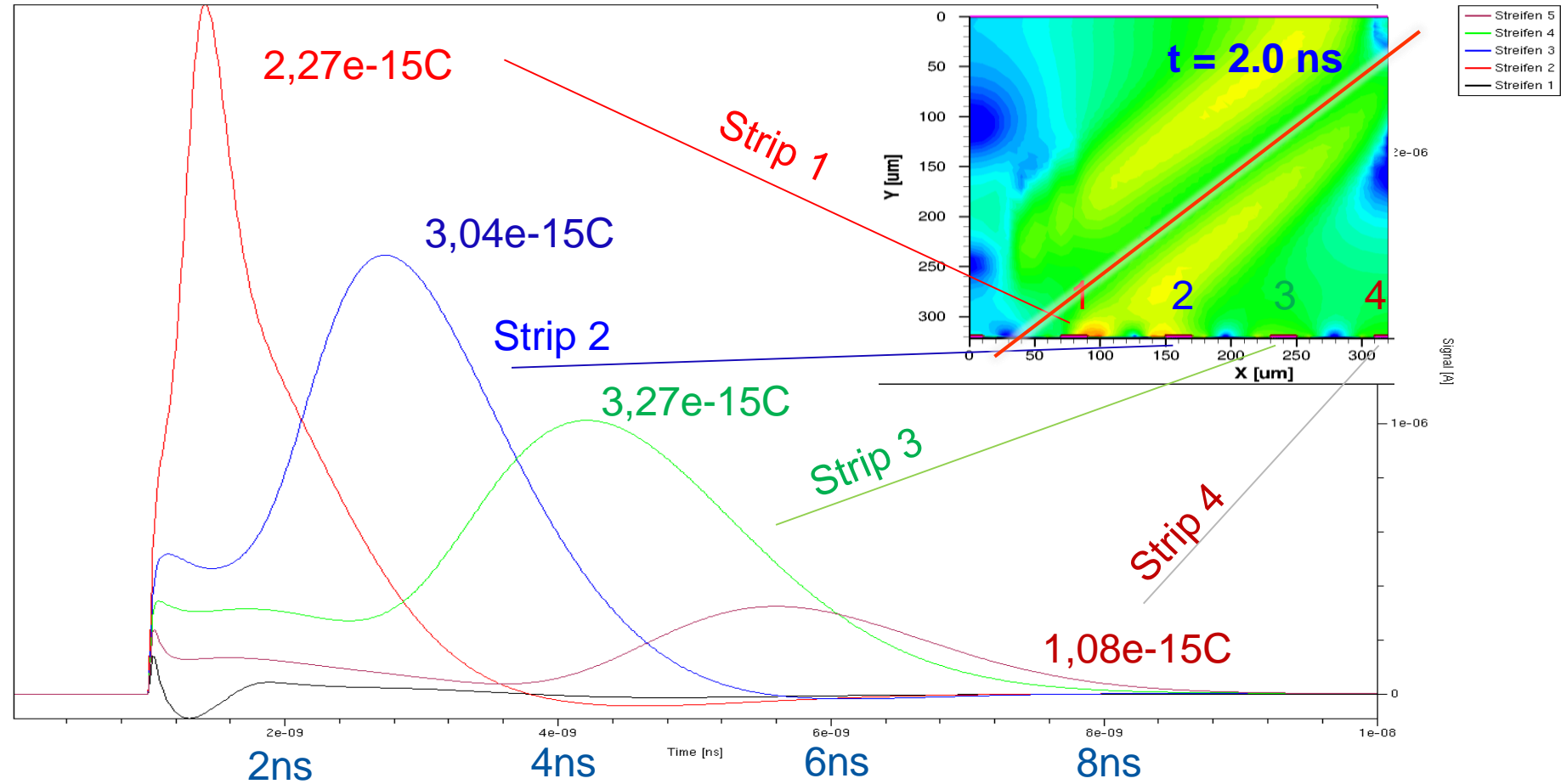


- **Simulation:**

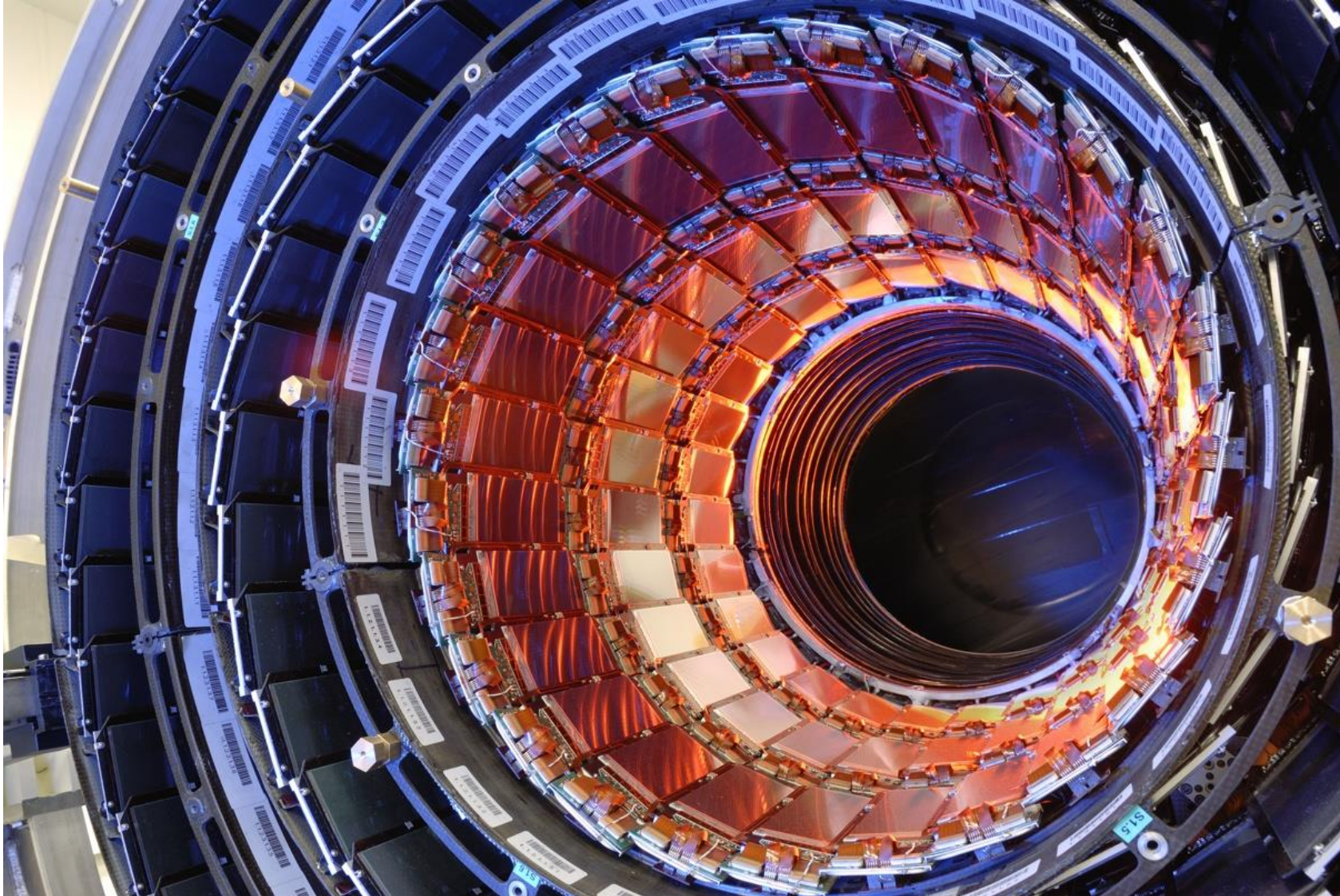
- mip, 45° angle

- **Plot:**

- Signals induced on electrodes
- Integration gives collected charge

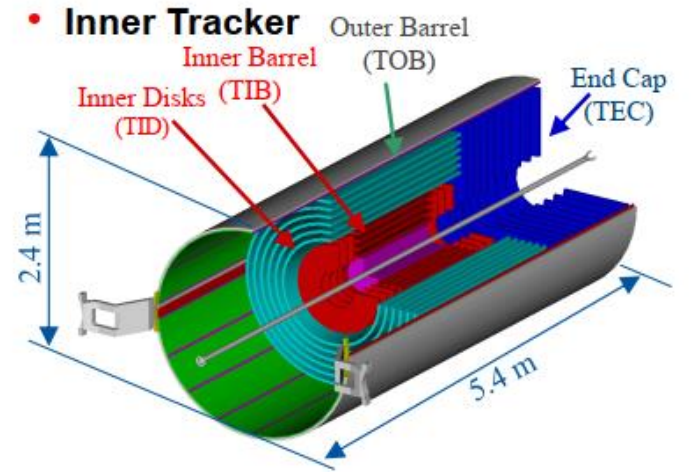


Present LHC Tracking Sensors



CMS Tracker

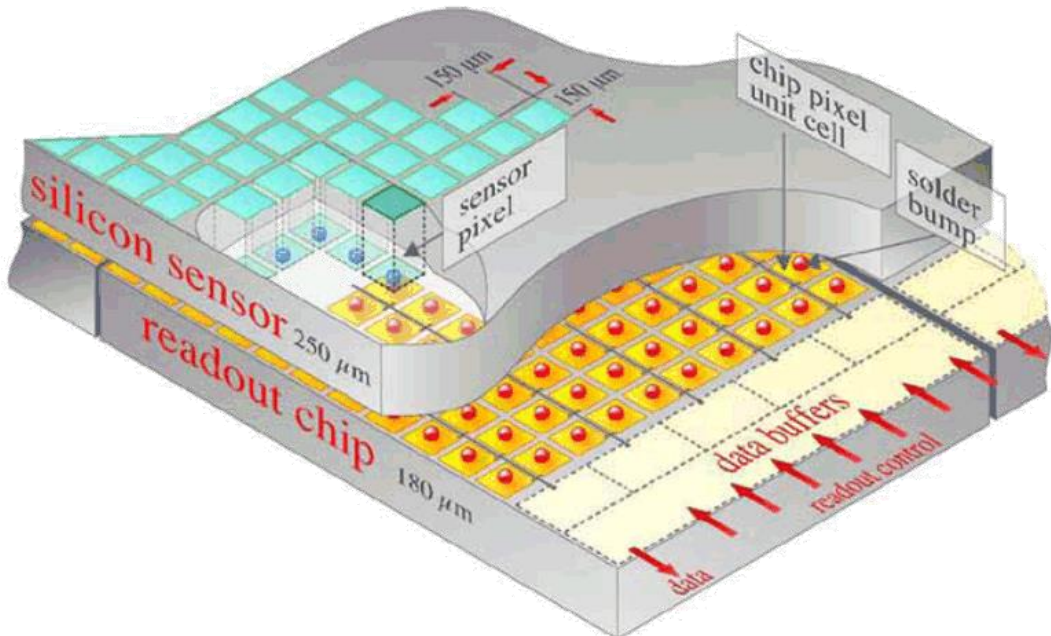
... 11.4 million strips



Hybrid Pixel Detectors

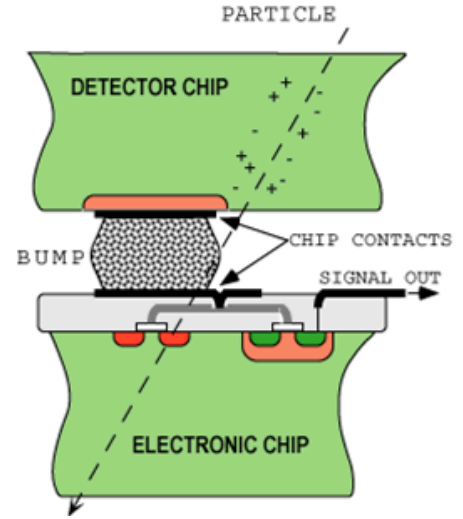
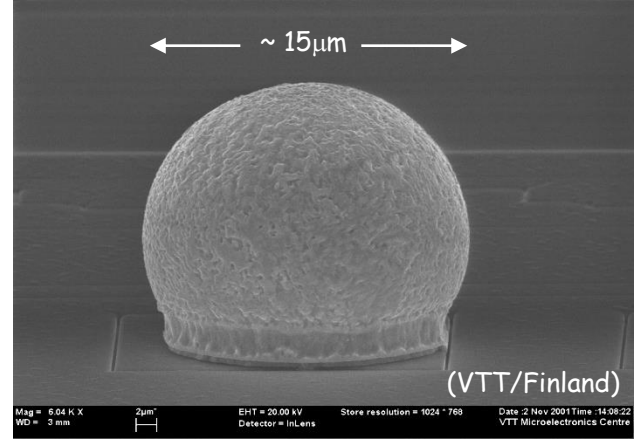


- HAPS – Hybrid Active Pixel Sensors
 - segment silicon to diode matrix with high granularity (⇒ true 2D, no reconstruction ambiguity)
 - readout electronic with same geometry (every cell connected to its own processing electronics)
 - connection by “bump bonding”
 - requires sophisticated readout architecture
 - Hybrid pixel detectors are used in LHC experiments: ATLAS, ALICE (from Run3 monolithic), CMS and LHCb



29.11.2021

Solder Bump: Pb-Sn



Flip-chip technique

Present LHC Tracking Sensors

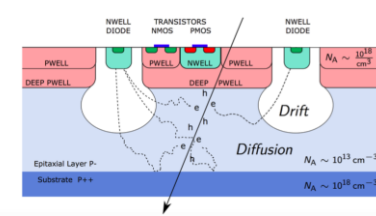


CMS Pixel (Half disk forward pixel)

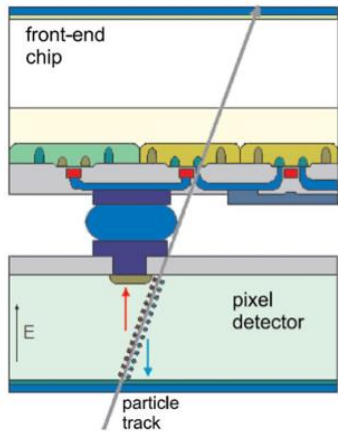


29.11.2021

Hybrid Pixels - Monolithic Pixels

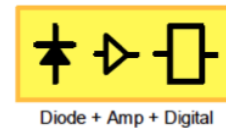
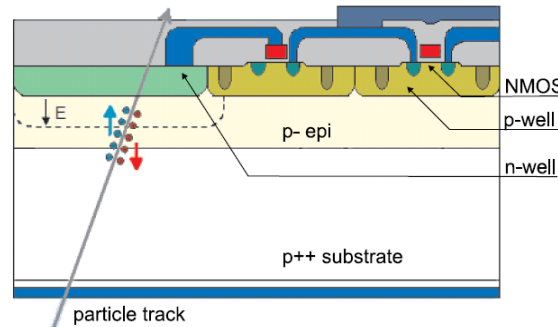


Hybrid Pixel



- Separately optimize sensor and FE-chip for very high radiation environment
- Fine pitch bump bonding to connect sensor and readout chip

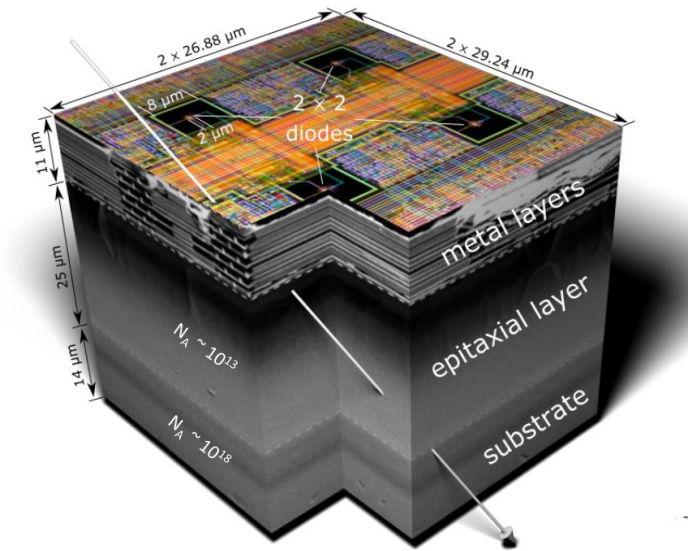
Monolithic Pixel



- Charge generation volume integrated into the ASIC, but many different variants!
- Thin monolithic CMOS sensor, on-chip digital readout architecture

...see talk of Magdalena Munker

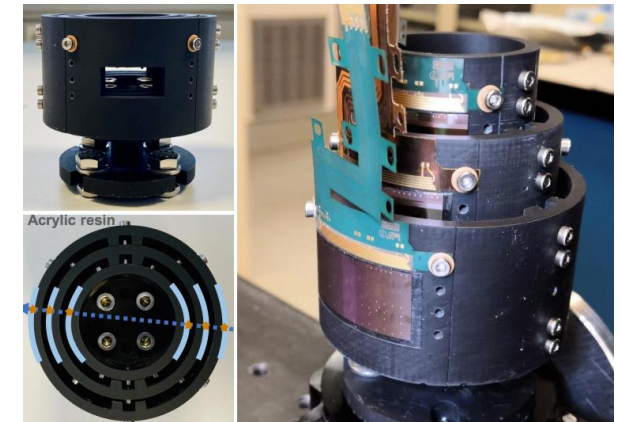
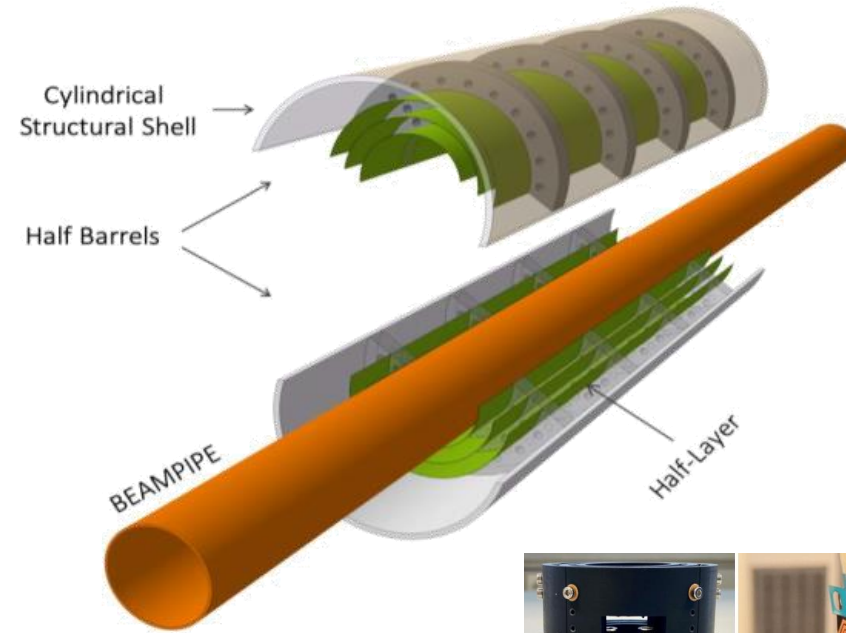
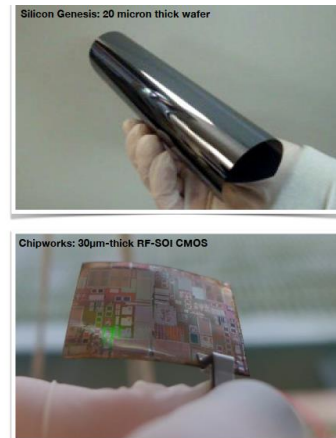
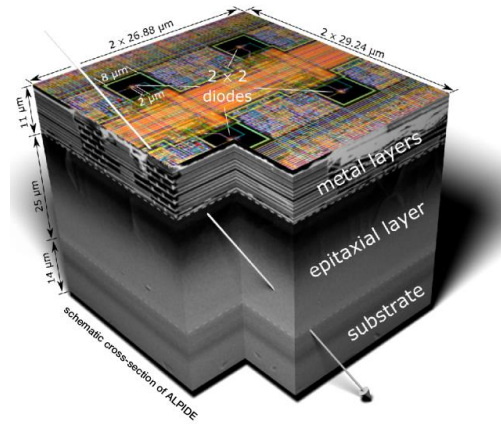
- Example: ALICE – Alpid Chip
 - TowerJazz 0.18 μm CMOS imaging process
 - N-well collection electrode in high resistivity epitaxial layer
 - State-of-art: based on **quadruple well** allows full CMOS
 - **High resistivity (> 1k Ω cm) epi-layer** (p-type, 20-40 μm thick) on p-substrate
 - **Moderate reverse bias => increase depletion region** around N-well collection diode to collect more charges by drift



The future ... going full wafer monolithic?



- ALICE ITS3 project (targeting Run 4 – 2028)
 - Use of 300mm wafer-scale chips
 - Thinned down to 20-40 um making them flexible
 - Mechanically held in place by Carbon foam ribs



..bent chips in test beam
radii: 18, 24, 30 mm

The Charge Signal



- Collected charge for a Minimum Ionizing Particle (MIP)

- **Mean energy loss**

dE/dx (Si) = 3.88 MeV/cm

\Rightarrow 116 keV for 300 μ m thickness

- **Most probable energy loss**

$\approx 0.7 \times$ mean

\Rightarrow 81 keV

- **3.6 eV to create an e-h pair**

\Rightarrow 108 e-h / μ m (mean)

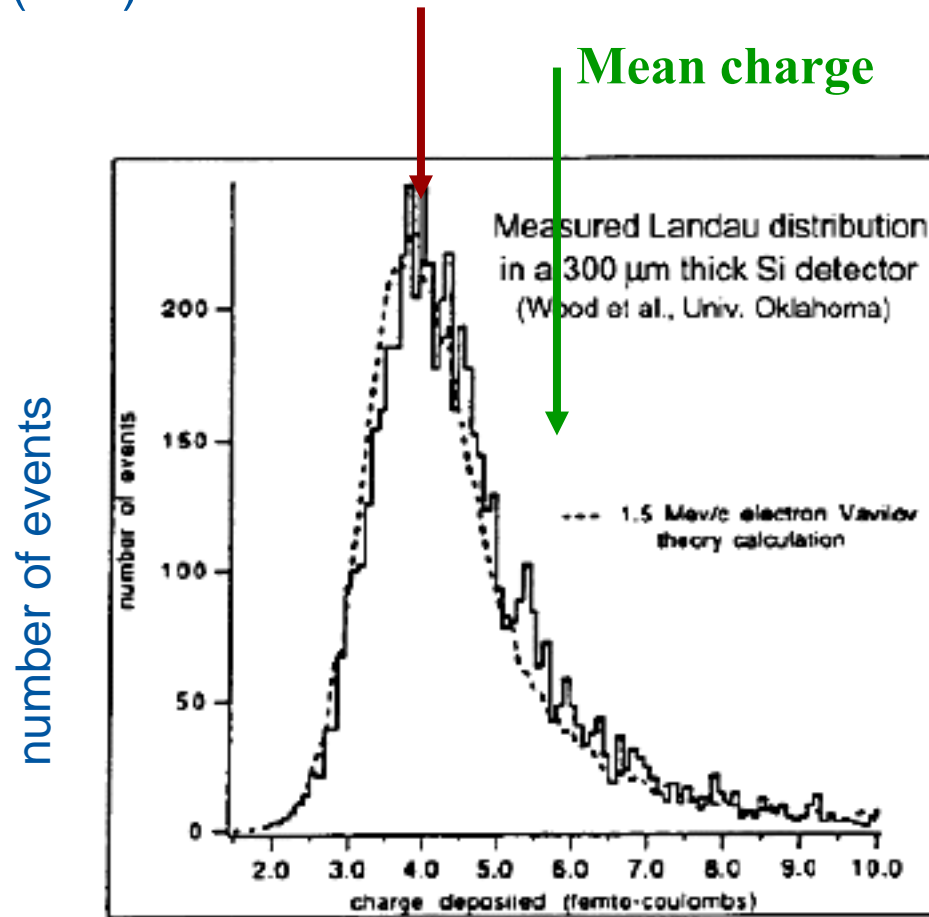
\Rightarrow 72 e-h / μ m (most probable)

- Most probable charge (300 μ m)

≈ 22500 e ≈ 3.6 fC

Most probable charge $\approx 0.7 \times$ mean

Mean charge



charge deposited [fC]

The Charge Signal



- Collected Charge for a Minimum Ionizing Particle (MIP)

- Landau distribution has a low energy tail
 - becomes even lower by noise broadening

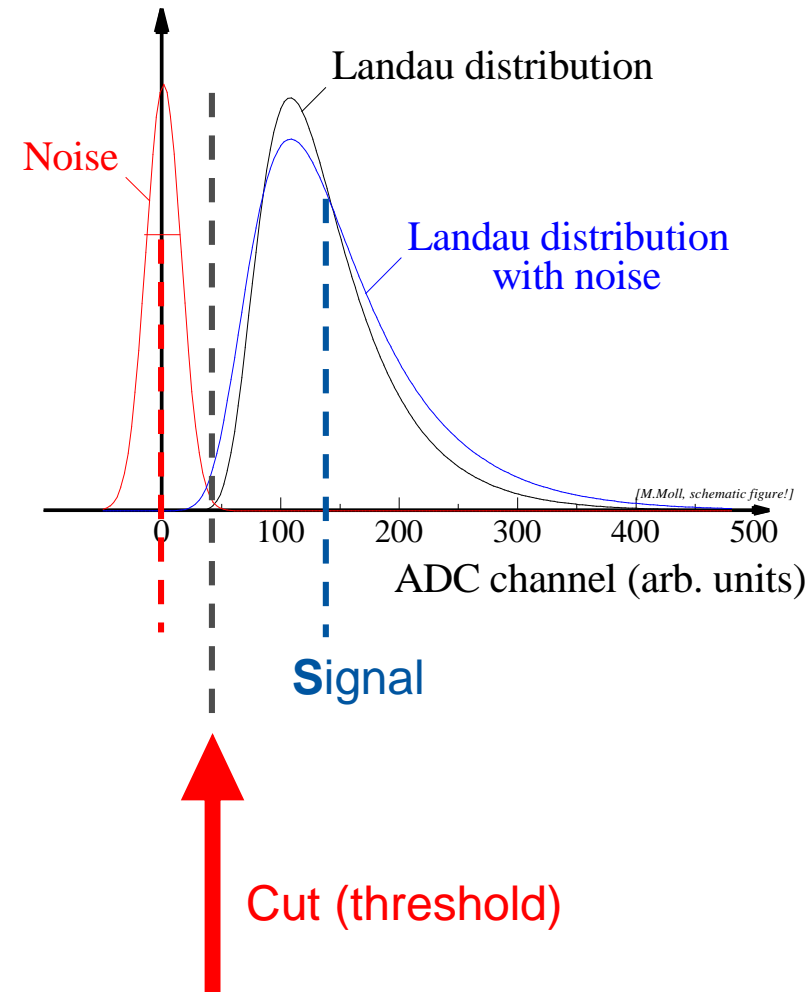
Noise sources: (ENC = Equivalent Noise Charge)

- Capacitance $ENC \propto C_d$

- Leakage Current $ENC \propto \sqrt{I}$

- Thermal Noise (bias resistor) $ENC \propto \sqrt{\frac{k_B T}{R}}$

- Good hits selected by requiring $N_{ADC} > \text{noise tail}$
 - If cut too high \Rightarrow efficiency loss
 - If cut too low \Rightarrow noise occupancy
- Figure of Merit: Signal-to-Noise Ratio S/N
- Typical values >10-15, people get nervous below 10.
 - Radiation damage severely degrades the S/N.

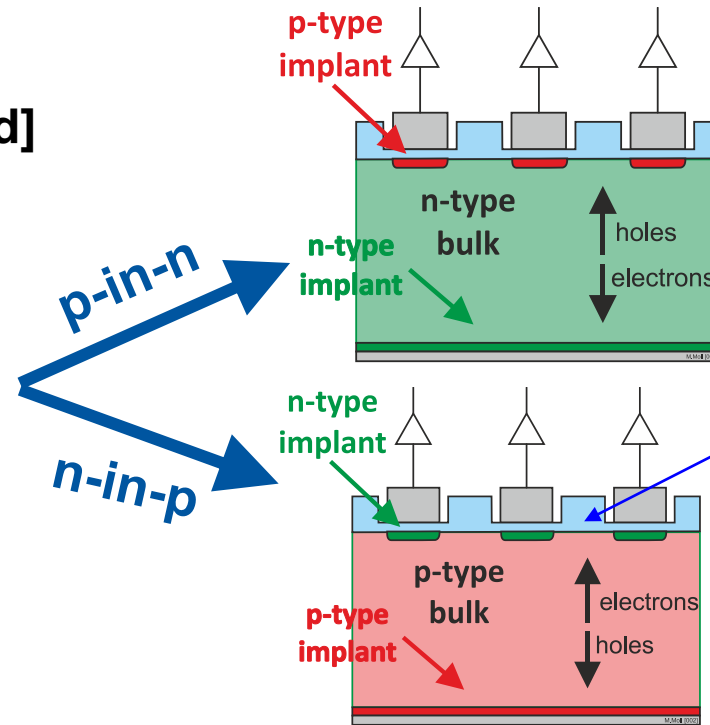
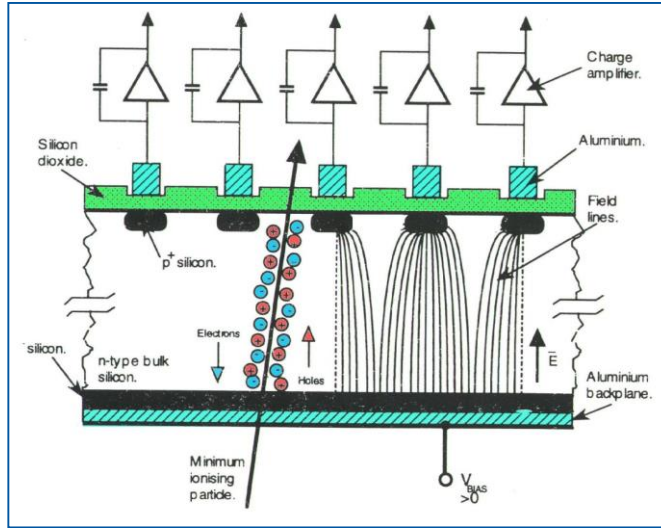
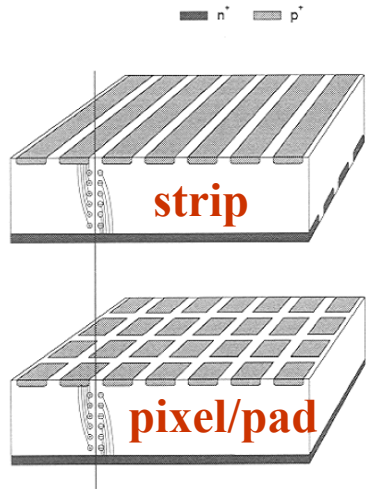


Summary: Silicon Sensors in HEP

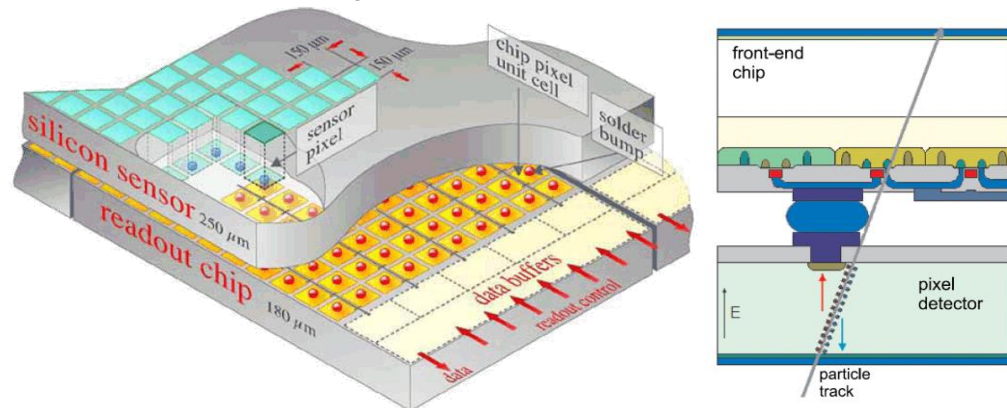


Main sensor concepts:

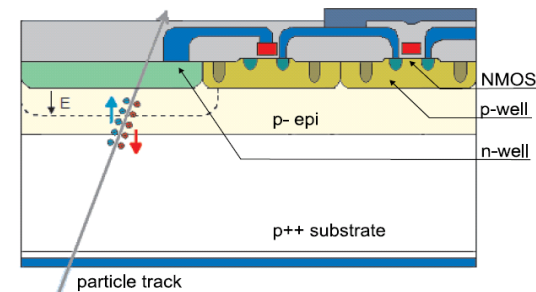
(Mini) Strip Detector [AC coupled]



Hybrid Pixel Detector

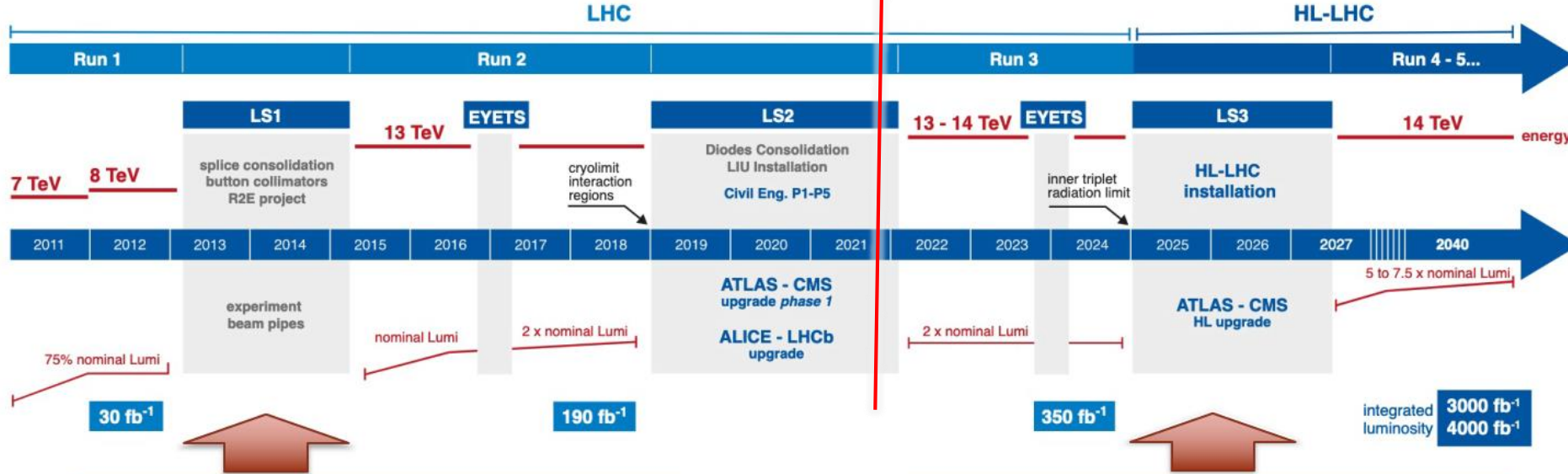


Monolithic CMOS Pixel Detector



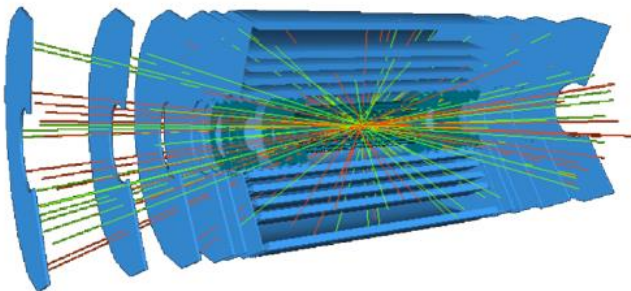
The LHC Upgrade

LHC upgrade



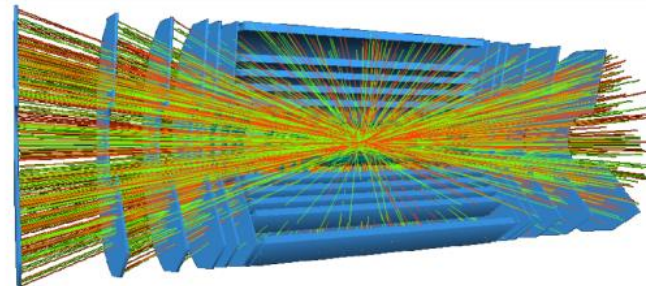
Example ATLAS:

Inner Detector (ID): Pixel+Strip+TRT upgraded by IBL



LHC
19 - 55 Pile-up events

“Phase II”: full inner detector replacement (Pixel+Strip)

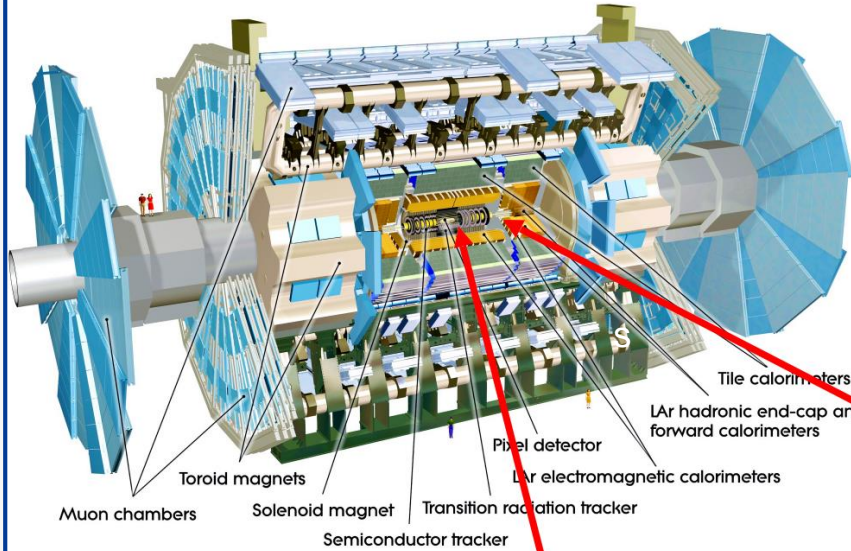


High Luminosity LHC (HL-LHC)
140-200 Pile-up events

Phase 2 upgrades – High Lumi LHC



ATLAS Phase-2 upgrade



Upgraded Trigger and Data Acquisition system

Level-0 Trigger at 1 MHz
Improved High-Level Trigger (150 kHz full-scan tracking)

Electronics Upgrades

On-detector and off-detector electronics upgrades of:
LAr Calorimeter
Tile Calorimeter
Muon Detectors

High Granularity Timing Detector (HGTD)

Forward region
Precision time recon. (30 ps) with Low-Gain Avalanche Detectors (LGAD)

Additional small upgrades

Luminosity detectors (1% precision)
HL-ZDC (Heavy Ion physics)

New Muon Chambers

Inner barrel region with new Resistive Plate Chambers and new Monitored Drift Tubes (sMDT) detectors

New Inner Tracking Detector (ITk)

All silicon (9 layers), up to $|\eta| = 4$

CMS Phase-2 upgrade

L1-Trigger HLT/DAQ

<https://cds.cern.ch/record/2714892>

<https://cds.cern.ch/record/2759072>

- Tracks in L1-Trigger at 40 MHz
- PFlow selection 750 kHz L1 output
- HLT output 7.5 kHz
- 40 MHz data scouting

Barrel Calorimeters

<https://cds.cern.ch/record/2283187>

- ECAL crystal granularity readout at 40 MHz with precise timing for e/γ at 30 GeV
- ECAL and HCAL new Back-End boards

Muon systems

<https://cds.cern.ch/record/2283189>

- DT & CSC new FE/BE readout
- RPC back-end electronics
- New GEM/RPC $1.6 < \eta < 2.4$
- Extended coverage to $\eta \approx 3$

Beam Radiation Instr. and Luminosity

<http://cds.cern.ch/record/2759074>

- Bunch-by-bunch luminosity measurement: 1% offline, 2% online

Calorimeter Endcap

<https://cds.cern.ch/record/2293646>

- 3D showers and precise timing
- Si, Scint+SiPM in Pb/W-SS

Tracker <https://cds.cern.ch/record/227226>

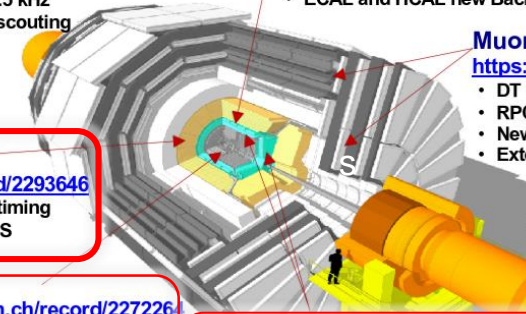
- Si-Strip and Pixels increased granularity
- Design for tracking in L1-Trigger
- Extended coverage to $\eta \approx 3.8$

MIP Timing Detector

<https://cds.cern.ch/record/2667167>

Precision timing with:

- Barrel layer: Crystals + SiPMs
- Endcap layer: Low Gain Avalanche Diodes



• About 800 m² of silicon sensors for the phase 2 upgrades of ATLAS & CMS

..and all based on p-type silicon and no longer n-type silicon. Why? ...see later

Radiation Damage

- Damage to dielectric layers and interfaces (not covered)
- Damage to the semiconductor bulk (introduction)

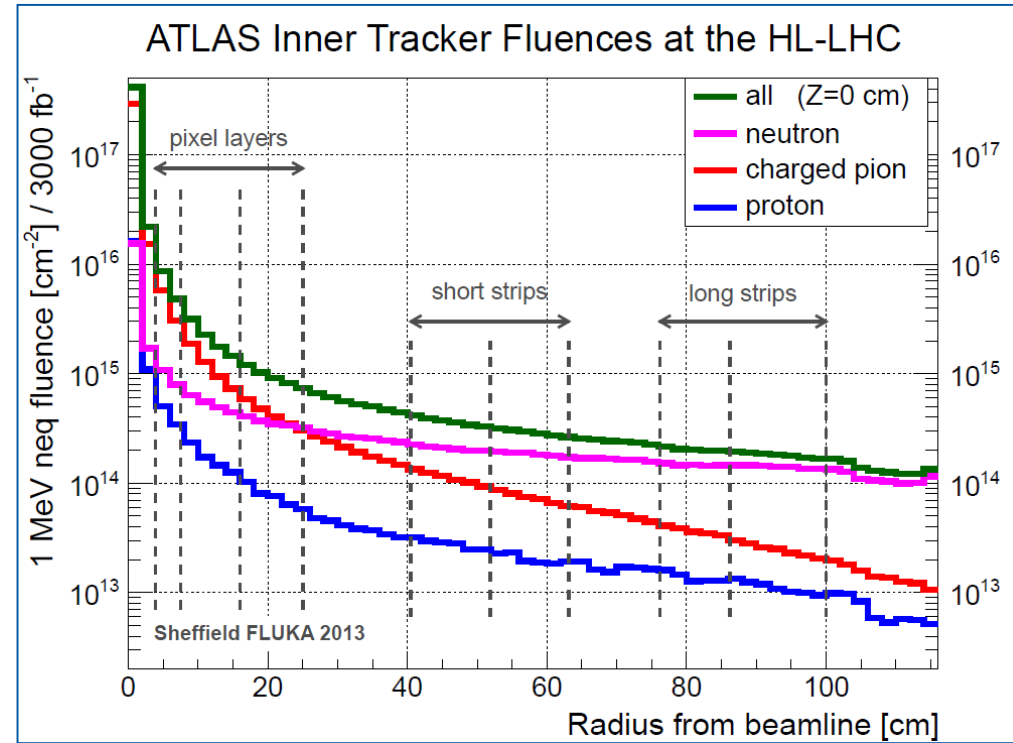
Motivation and Challenge



Silicon detectors upgrades and operation

- Radiation Hardness -

- **LHC operation**
- **HL-LHC (High Luminosity LHC)**
 - detector developments for HL-LHC
 - starting after LS3 (~2025-27);
 - expect 4000 fb^{-1} (nominal LHC was 300 fb^{-1})
- **HL-LHC operation & upgrades**
 - operation of HL-LHC
 - damage modelling, evaluation, mitigation
 - ATLAS Pixel replacement, LHCb upgrade, ...
- **FCC – Future Circular Collider**
 - ..also FCC-ee



[I. Dawson, P. S. Miyagawa, Sheffield University, Atlas]

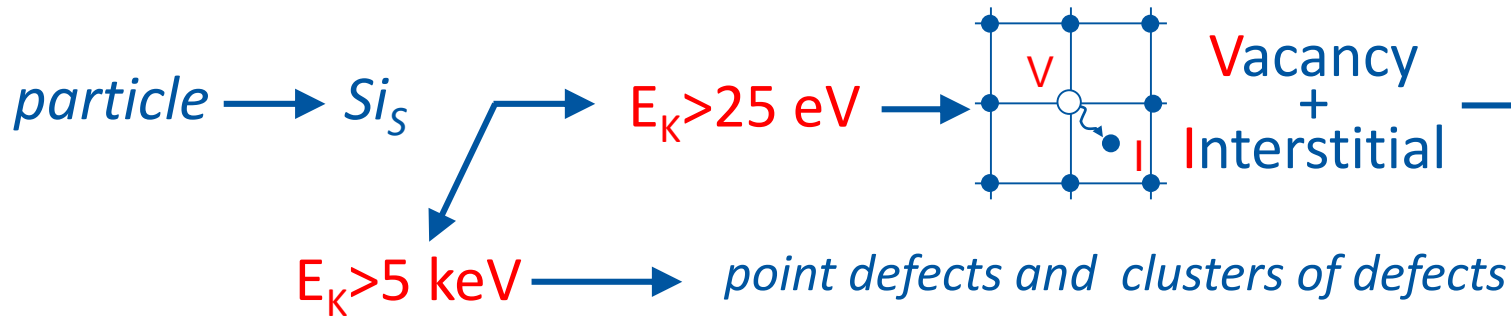
- **Increasing radiation levels**

- Semiconductor detectors will face $>10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$ (**HL-LHC**) and $>7 \times 10^{17} \text{ n}_{\text{eq}}/\text{cm}^2$ (**FCC-hh**)
→ detectors used at LHC cannot be operated after such irradiation

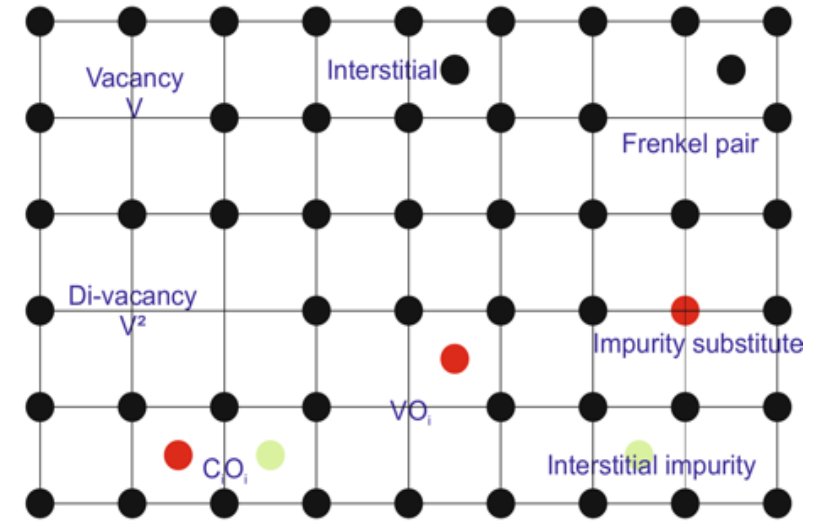
- **New requirement and new detector technologies**

- New requirements or opportunities lead to new technologies (e.g. HV-CMOS, LGAD,...)
which need to be evaluated and optimized in terms of **radiation hardness and/or 4D tracking capabilities**

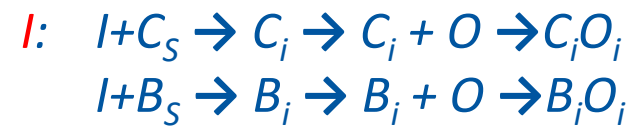
Displacement Damage



..... a wide range of point defects

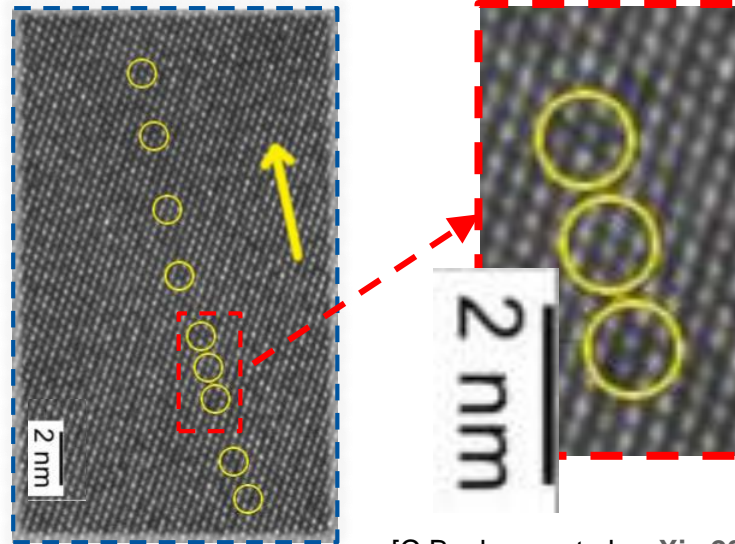


• example of point defect reactions:

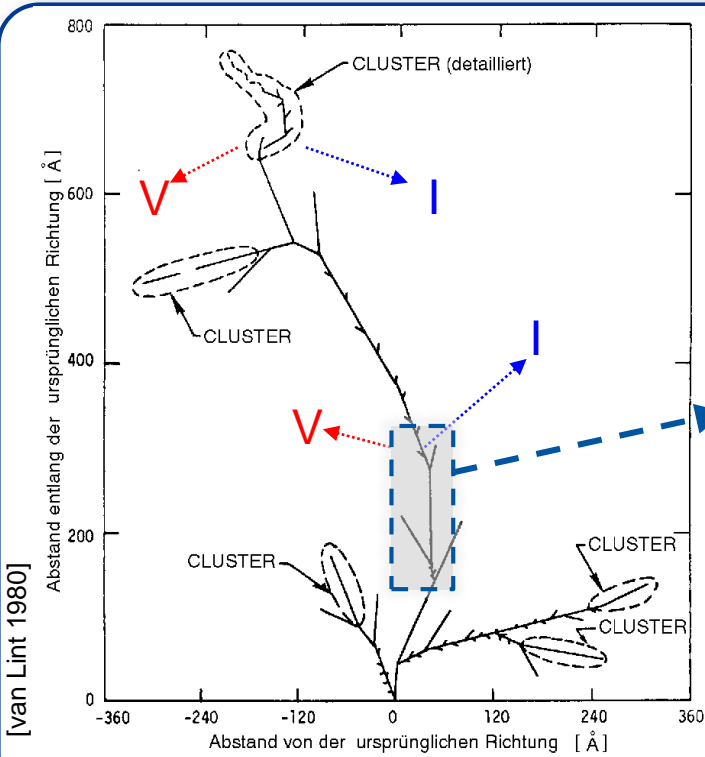


... many more reactions!

Can we see the defects?
 HRTEM on Si: n-irradiated $10^{19} n_{eq}/cm^2$
 High Resolution Transmission Electron Microscopy



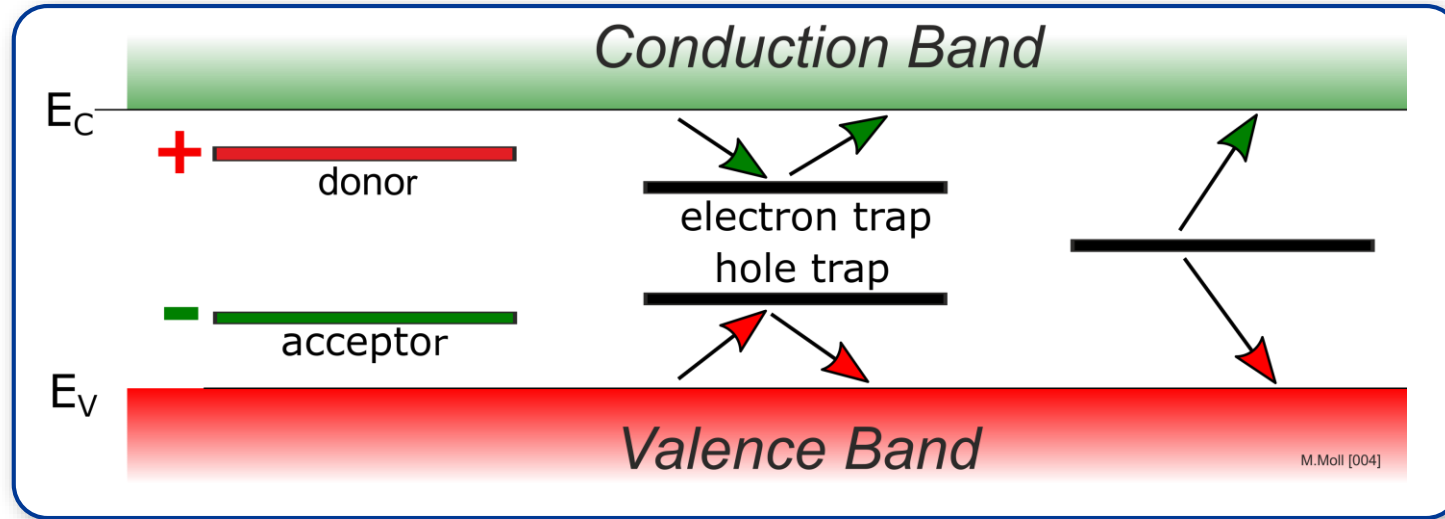
[C.Besleaga et al. arXiv 2021]



[van Lint 1980]

Impact of Defects on Detector Properties

- Shockley-Read-Hall statistics



charged defects

$\Rightarrow N_{\text{eff}}, V_{\text{dep}}$

e.g. donors in upper half, acceptors in lower half of the band gap

trapping (e and h)

$\Rightarrow \text{CCE}$

shallow defects do not contribute at RT due to fast de-trapping

generation

\Rightarrow leakage current

levels close to midgap most effective

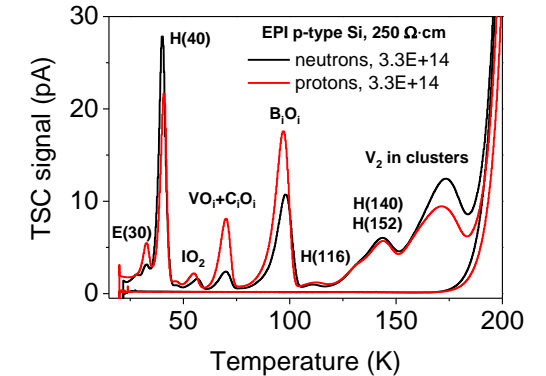
Impact on detector properties can be calculated if defect parameters are known:

$\sigma_{n,p}$: cross sections

ΔE : ionization energy

N_t : concentration

Defect spectroscopy



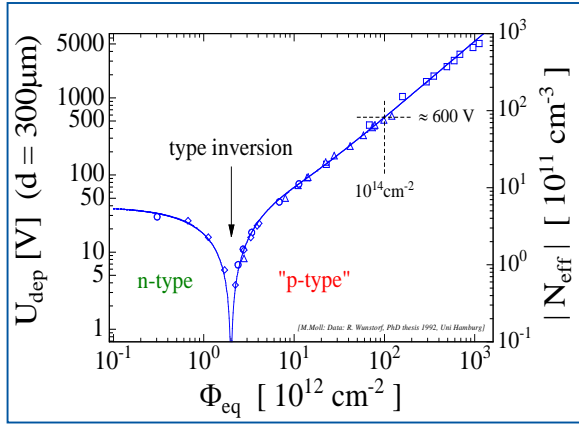
e.g. DLTS, TSC allows to measure the defect properties (see backup)



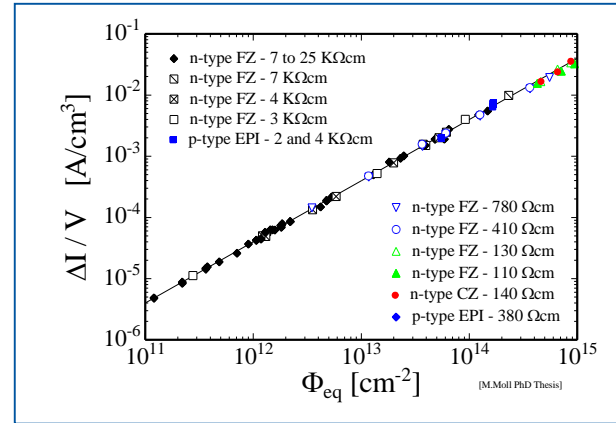
Extracted parameters serve as input to TCAD simulations (see backup)

Radiation Damage Summary

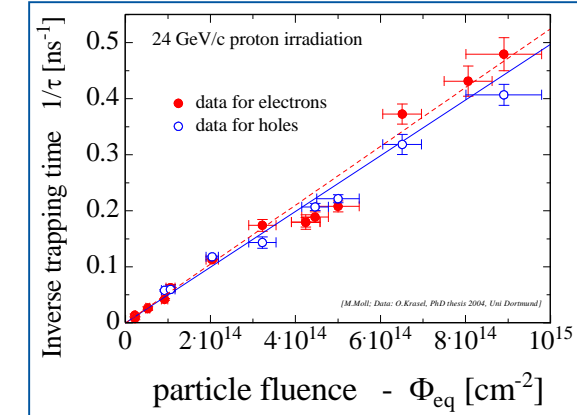
- Macroscopic bulk effects:



Depletion Voltage (N_{eff})

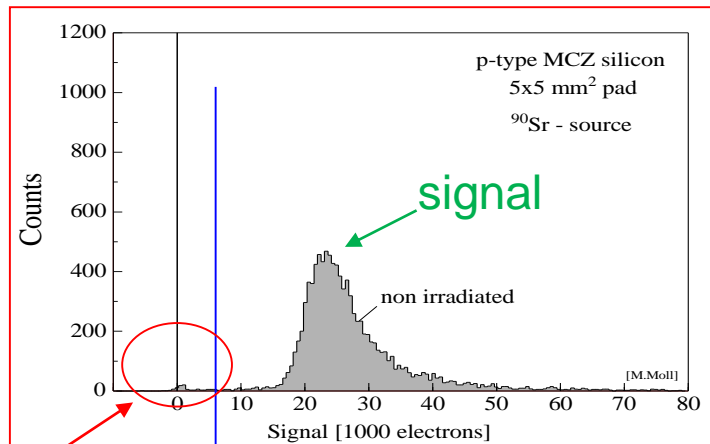


Leakage Current



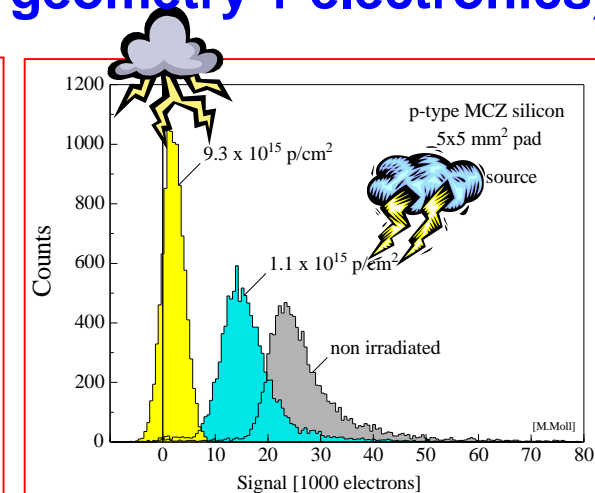
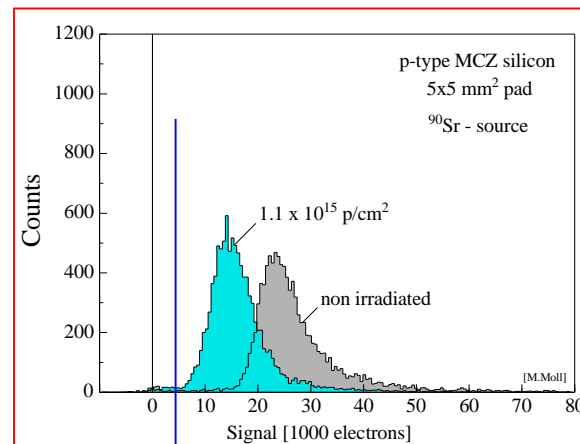
Charge Trapping

- Signal to Noise ratio is quantity to watch (material + geometry + electronics)



noise

Cut (threshold)



Radiation Hard Detectors

The RD50 Collaboration

Full member list: www.cern.ch/rd50

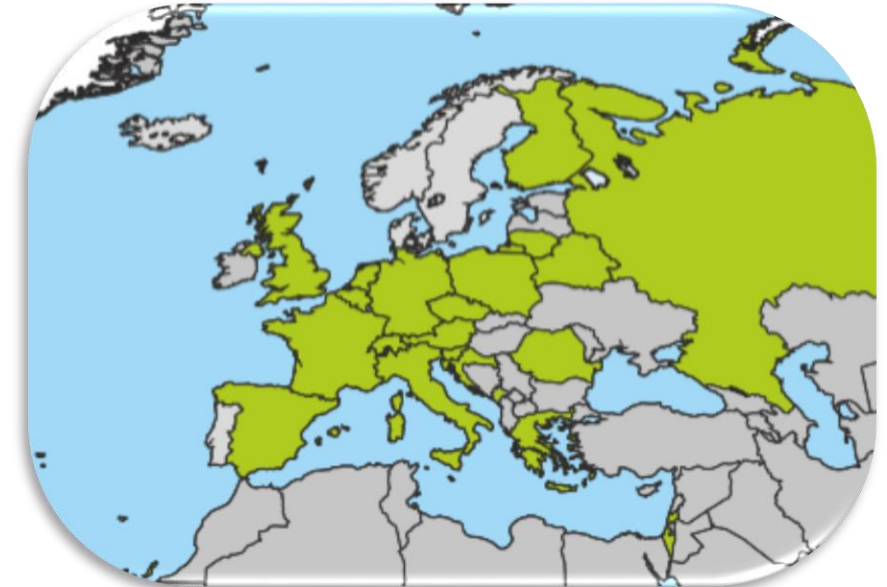


- RD50: 66 institutes and 420 members

51 European institutes

Austria (HEPHY), **Belarus** (Minsk), **Czech Republic** (Prague (3x)), **Finland** (Helsinki, Lappeenranta), **France** (Marseille, Paris, Orsay), **Germany** (Bonn, Dortmund, Freiburg, Göttingen, Hamburg (Uni & DESY), Karlsruhe, Munich (MPI & MPG HLL)), **Greece** (Demokritos), **Italy** (Bari, Perugia, Pisa, Trento, Torino), **Croatia** (Zagreb), **Lithuania** (Vilnius), **Montenegro** (Montenegro), **Netherlands** (NIKHEF), **Poland** (Krakow), **Romania** (Bucharest), **Russia** (Moscow, St.Petersburg), **Slovenia** (Ljubljana), **Spain** (Barcelona(3x), Santander, Sevilla (2x), Valencia), **Switzerland** (CERN, PSI, Zurich), **United Kingdom** (Birmingham, Glasgow, Lancaster, Liverpool, Oxford, Manchester, RAL)

- **LPHNE, UPMC; Université Paris-Diderot; CNRS/IN2P3, Paris**
Marco Bomben, Giovanni Calderini, J.Chauveau, F.Crescioli, Giovanni Marchiori
- **IJCLab - Laboratoire de Physique des 2 Infinis, Irène Joliot-Curie**
L.Iconomidou-Fayard, Abdenour Lounis, C.Nellist
- **CPPM Marseille**; Marlon Barbero, P.Barrillon, P.Breugnon, A.Habib, P.Pangaud, M.Zhao



8 North-American institutes

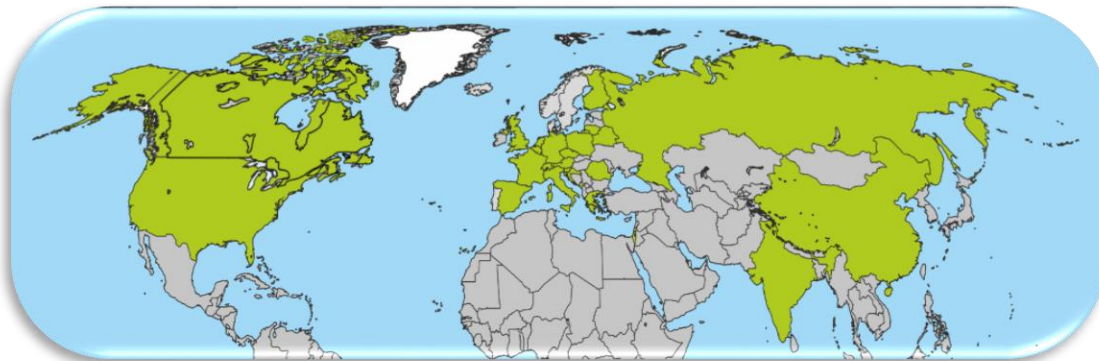
Canada (Ottawa), **USA** (BNL, Brown Uni, Fermilab, LBNL, New Mexico, Santa Cruz, Syracuse)

1 Middle East institute

Israel (Tel Aviv)

6 Asian institutes

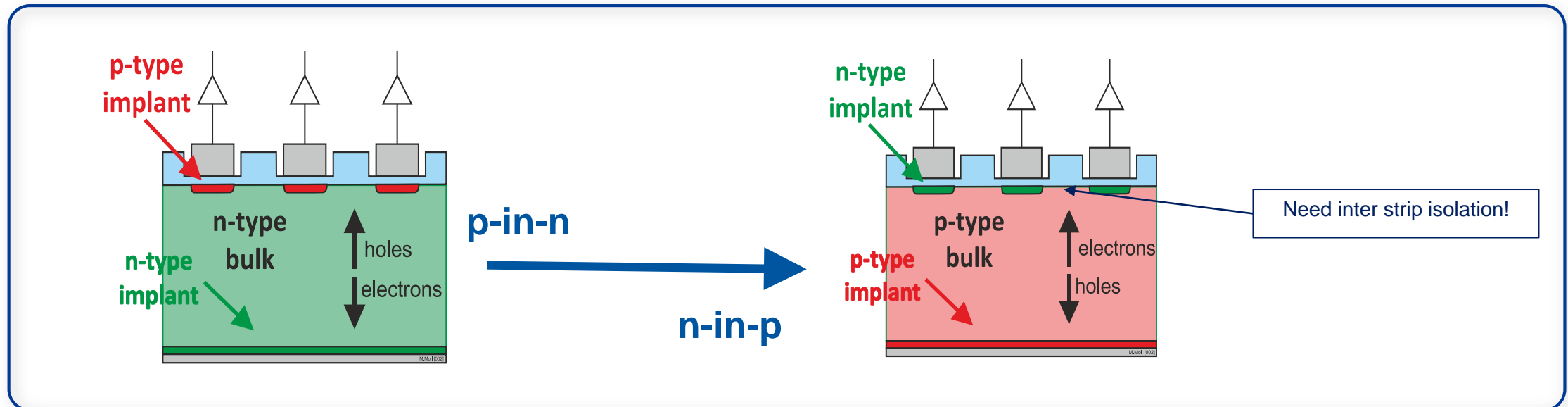
China (Beijing-IHEP, Dalian, Hefei, Jilin, Shanghai),
India (Delhi)



Device engineering example: n-in-p sensors

- Why will we use p-type strip/pixel sensors (n-in-p) for the LHC upgrade in ATLAS and CMS instead of p-in-n sensors?
- Why are segmented sensors^(*) build on p-type silicon sensors radiation harder than n-type sensors?

(*) 300 μm



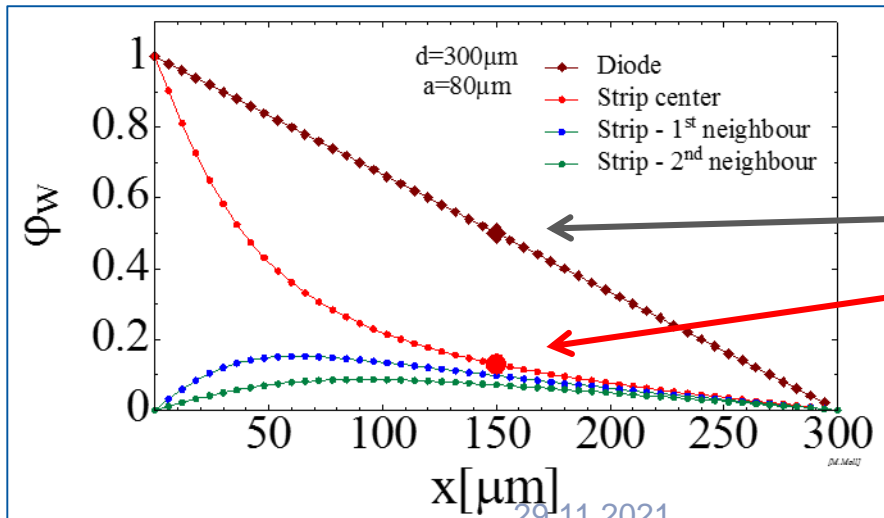
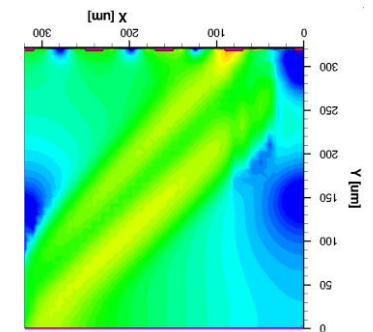
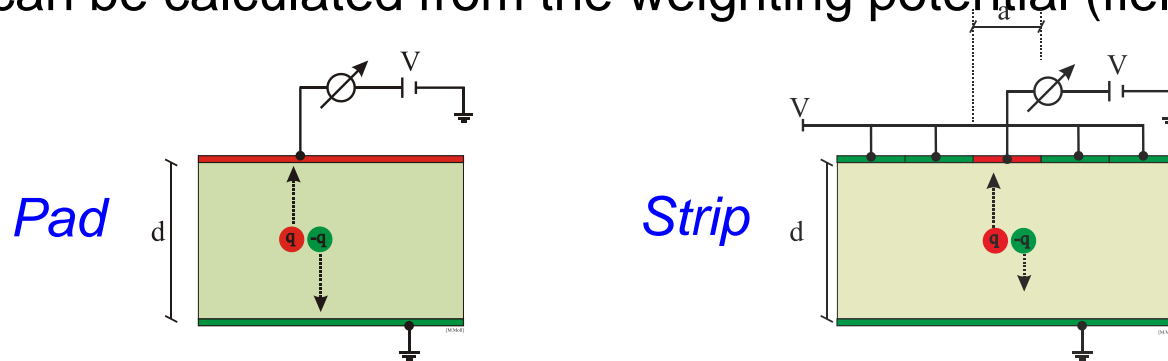
Sensor Signal: Pad vs. Strip/Pixel



- Signal = Induced charge on read-out electrode
 - Described by Shockley-Ramo Theorem
 - Charged induced on electrode by moving charge can be calculated from the weighting potential (field)

$$i = q \cdot \vec{v} \cdot \vec{E}_W(\vec{x})$$

$$Q = -q \cdot (\phi_W(\vec{x}_2) - \phi_W(\vec{x}_1))$$



– Total collected charge in both cases 100% ($Q = q$) when charges have reached the electrodes, however

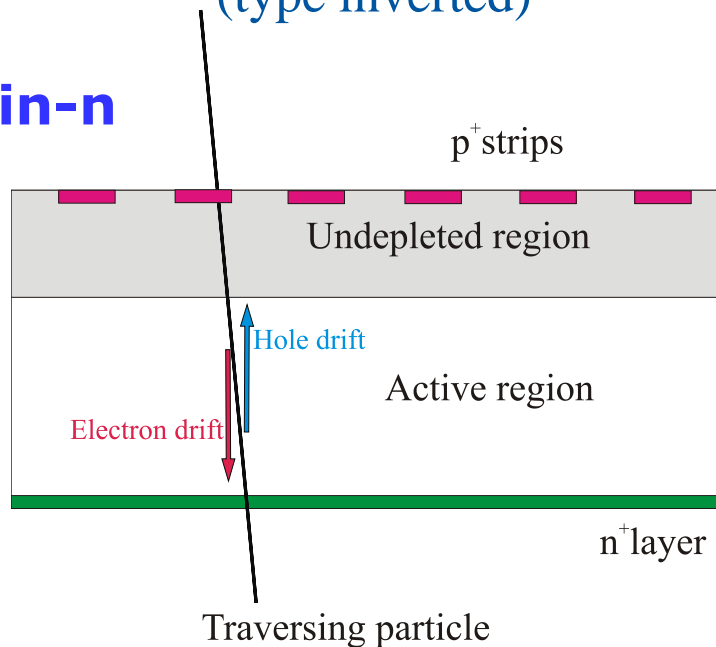
- Diode: 50% from (+q); 50% from (-q)
- Strip: 87% from (+q); 13% from (-q)

– In a p-in-n strip sensor the holes give a higher contribution to the (m.i.p.) signal than the electrons!

Device engineering: p-in-n vs. n-in-p (or n-in-n)

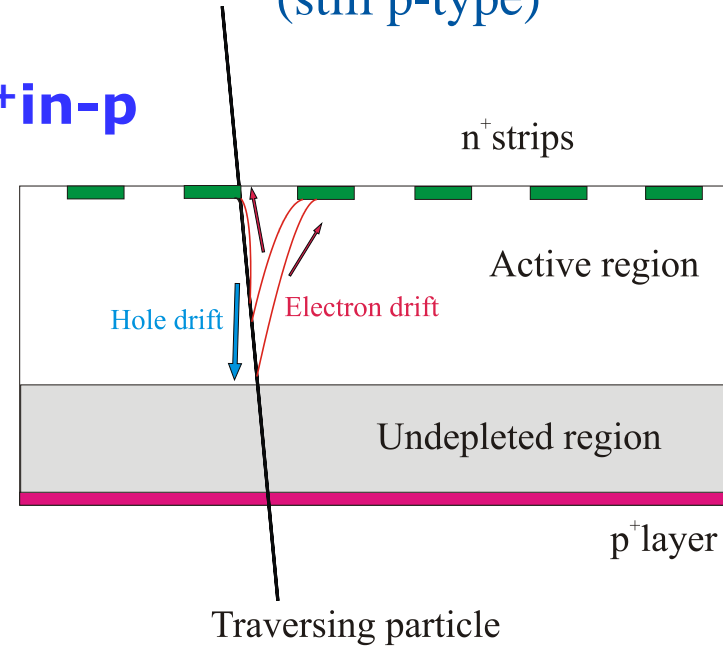
n-type silicon after high fluences:
(type inverted)

p⁺in-n



p-type silicon after high fluences:
(still p-type)

n⁺in-p



p-in-n silicon, under-depleted:

- Charge spread – degraded resolution
- Charge loss – reduced CCE

n-in-p silicon, under-depleted:

- Limited loss in CCE
- Less degradation with under-depletion
- Collect electrons (3 x faster than holes)

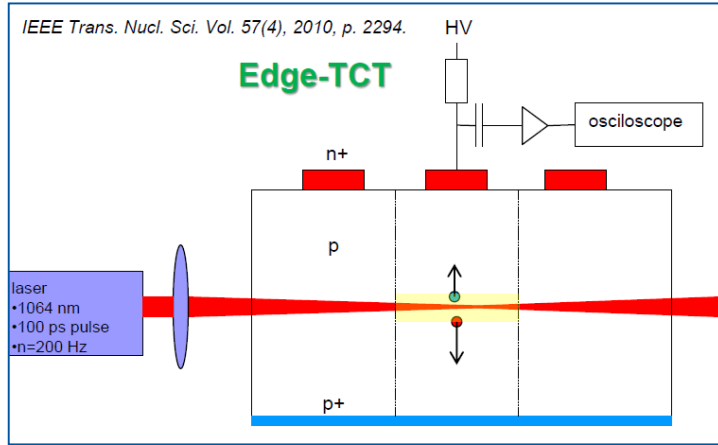
Comments:

- Instead of n-in-p also n-in-n devices could be used

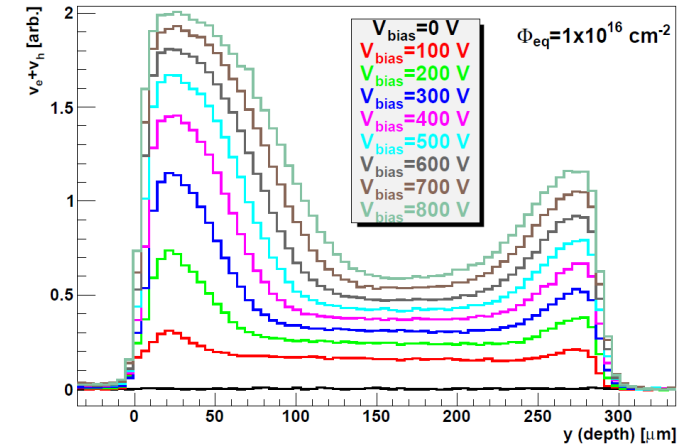
- Reality is much more complex: Usually double junctions form leading to fields at front and back!

E-Field after irradiation: “double junctions”

- Investigation by measurement

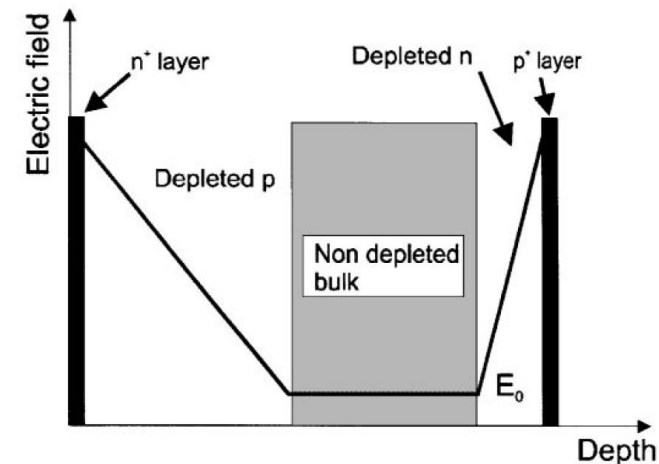
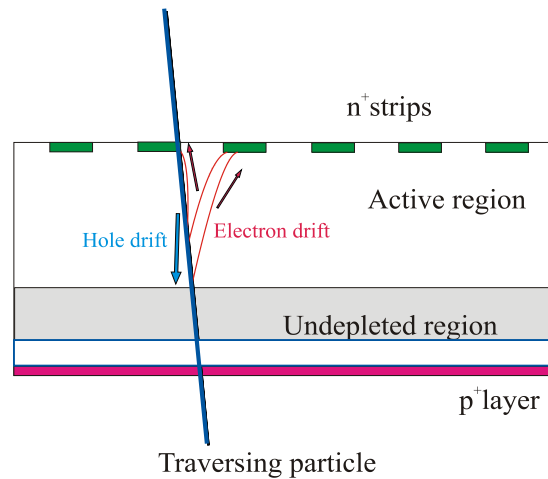


n-in-p sensor still “p-type” (i.e. highest field at front electrode) after high level of radiation



[G.Kramberger et al, 2014 JINST 9 P10016]

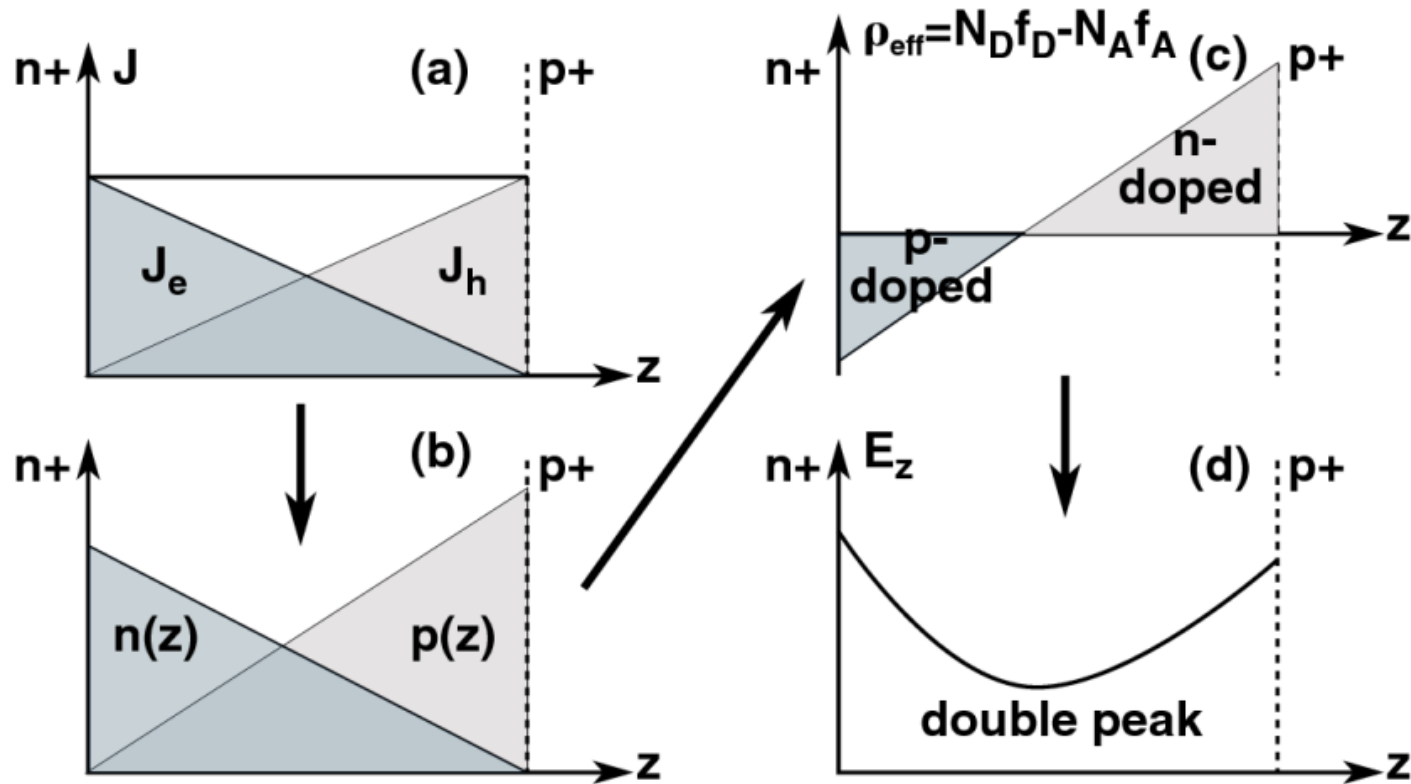
- Dominant junction close to n+ readout strip for FZ n-in-p



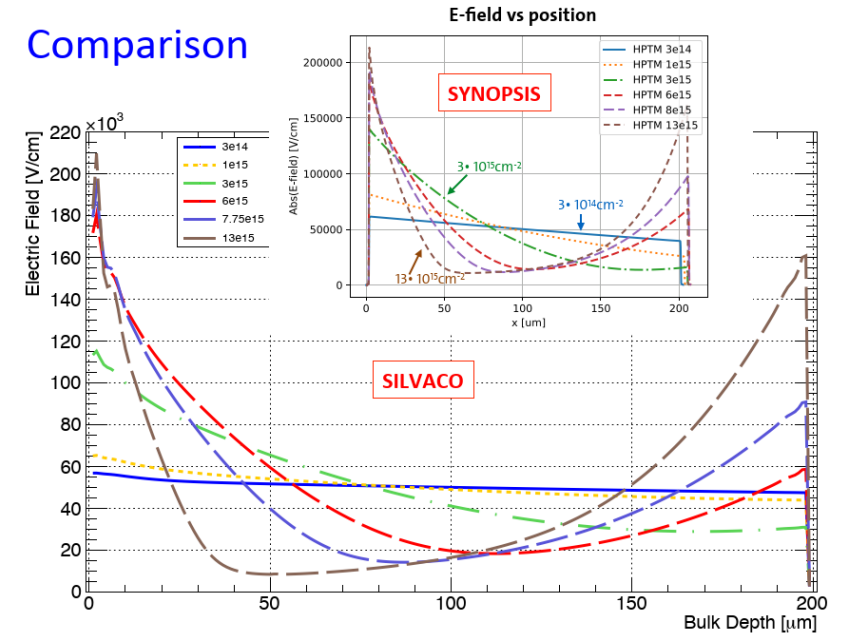
Double Junction



- Double Junction = Polarization Effect



Comparison

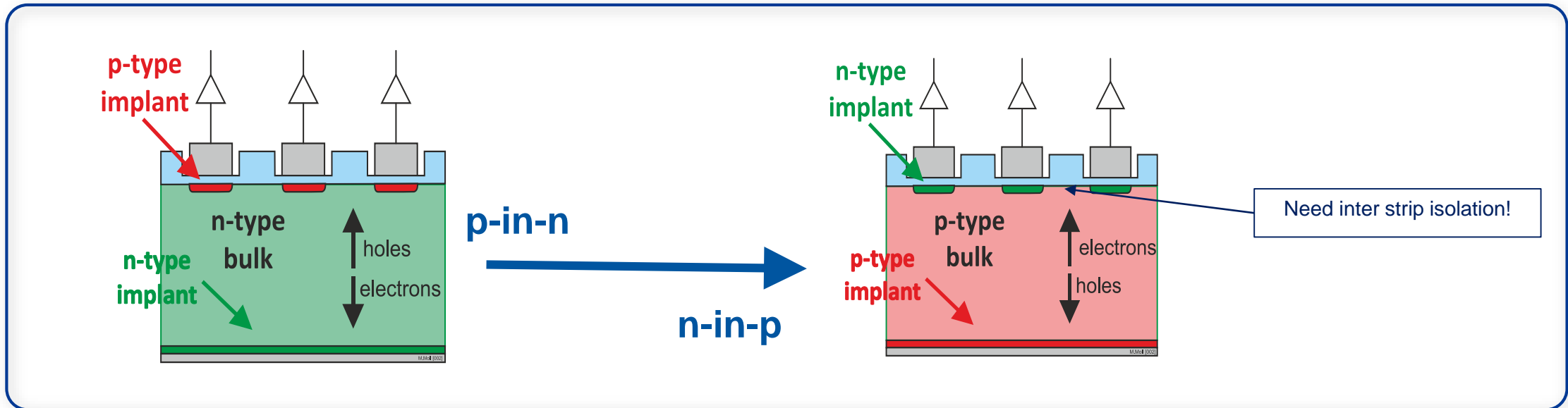


M. Bomben - SIMDET 2018 - LPNHE, Paris

30

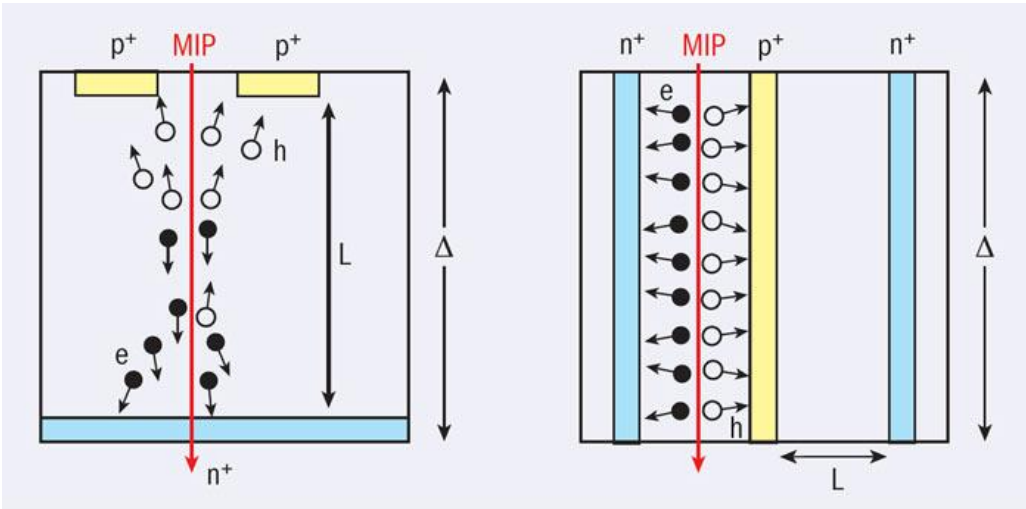
Marco Bomben SIMDET 2018

Device engineering example: n-in-p sensors



Sensors in LHC trackers today (ATLAS/CMS) → HL-LHC trackers tomorrow (2028)

Device engineering example: 3D Hybrid Pixel Detectors

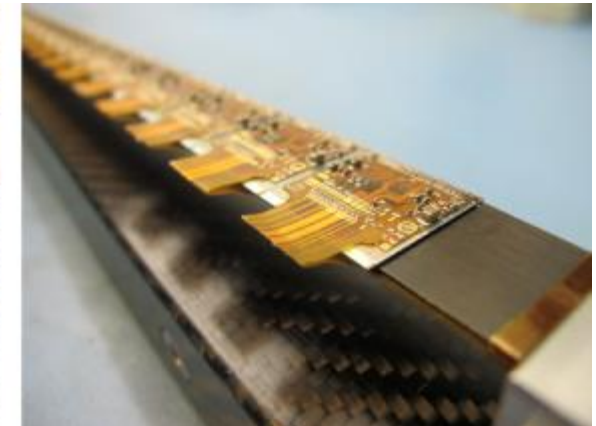


Array of narrow electrode columns ($\sim 5\text{-}10\mu\text{m}$) passing through the silicon thickness (micromachining):

- Depletion voltage prop. spacing²
 - Collection time prop. spacing
 - Reduced charge sharing
- More suited to high radiation environment

Connected to standard pixel ASIC – hybrid pixel detector

Installed 2014 in ATLAS IBL
(Inner b-layer)
&
inner pixel layers
for LHC phase II (2028)



TCAD simulations

TCAD simulations

- Why do we need TCAD simulations for understanding (irradiated) sensors ?
 - Complexity of the problem: Coupled differential equations (semiconductor equations)
 - Complex device geometry and complex signal formation in segmented devices
 - Evaluation of new and innovative design approaches
 - Impact of defects depending on local charge densities, field-strength, ... (“feedback loop”)
 - Interplay of surface and bulk damage..

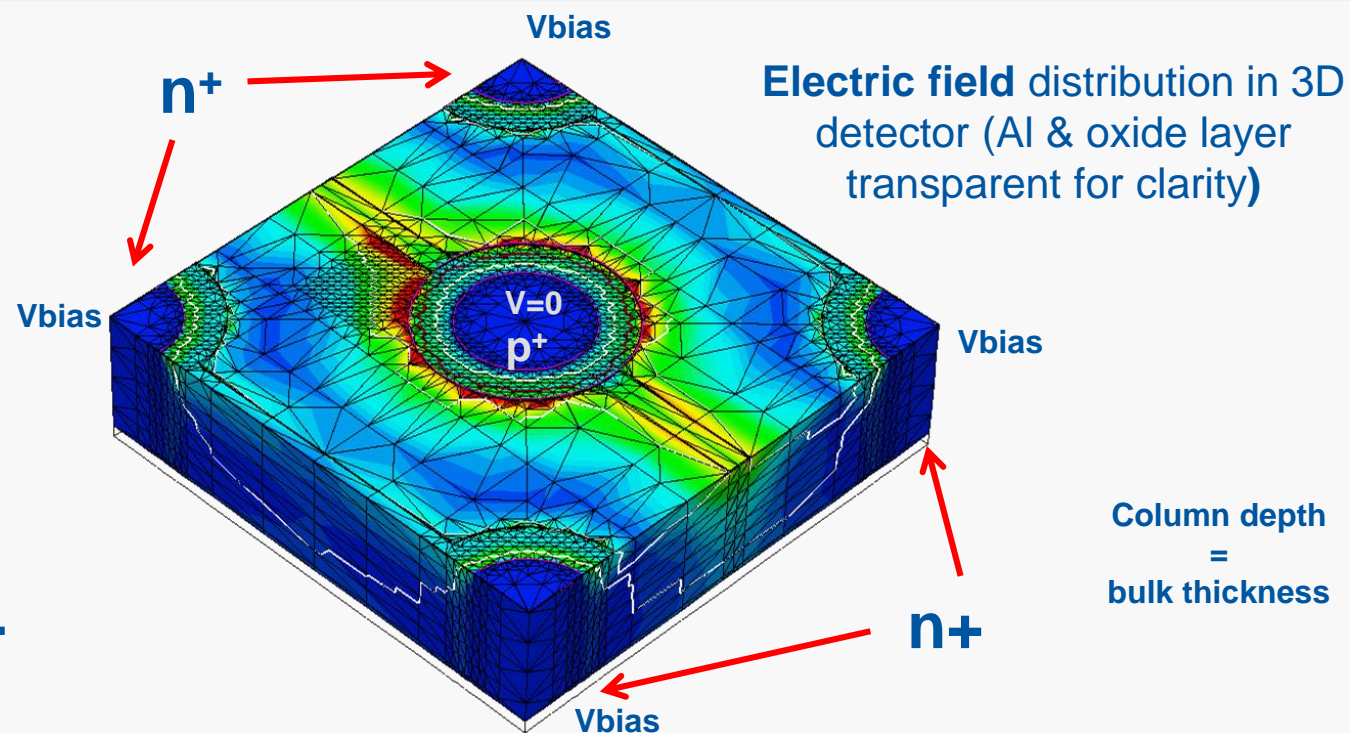
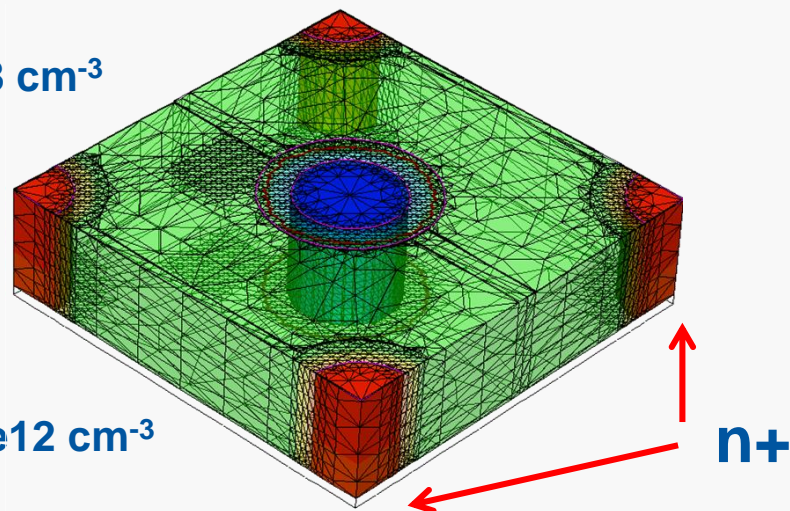
Details in the following presentations

3D detector

Doping profiles

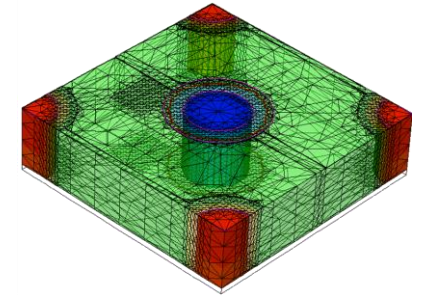
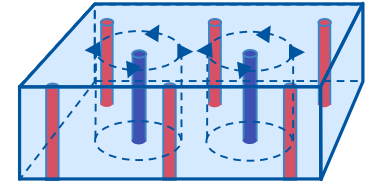
$$N_{p,n} = 5e18 \text{ cm}^{-3}$$

$$N_{\text{bulk}} = 1.7e12 \text{ cm}^{-3}$$



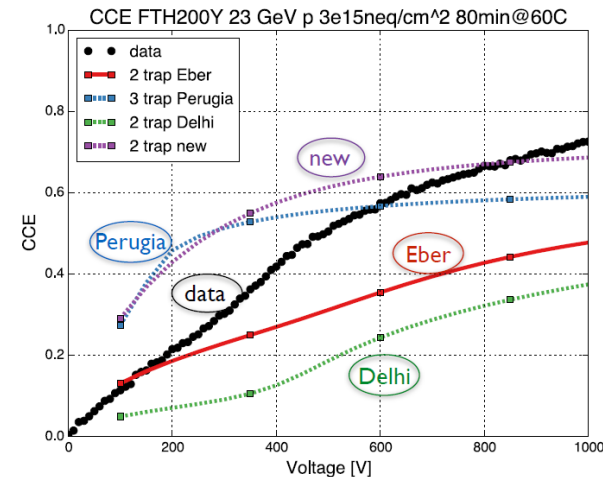
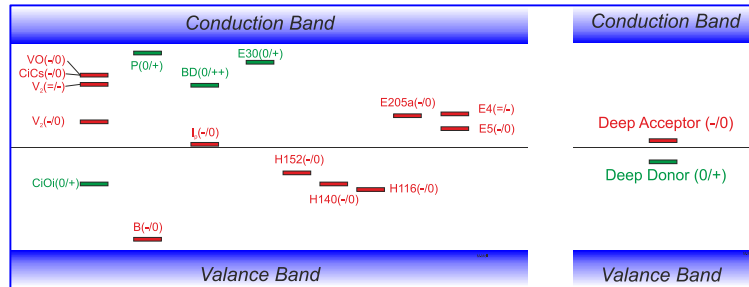
3D sensor: T.Peltola (HIP, Helsinki): CMS & RD50

Device simulation: TCAD & signal simulators



- Status of TCAD device simulations
 - Required by complexity of the problem:
 - solve semiconductor equations with physics properties, complex geometry and radiation damage
 - mainly commercial tools used (Silvaco and Synopsis)
 - Excellent tools for sensor optimization
- Radiation damage TCAD: enormous progress over recent years
 - getting predictive power but need further optimization!
 - “effective” defect levels (2 to 5 levels) are used

Measured defects → **TCAD input**



needs more work !

Signal simulators

- TCAD simulations for signal formation are complex (time consuming, TCAD is not a fitting tool!)
- Custom build signal simulators (open code) developed: sensor optimization, parameter fitting
 - ..using E-Field and other parameters (e.g. charge trapping) from TCAD as input

PixelAV, KdetSim,
Garfield++,
Weightfield2, TRACS,
(unpublished codes),
...

Summary



- **Silicon Sensors are based on reverse biased pn-junctions** (silicon sensors are reverse biased diodes)
- **Silicon Detectors at the LHC and upgrade of LHC**
 - Inner tracking at LHC and HL-LHC done by silicon detectors
 - Hybrid-pixel (planar and 3D) and strip sensors implemented in LHC experiments (ALICE upgraded to monolithic sensors)
 - Radiation Hard Monolithic sensors under development (competing beyond LS3 for HL-LHC upgrades)
- **Radiation Damage in Silicon Sensors**
 - Damage: displacement damage that is evidenced as defect levels in the band gap of the semiconductor (+ some impact of surface damage in segmented sensors)
 - **Modification of internal electric field** (space charge distribution, depletion voltage, “type inversion”, reverse annealing, loss of active volume, ...), defect engineering possible!
 - **Increase of Leakage Current** and **Charge Trapping** (same for all silicon materials)
 - **Signal to Noise ratio** is quantity to watch (material + geometry + electronics)
- **Radiation tolerant silicon sensors**
 - Several examples of successful Material and Device Engineering (mitigation strategies) oxygenation, 3D sensors, p-type (n-readout) sensors
- **“Hot topics” in R&D on radiation hard silicon sensors**
 - Sensors for timing (i.e. LGAD with intrinsic gain, acceptor removal); monolithic sensors; CMOS
 - **Reliability of TCAD simulations with defects**; characterization of damage beyond 10^{16} cm^{-2}

Acknowledgements & References



- **Most references to particular works given on the slides**
 - RD50 workshop presentations: <http://www.cern.ch/rd50/>
 - Conferences: VERTEX, PIXEL, RESMDD, ...
- **Instrumentation Schools**
 - ICFA, EDIT, ESI, CERN & DESY Summer Student Lectures
- **Books about silicon tracking detectors (and radiation damage)**
 - Helmuth Spieler, “Semiconductor Detector Systems”, Oxford University Press 2005
 - C.Leroy, P-G.Rancoita, “Silicon Solid State Devices and Radiation Detection”, World Scientific 2012
 - Frank Hartmann, “Evolution of silicon sensor technology in particle physics”, Springer 2009 & 2017
 - L.Rossi, P.Fischer, T.Rohe, N.Wermes “Pixel Detectors”, Springer, 2006
 - Gerhard Lutz, “Semiconductor radiation detectors”, Springer 1999
- **Review Articles**
 - 2018: Garcia-Sciveres and Wermes, A review of advances in pixel detectors for experiments with high rate and radiation, <https://doi.org/10.1088/1361-6633/aab064>
 - 2018: M.Moll, Displacement Damage in Silicon Detectors for High Energy Physics <https://doi.org/10.1109/TNS.2018.2819506>
- **Research collaborations and web sites**
 - CERN RD50 collaboration (<http://www.cern.ch/rd50>) - Radiation Tolerant Silicon Sensors
 - CERN RD42 collaboration – Diamond detectors
 - Inter-Experiment Working Group on Radiation Damage in Silicon Detectors (CERN)
 - ATLAS IBL, ATLAS and CMS upgrade groups

Backup Slides

29.11.2021



SIMDET 2021
4th school on silicon detectors simulation

LPNHE - Paris

November 29, December 1, 2021

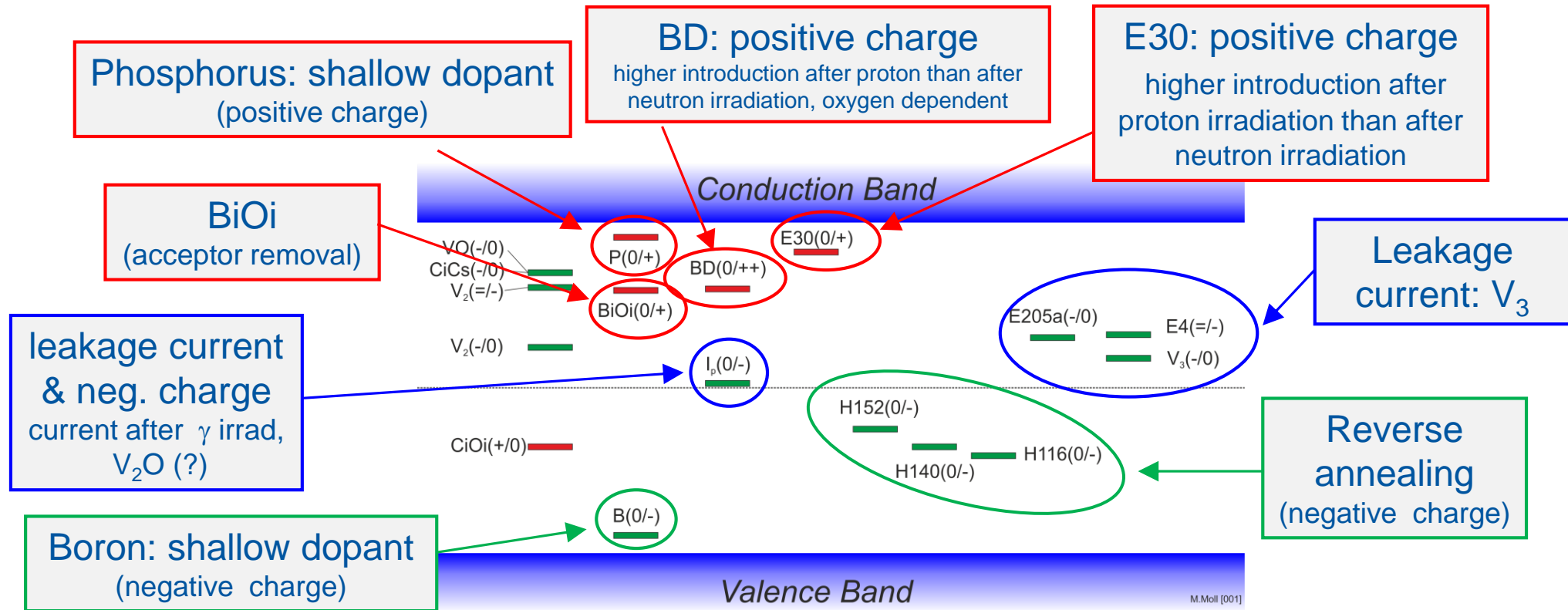
Scientific committee
BOMBEN Marco LPNHE, Paris
CALDERINI Giovanni LPNHE, Paris
CORLAT Rémi LPNHE, Paris
LAURENT Philippe, APC
LAVERGNE Laurence IRAP, Toulouse
LIMOUSIN Olivier CEA/IRFU, Saclay
LOUNIS Abdenour ICLab, Orsay
MARCHIORI Giovanni LPNHE, Paris
MOROZZI Arianna, INFN Perugia
MOLL Michael CERN, Genève
ORSINI Fabienne CEA/IRFU, Saclay
TONAZZO Alessandra APC, Paris

Local organising committee
BOMBEN Marco
CALDERINI Giovanni
CARVALHAIS Carla
CORLAT Rémi
CRESCIOLI Francesco
GUYONVARCH Pascale
LOUNIS Abdenour
MARCHIORI Giovanni
MARQUET Laurence

LPNHE Paris
CEA
SORBONNE UNIVERSITÉ
CNRS
IRAP
ICJ Lab
Laboratoire de Physique des Hautes Pressions

Radiation induced defects with impact on device performance

RD50 map of most relevant defects for device performance near room temperature:



- Trapping: Indications that E205a and H152K are important (further work needed)
- Converging on consistent set of defects observed after p, π , n, γ and e irradiation.
- Defect introduction rates are depending on particle type and energy, and some on material!

Some TCAD models from literature



TABLE II

COLLECTION (NONEXHAUSTIVE) OF RADIATION DAMAGE MODELS USED TO SIMULATE THE ELECTRIC FIELD WITHIN SILICON SENSORS AFTER HIGH FLUENCE HEAVY PARTICLE IRRADIATION (SEE TEXT). A: ACCEPTOR AND D: DONOR

Model	Type	Level [eV]	$\sigma_{e,h}$ [cm ²]	η [cm ⁻¹]	Comment	
EVL 2002 [40]	A	$E_C - 0.525$	1×10^{-15}	–	Tool: Microsoft Excel [116]	
	D	$E_V + 0.48$	1×10^{-15}	–		
	–	$E_C - 0.65^{(*)}$	1×10^{-13}	0.4	(*)level for current generation, no space charge	
Perugia 2006 [109]	A	$E_C - 0.42$	$2 \times 10^{-15}, 2 \times 10^{-14}$	1.613	Tool: Silvaco [117]	
	(p-type sensors)	A	$E_C - 0.46$	$5 \times 10^{-15}, 5 \times 10^{-14}$		0.9
	D	$E_V + 0.36$	$2.5 \times 10^{-14}, 2.5 \times 10^{-15}$	0.9		
	(n-type sensors)	A	$E_C - 0.42$	$2 \times 10^{-15}, 1.2 \times 10^{-14}$	13	
		A	$E_C - 0.50$	$5 \times 10^{-15}, 3.5 \times 10^{-14}$	0.08	
		D	$E_V + 0.36$	$2 \times 10^{-18}, 2.5 \times 10^{-15}$	1.1	
Glasgow 2008 [110]	A	$E_C - 0.42$	$9.5 \times 10^{-15}, 9.5 \times 10^{-14}$	1.613	Tool: Synopsys [118]	
	A	$E_C - 0.46$	$5 \times 10^{-15}, 5 \times 10^{-14}$	0.9	model adapted from <i>Perugia 2006</i> [109]	
	D	$E_V + 0.36$	$3.23 \times 10^{-13}, 3.23 \times 10^{-14}$	0.9	simulation of p-type 3D sensors	
KIT 2013 [111]	(protons)	A	$E_C - 0.525$	$1 \times 10^{-14}, 1 \times 10^{-14}$	–	Tool: Synopsys [118] $\eta_A = 1.189 \text{ cm}^{-1} \times \phi - 6.454 \times 10^{13} \text{ cm}^{-3}$
		D	$E_V + 0.48$	$1 \times 10^{-14}, 1 \times 10^{-14}$	–	
	(neutrons)	A	$E_C - 0.525$	$1.2 \times 10^{-14}, 1.2 \times 10^{-14}$	1.55	
		D	$E_V + 0.48$	$1.2 \times 10^{-14}, 1.2 \times 10^{-14}$	1.395	
	Delhi 2014 [112]	A	$E_C - 0.51$	$2 \times 10^{-14}, 2.6 \times 10^{-14}$	4	Tool: Silvaco [117]
		D	$E_V + 0.48$	2×10^{-14}	3	
Perugia 2016 [113]	A	$E_C - 0.42$	$1 \times 10^{-15}, 1 \times 10^{-14}$	1.613	improving <i>Perugia 2006</i> [109] $\phi_{eq} \leq 7 \times 10^{15} \text{ cm}^{-2}$ $7 \times 10^{15} \text{ cm}^{-2} \leq \phi_{eq} \leq 1.5 \times 10^{16} \text{ cm}^{-2}$ $1.5 \times 10^{16} \text{ cm}^{-2} \leq \phi_{eq} \leq 2.2 \times 10^{16} \text{ cm}^{-2}$	
	(p-type sensors)	A	$E_C - 0.46$	$7 \times 10^{-15}, 7 \times 10^{-14}$		0.9
	–	–	$3 \times 10^{-15}, 3 \times 10^{-14}$	–		
	–	–	$1.5 \times 10^{-15}, 1.5 \times 10^{-14}$	–		
	D	$E_V + 0.36$	$3.23 \times 10^{-13}, 3.23 \times 10^{-14}$	0.9		

• Several models available (non exhaustive list):

Table: *M.Moll, Displacement Damage in Silicon Detectors*, doi.org/10.1109/TNS.2018.2819506

Macroscopic Damage

Degradation of Detector Performance

Summary: Basics of Radiation Damage in Silicon Sensors



■ Two general types of radiation damage to the detector materials:

- **Bulk (Crystal) damage due to Non Ionizing Energy Loss (NIEL)**
 - displacement damage, built up of crystal defects –
 - I.** Change of **effective doping concentration & acceptor/donor removal** (higher depletion voltage, under- depletion)
 - II.** Increase of **leakage current** (increase of shot noise, thermal runaway)
 - III.** Increase of **charge carrier trapping** (loss of charge)
- **Surface damage due to Ionizing Energy Loss (IEL)**
 - accumulation of positive in the oxide (SiO_2) and the Si/SiO_2 interface –
 - affects: interstrip capacitance (noise factor), breakdown behavior, ...

Influenced
by impurities
in Si – **Defect
Engineering
is possible!**

Same for
all tested
Silicon

materials!

■ **Impact on detector performance and Charge Collection Efficiency** (depending on detector type and geometry and readout electronics!)

Signal/noise ratio is the quantity to watch

⇒ Sensors can fail from radiation damage !

**Can be
optimized!**

How to increase the radiation hardness?

Approaches to develop radiation harder solid state tracking detectors



• Defect Engineering of Silicon

Deliberate incorporation of impurities or defects into the silicon bulk to improve radiation tolerance of detectors

- **Needs:** Profound understanding of radiation damage
 - microscopic defects, macroscopic parameters
 - dependence on particle type and energy
 - defect formation kinetics and annealing
- **Examples:**
 - **Oxygen rich Silicon (DOFZ, Cz, MCZ, EPI)**
 - Oxygen dimer & hydrogen enriched Si
 - Pre-irradiated Si
 - Influence of processing technology

• New Materials

- Silicon Carbide (SiC), Gallium Nitride (GaN)
- Diamond (CERN RD42 Collaboration)
- Amorphous silicon, Gallium Arsenide

• Device Engineering (New Detector Designs)

- p-type silicon detectors (n-in-p)
- thin detectors, epitaxial detectors
- 3D detectors and LGAD - Low Gain Avalanche
- Cost effective detectors
- Monolithic devices – HV-CMOS

CERN-RD39 (closed, now part of RD50)
“Cryogenic Tracking Detectors”
operation at 100-200K to reduce charge loss

SIMDET 2021

4th school on silicon detectors simulation

LPNHE - Paris

November 29, December 1, 2021

Scientific committee

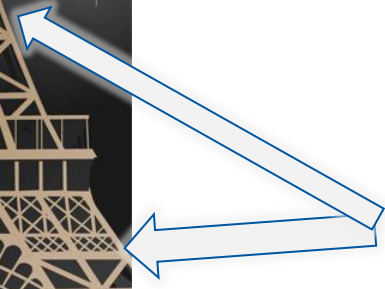
BOMBEN Marco LPNHE, Paris
CALDERINI Giovanni LPNHE, Paris
CORNAT Rémi LPNHE, Paris
LAURENT Philippe, APC
LAVERGNE Laurence IRAP, Toulouse
LIMOUSIN Olivier CEA/IRFU, Saclay
LOUNIS Abdenour IJCLab, Orsay
MARCHIORI Giovanni LPNHE, Paris
MOROZZI Arianna, INFN Perugia
MOLL Michael CERN, Genève
ORSINI Fabienne CEA/IRFU, Saclay
TONAZZO Alessandra APC, Paris

Local organising committee

BOMBEN Marco
CALDERINI Giovanni
CARVALHAIS Carla
CORNAT Rémi
CRESCIOLI Francesco
GUYONVARCH Pascale
LOUNIS Abdenour
MARCHIORI Giovanni
MARQUET Laurence



The END



P.S.: Take care of your meshing.
Very important to have the right
granularity at the right place.